

TCAD simulations of LGAD devices using Silvaco software

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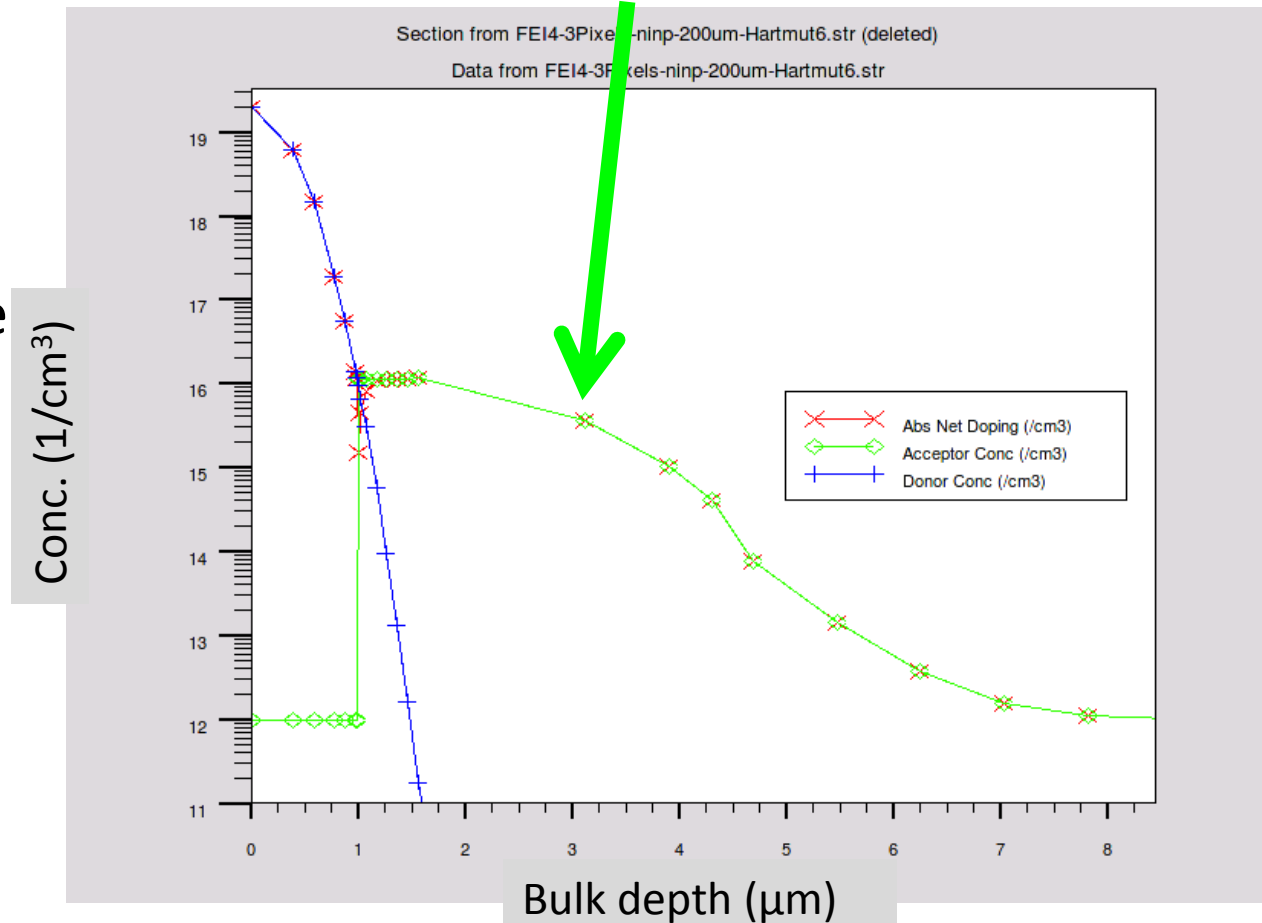


Outline

- Simulated structure & doping profile
- CV & Electric field
- Simulation of alpha particles hitting from the backside
- Simulation of MIPs hitting from the frontside
- Comments & conclusion

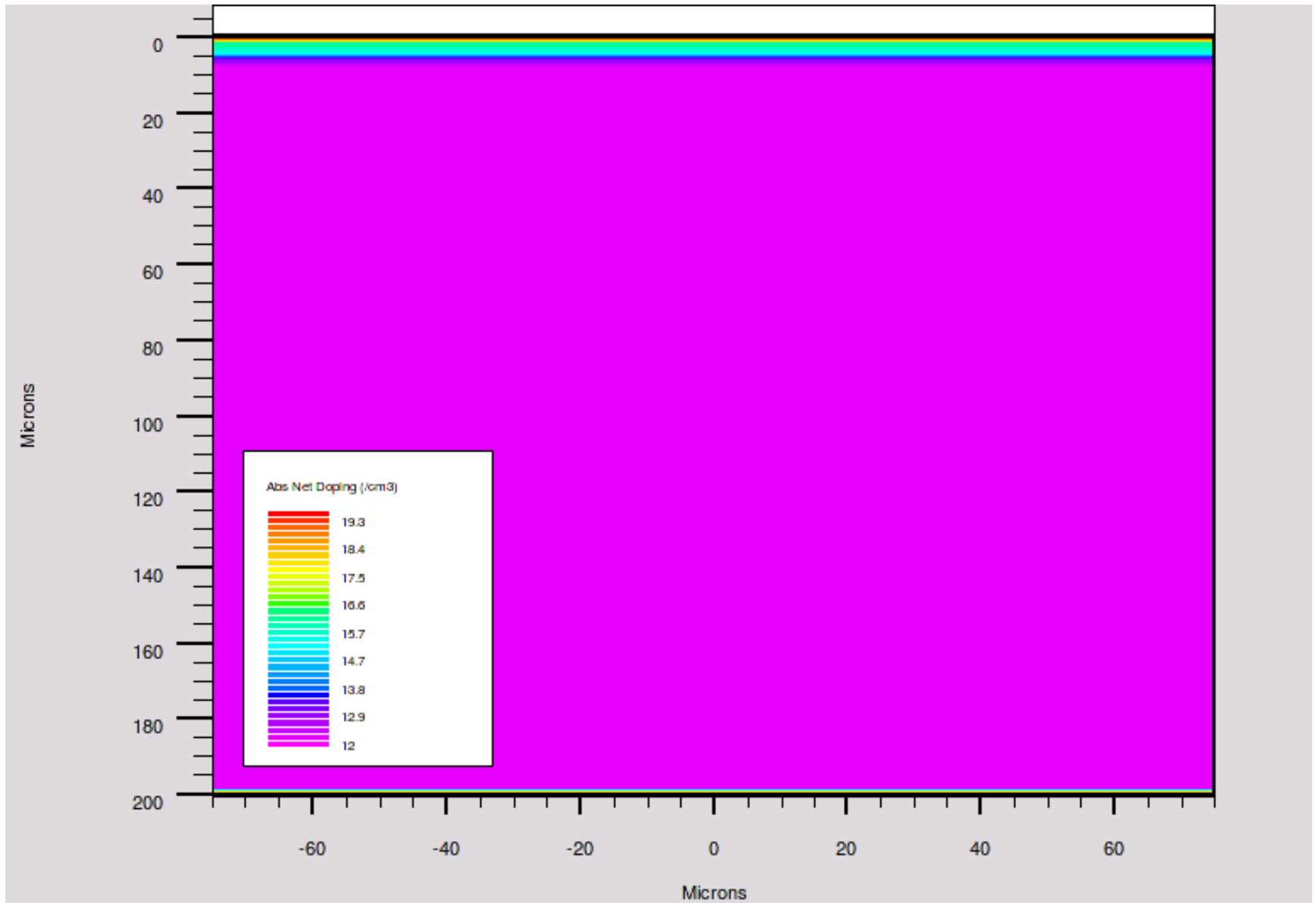
Simulated structure & doping profile

- 2D simulation of a 200 μm thick n-on-p diode, 150 μm wide
- Bulk doping conc. = $1 \times 10^{12} / \text{cm}^3$
- 2 versions studied: with and without multiplication implant
- Profile from real data*
- Peak @ 1 μm
- Plateau 0.5 μm wide

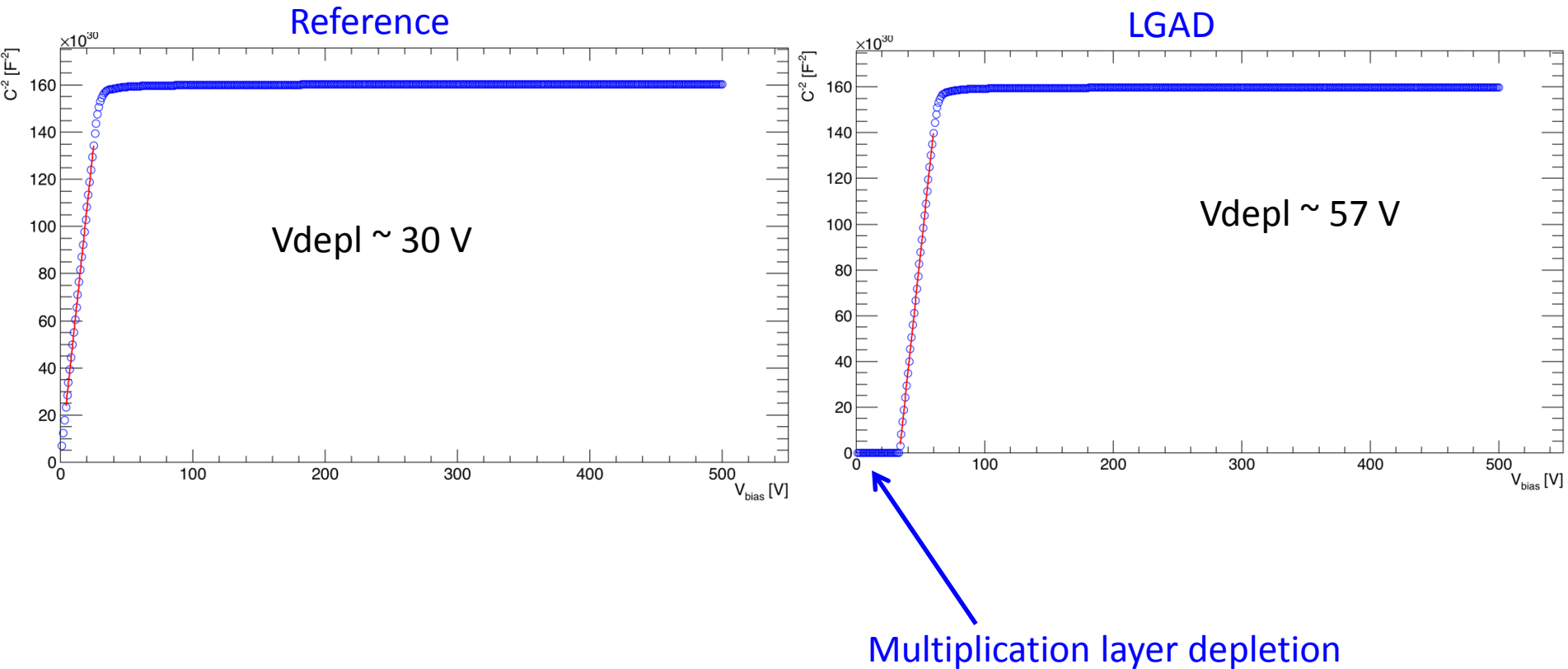


* Profile provided by H. Sadrozinski (from CV on a low-gain diode)

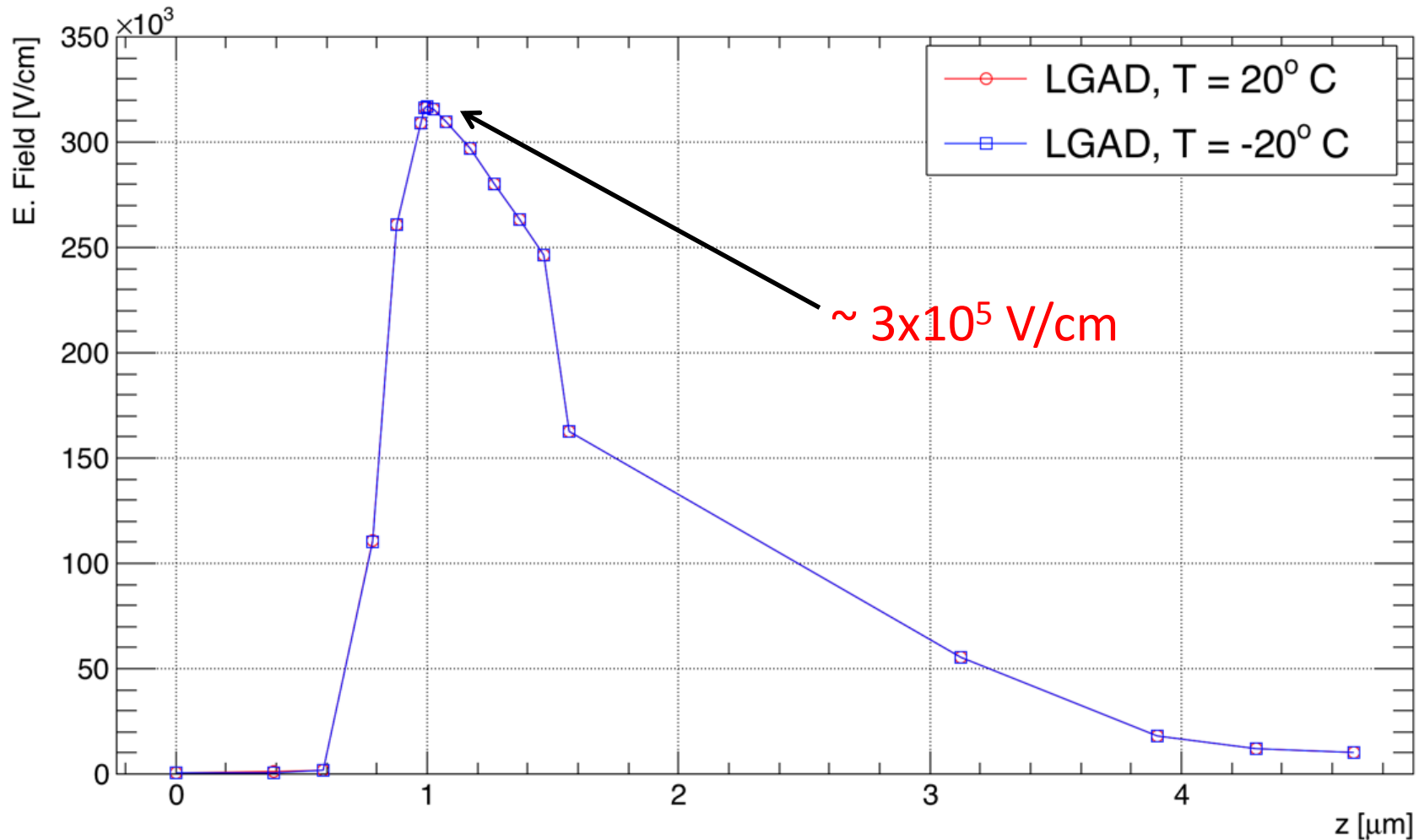
The 2D simulated structure



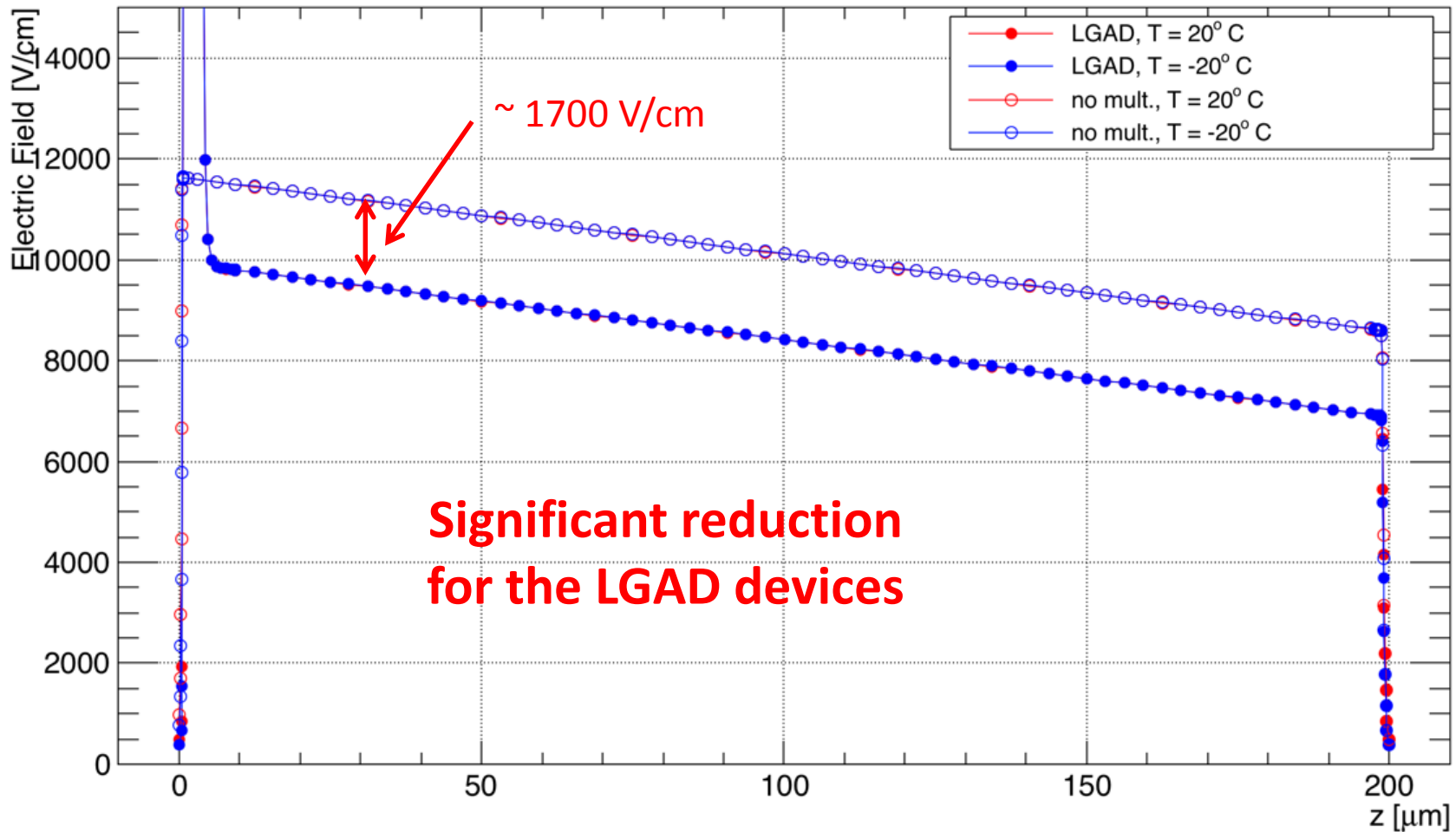
Depletion voltage, reference vs LGAD



Electric field – mult. zone



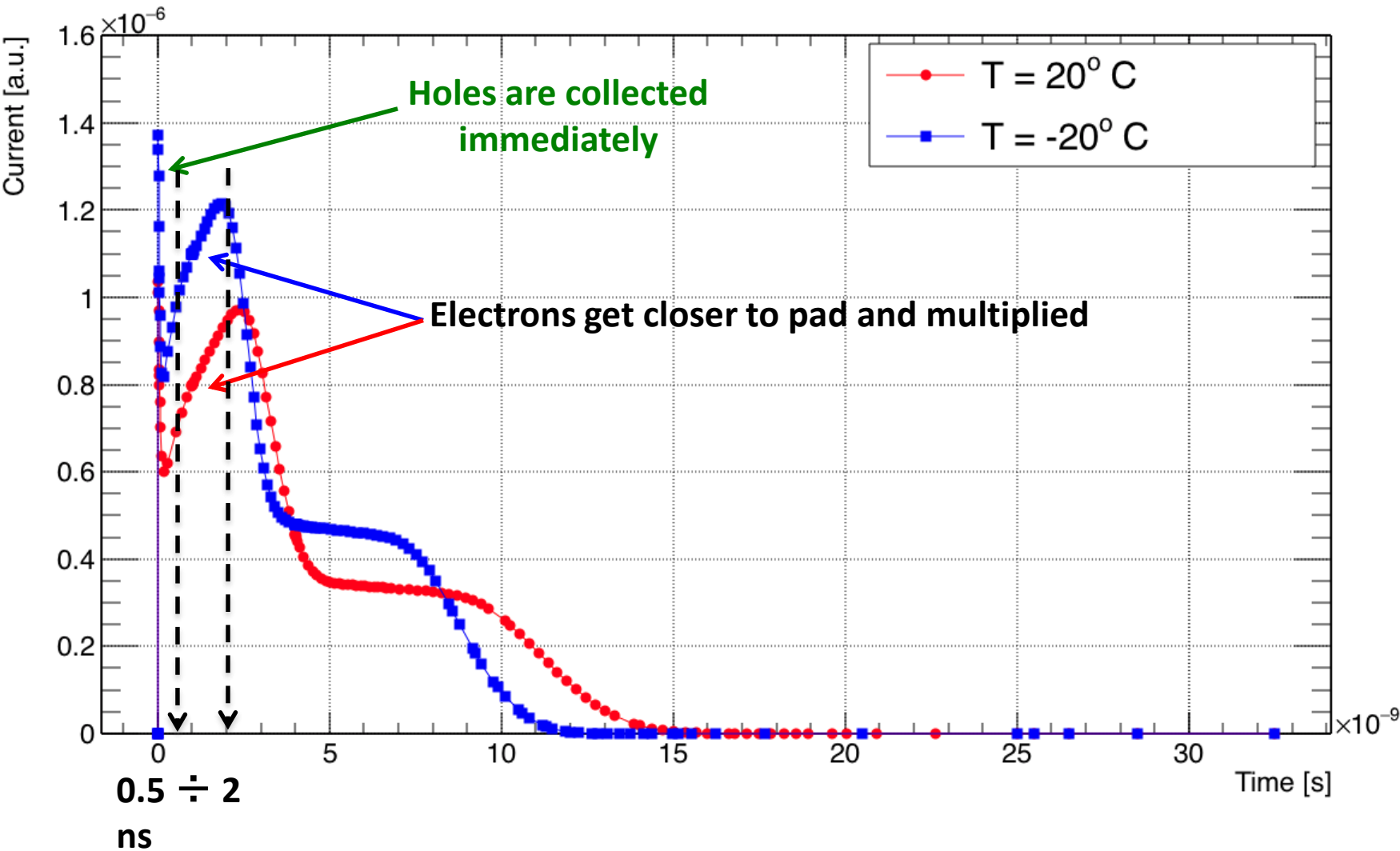
Electric field – bulk



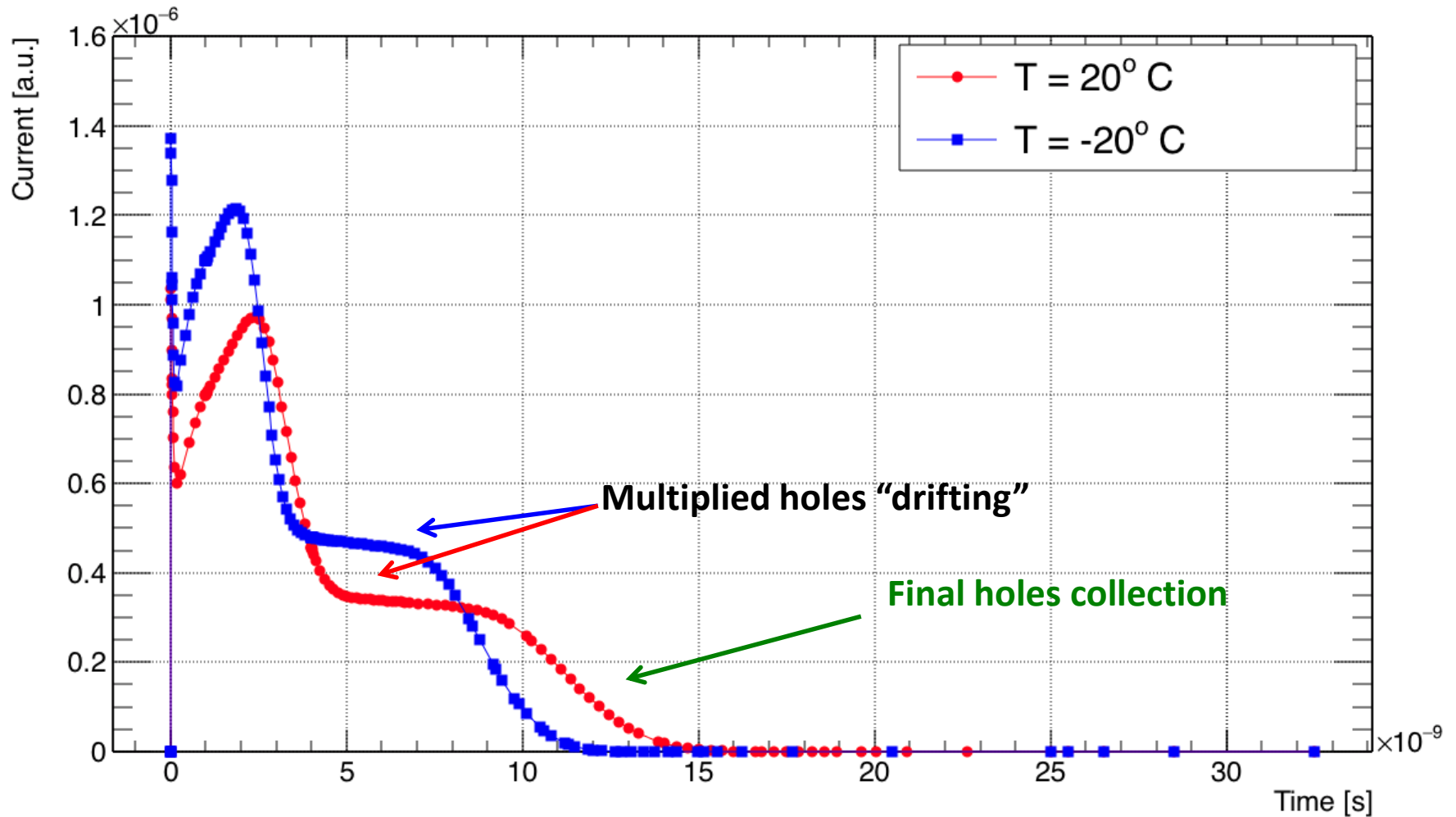
Alpha's simulations

- Alpha impinging from the back
 - Range: 5 μm
 - Energy ~ 1 MIP in 200 μm
- 200 μm thick devices
- $V_{\text{bias}} = 50, 100, 150 \text{ \& } 200 \text{ V}$
- $\Phi = 0$
- $T = \text{from } -35^\circ \text{ C to } +20^\circ \text{ C}$
- Observables: signal, electric field and gain

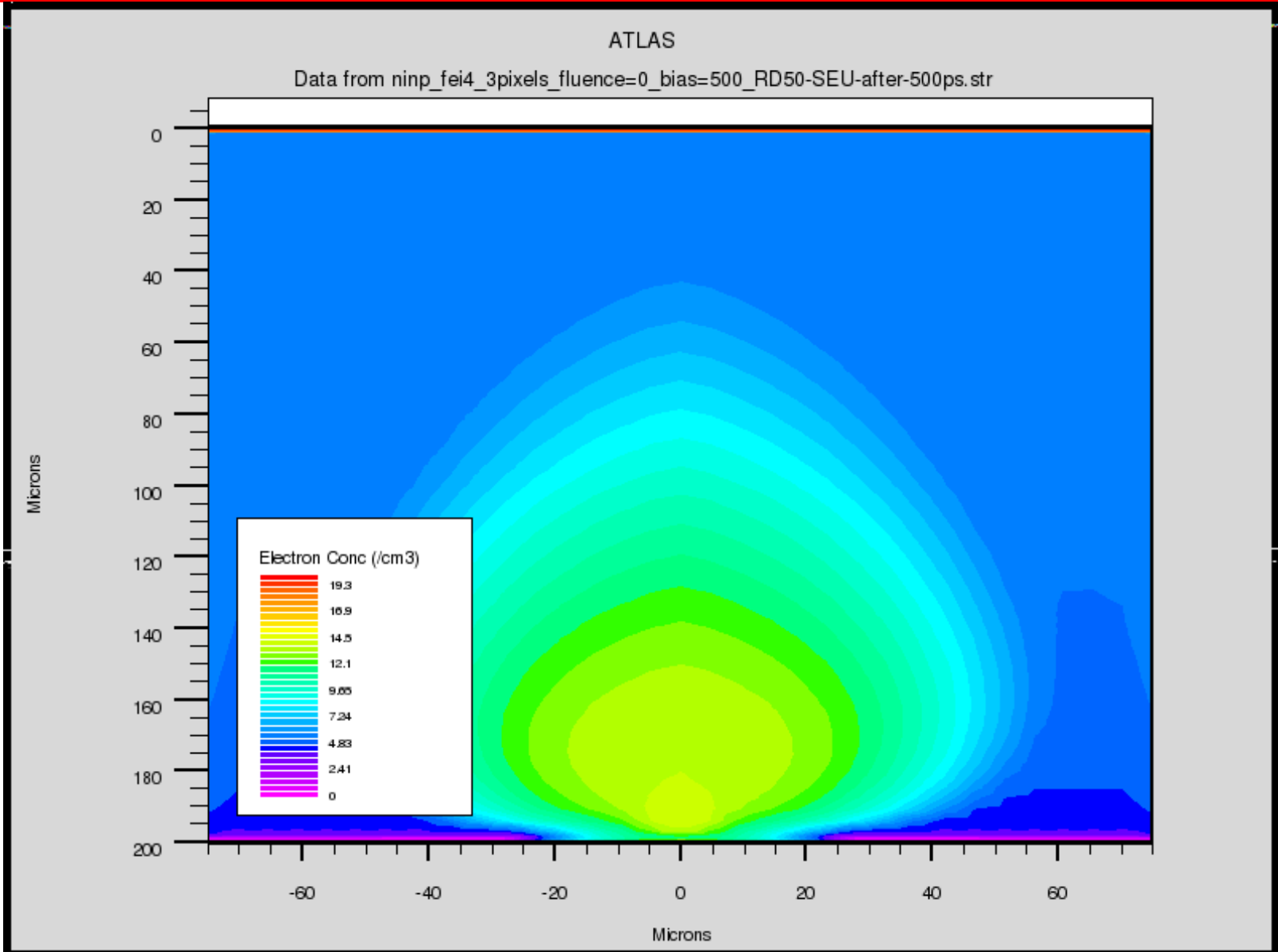
Signal, $V = 150\text{ V}$



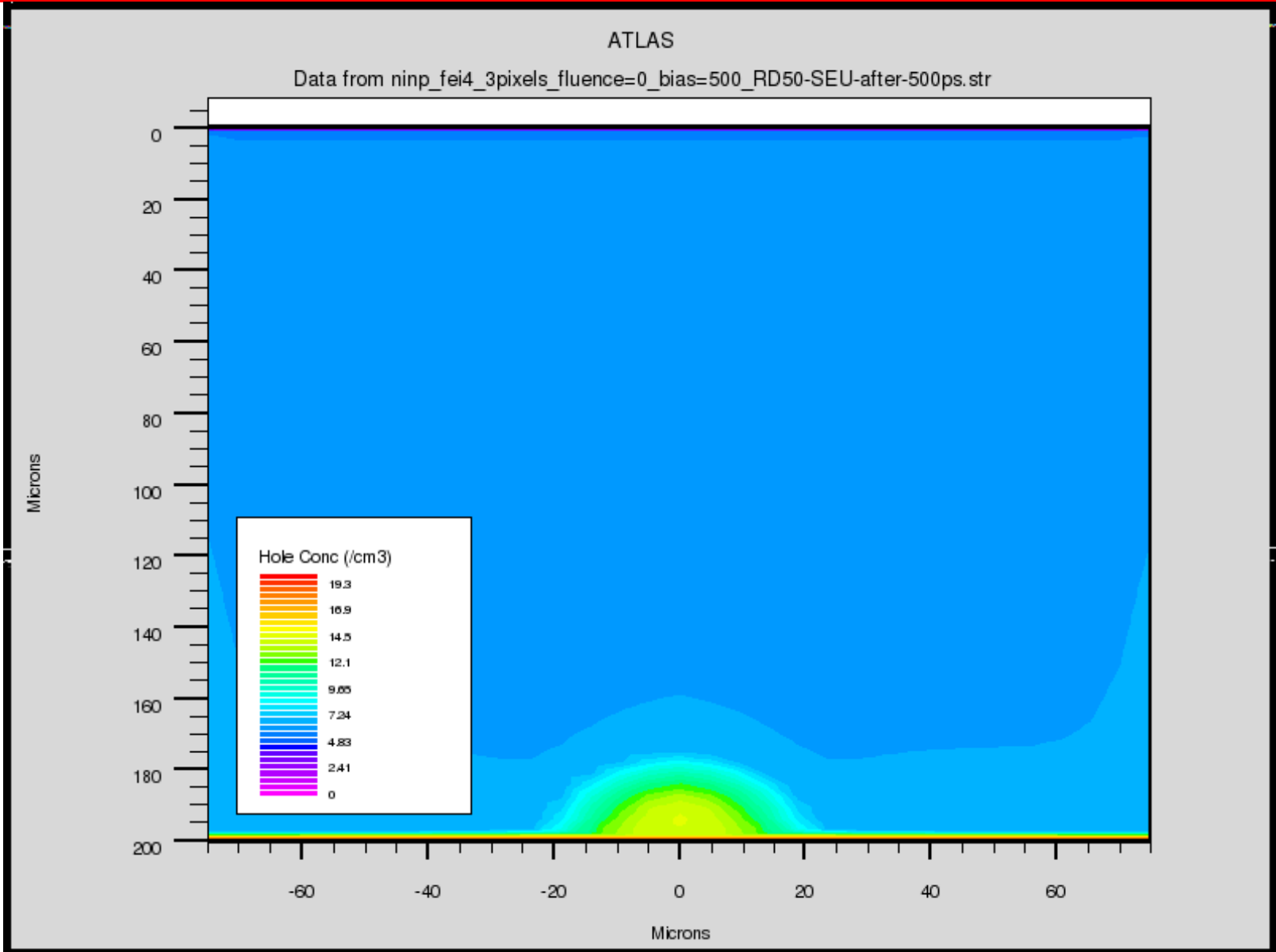
Signal, $V = 150\text{ V}$



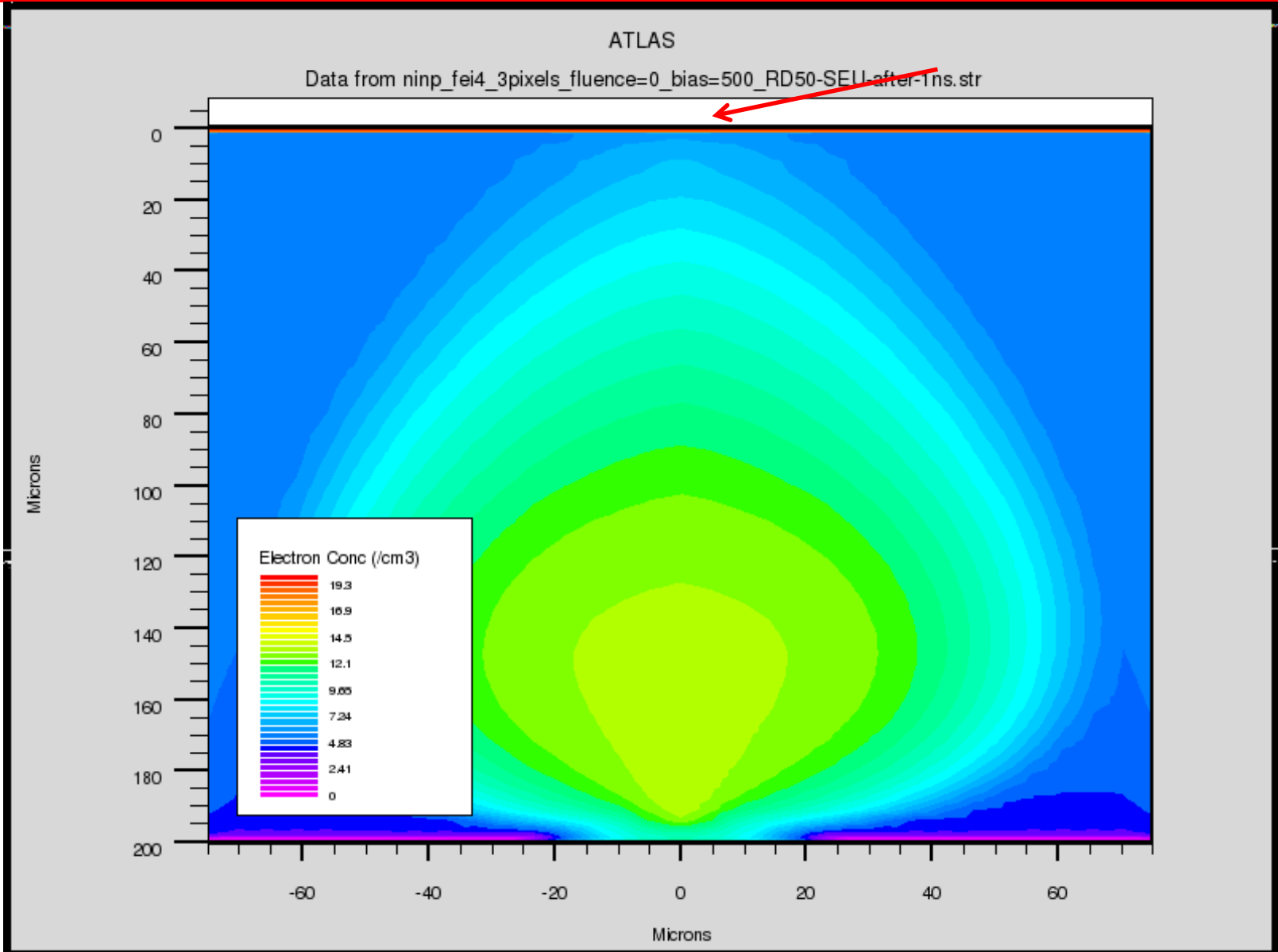
Elec. Conc. – 150 V, 500 ps after particle strike



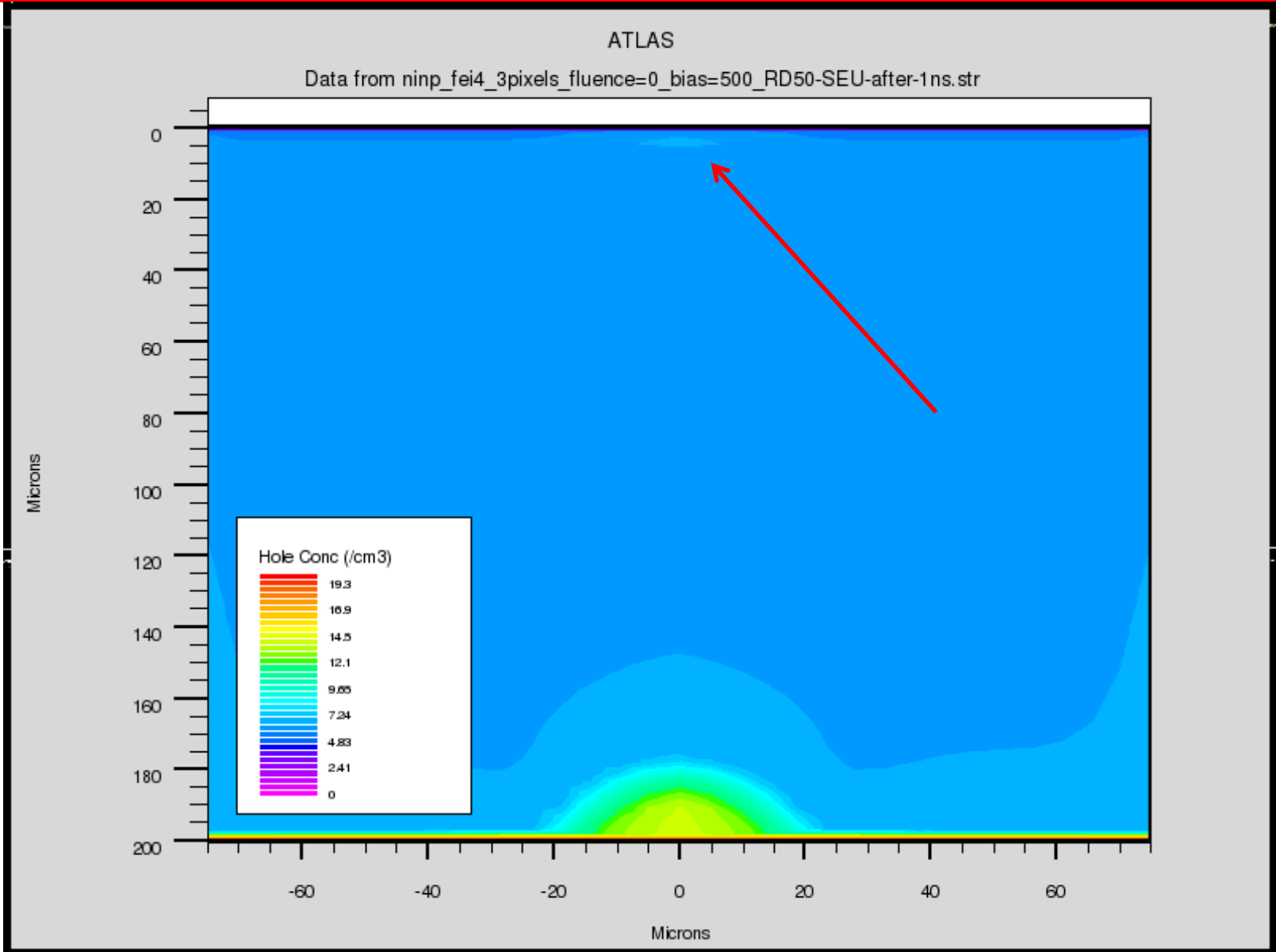
Hole Conc. – 150 V, 500 ps after particle strike



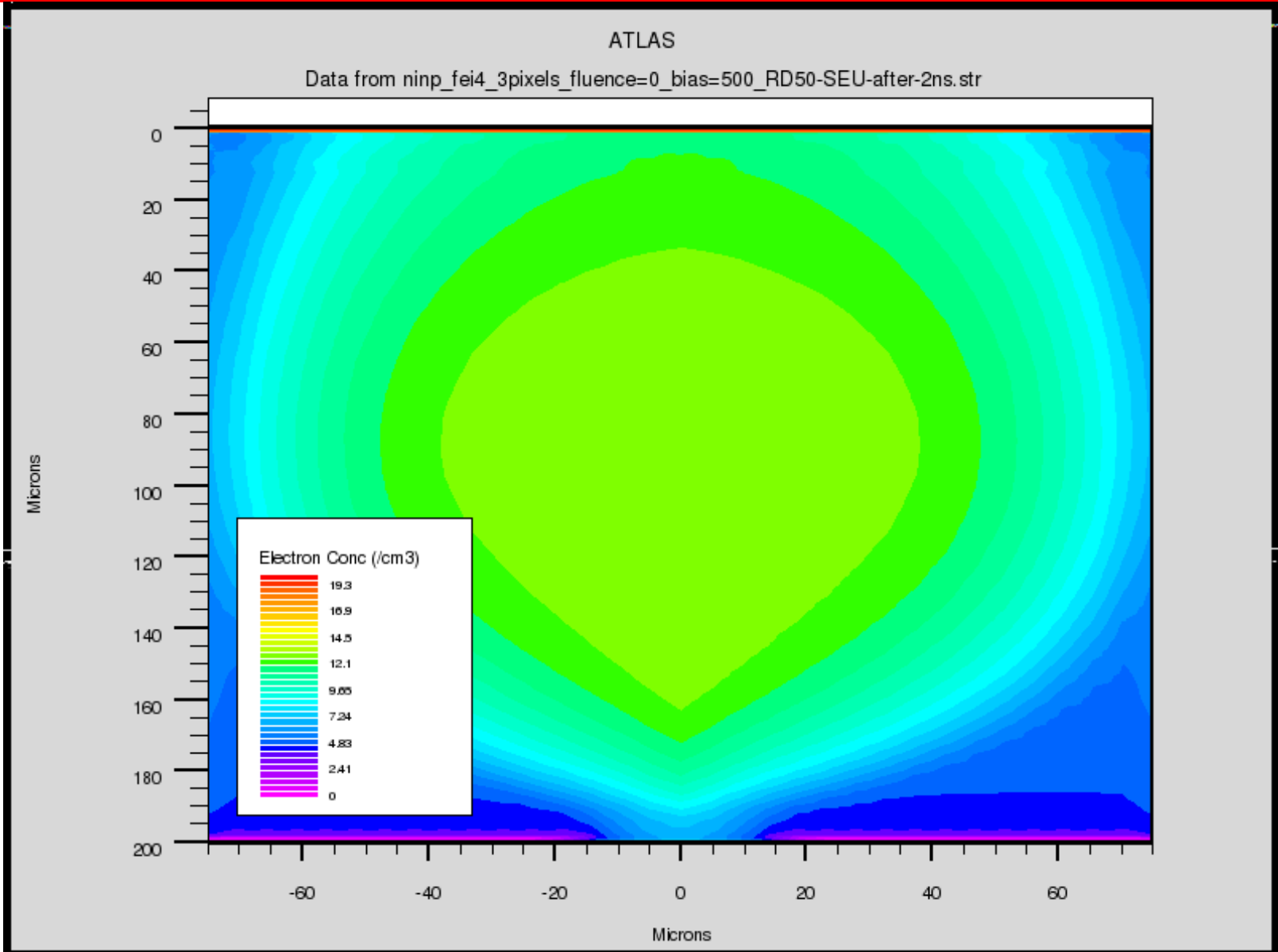
Elec. Conc. – 150 V, 1 ns after particle strike



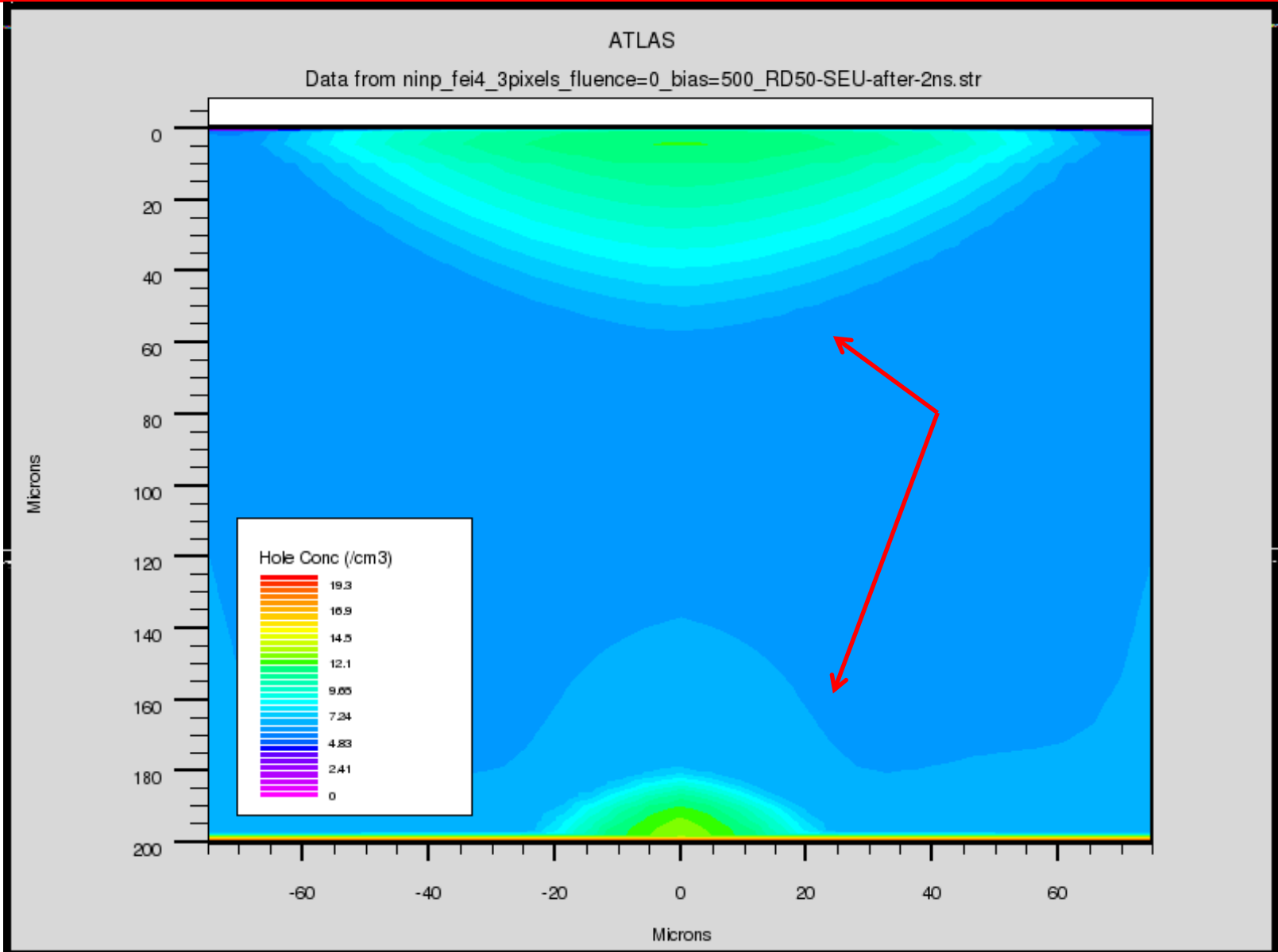
Hole Conc. – 150 V, 1 ns after particle strike



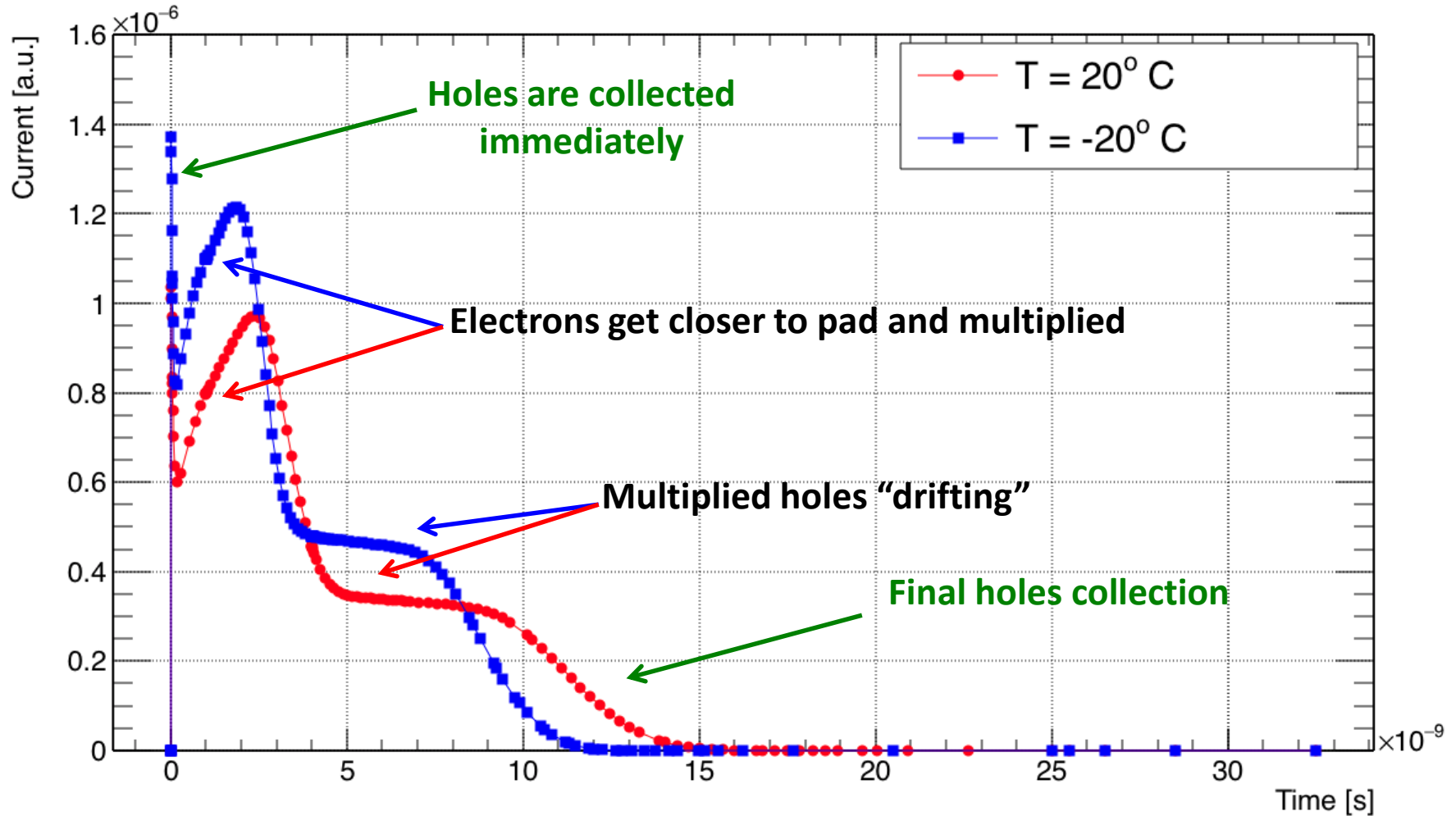
Elec. Conc. – 150 V, 2 ns after particle strike



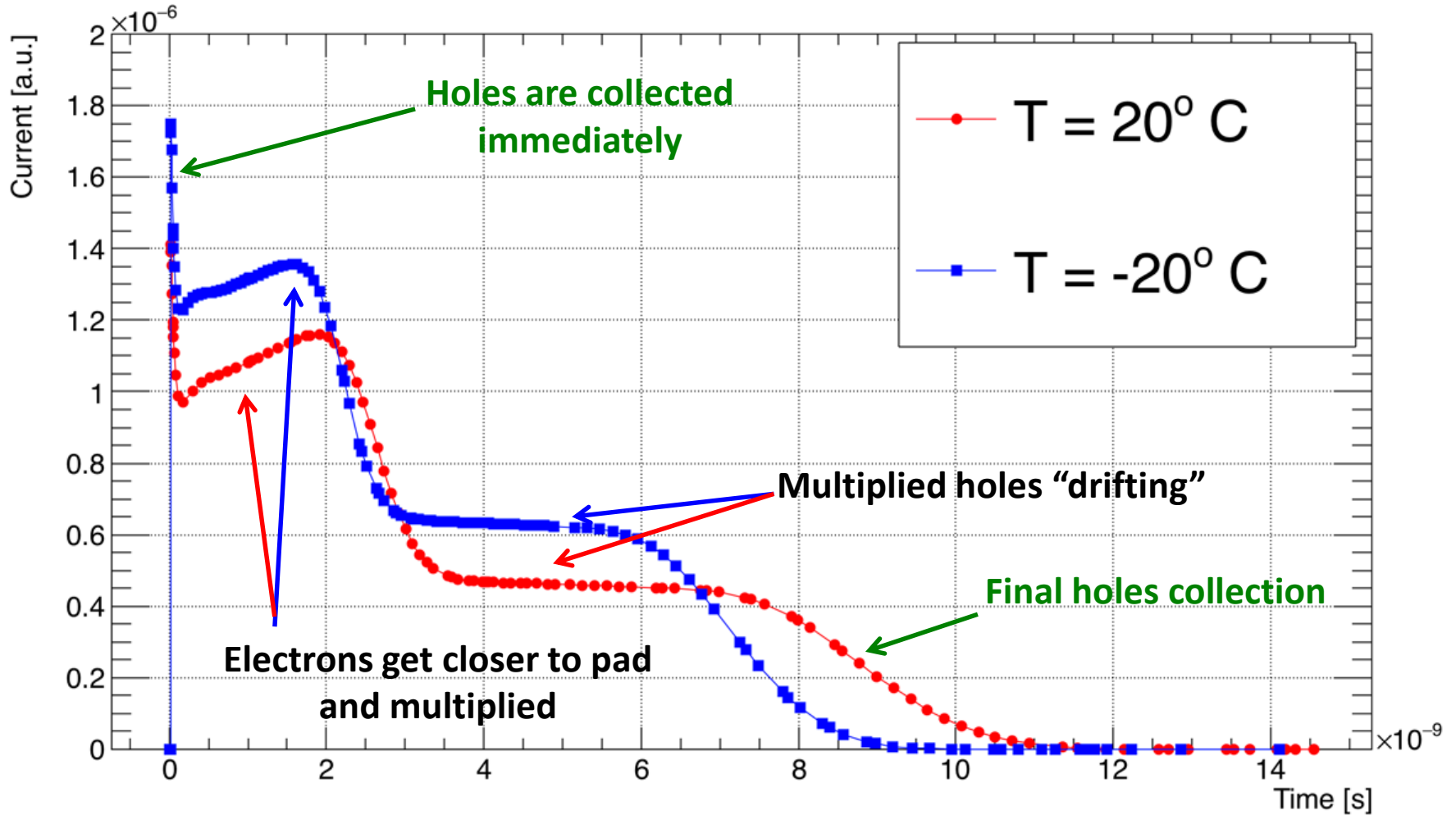
Hole Conc. – 150 V, 2 ns after particle strike



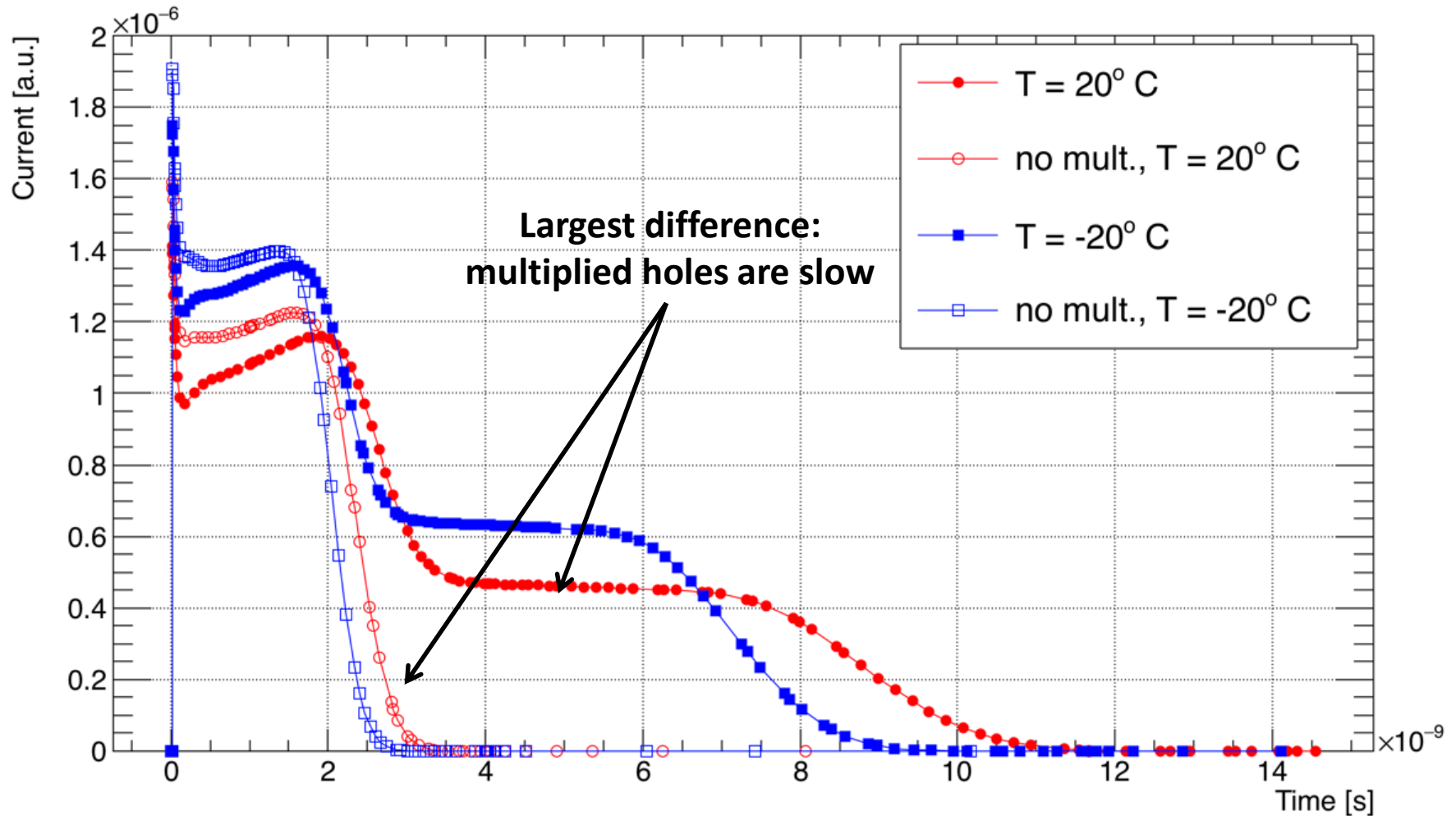
Signal, $V = 150$ V



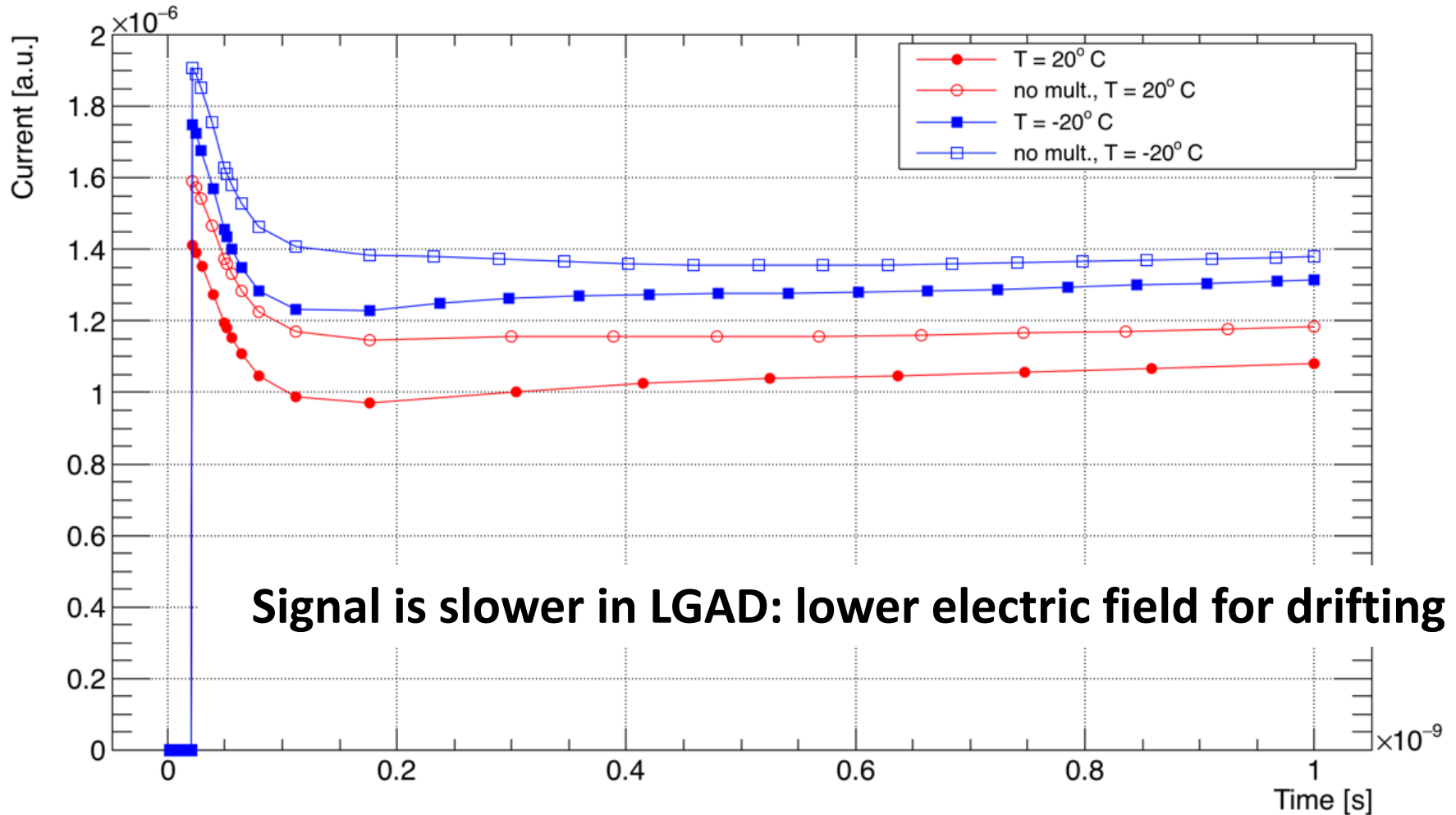
Signal, $V = 200\text{ V}$



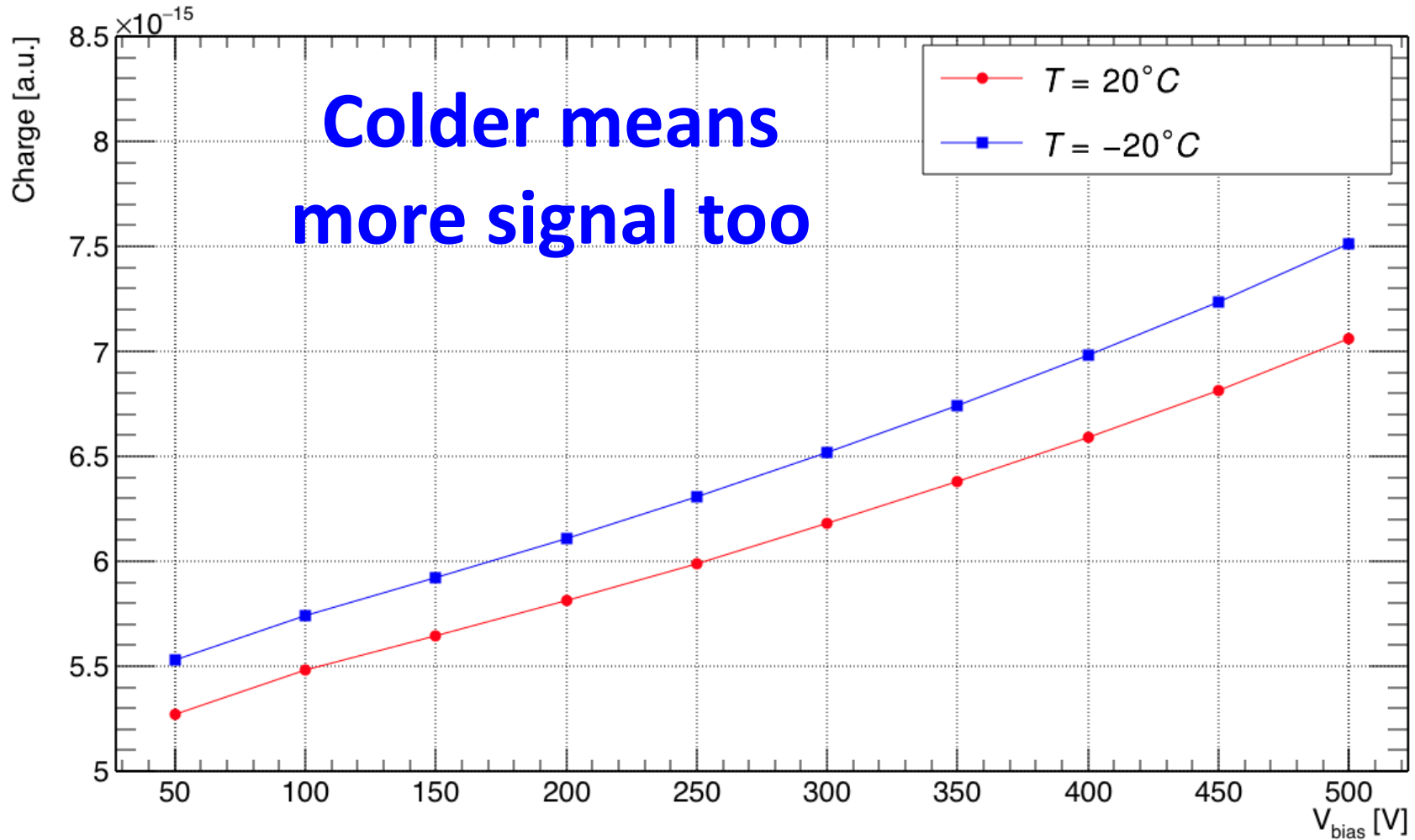
LGAD vs reference – 200 V



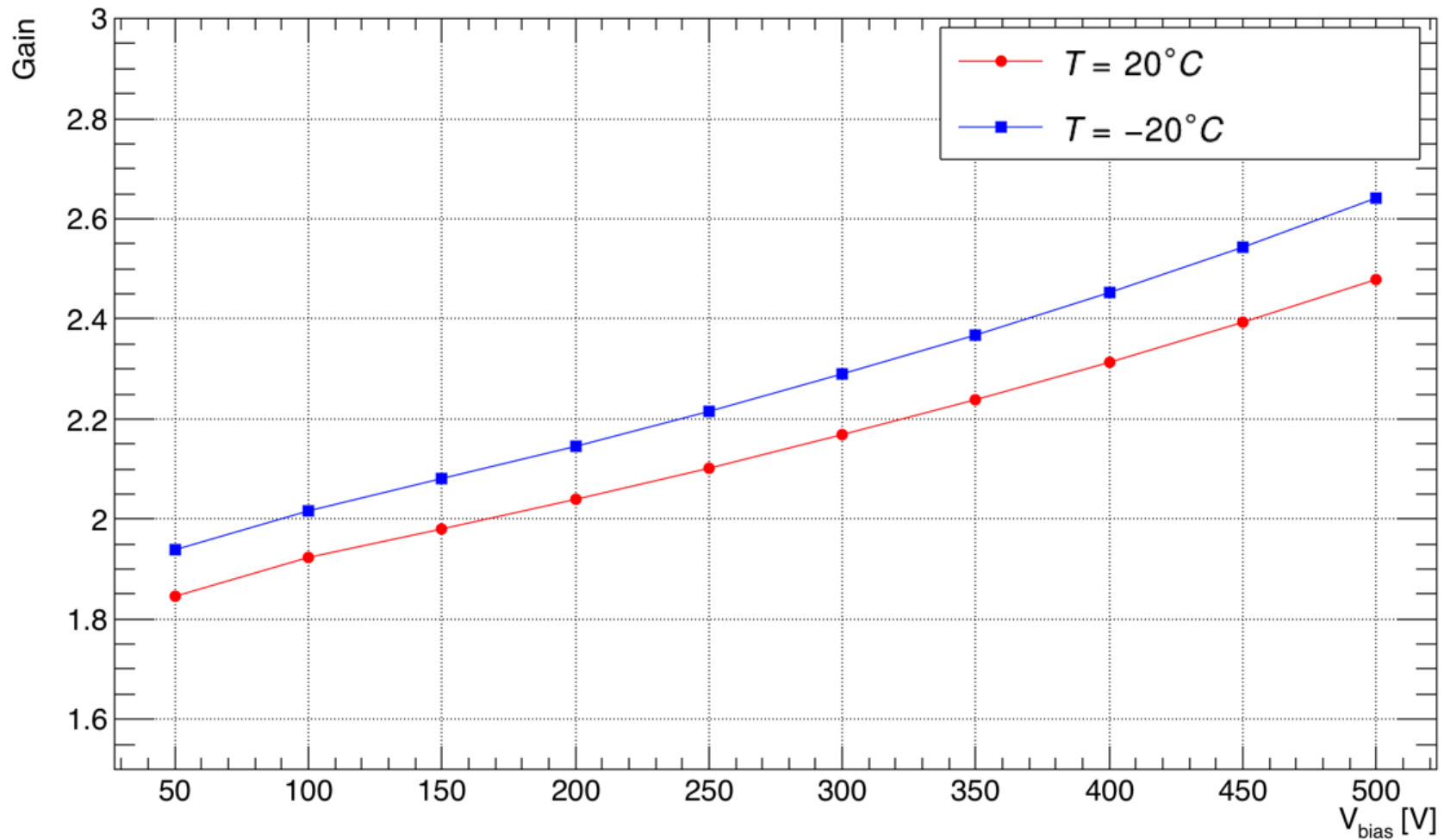
LGAD vs reference – 200 V - zoom



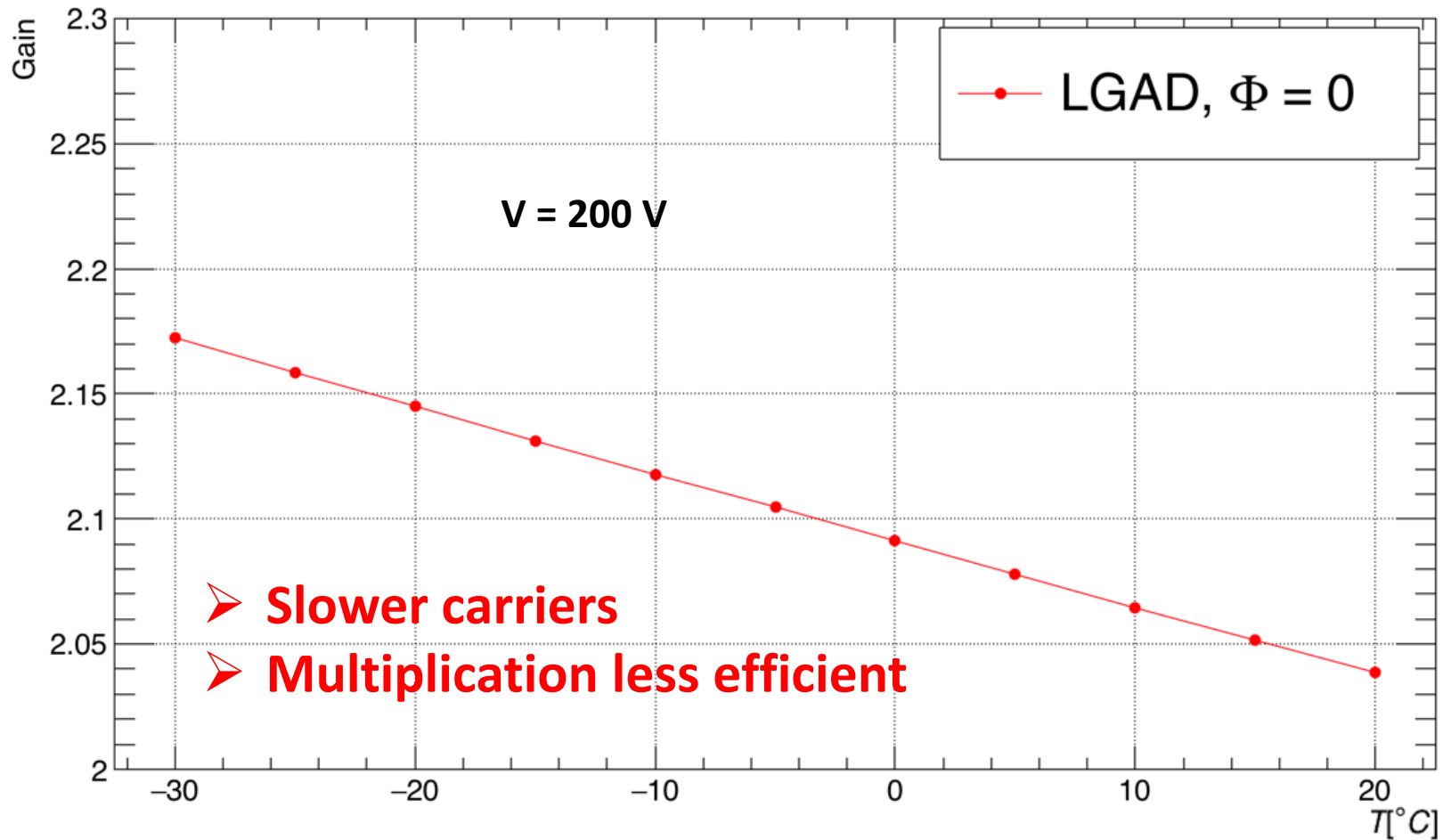
Charge: comparison



Gain for Fluence = 0



Gain vs temperature



MIPs simulations

- MIP impinging from the front
- 50, 100, 200 & 300 μm thick devices
- $V_{\text{bias}} =$ from 50 to 1000 V
- $\Phi = 0, 1 \times 10^{15}, 3 \times 10^{15} \text{ \& } 1 \times 10^{16}$
 - Model: Moscatelli et al. 2015 – NSS 2015
 - and Passeri et al. 2015 - Nucl. Instr. Meth. A (in press)
 - Bulk damage only (*N.B.* no acceptor removal, only trapping)
- Observables: signal, IV, electric field and gain

Modeling of radiation damage effects in silicon detectors at high fluences HL-LHC with Sentaurus TCAD

D. Passeri^{a,b,*}, F. Moscatelli^{c,b}, A. Morozzi^{a,b}, G.M. Bilei^b

Table 1

Parameters for fluences up to 7×10^{15} n/cm².

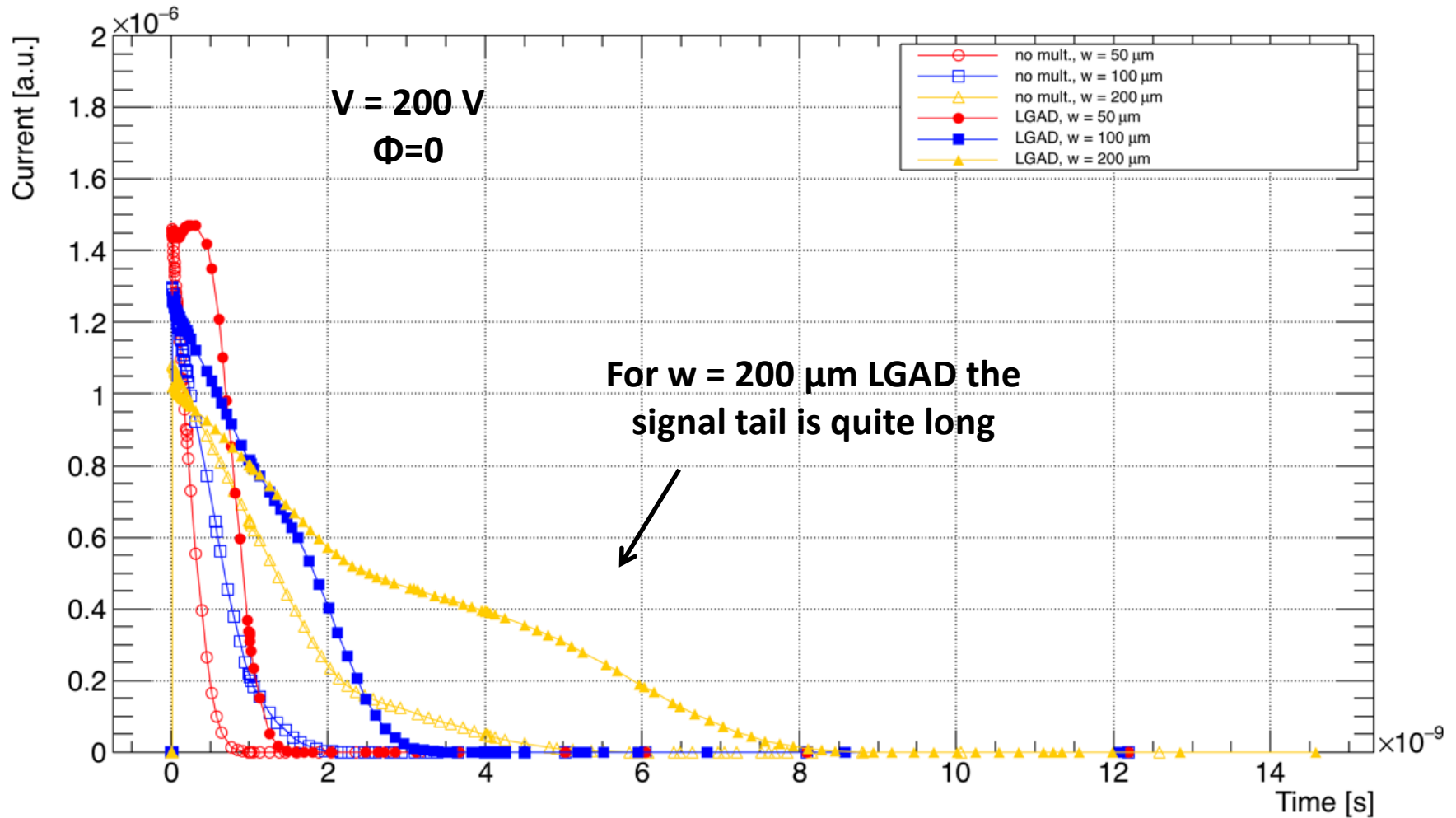
Defect	E (eV)	σ_e (cm ⁻²)	σ_n (cm ⁻²)	η
Acceptor	$E_c - 0.42$	1.00×10^{-15}	1.00×10^{-14}	1.6
Acceptor	$E_c - 0.46$	7.00×10^{-15}	7.00×10^{-14}	0.9
Donor	$E_v + 0.36$	3.23×10^{-13}	3.23×10^{-14}	0.9

Table 2

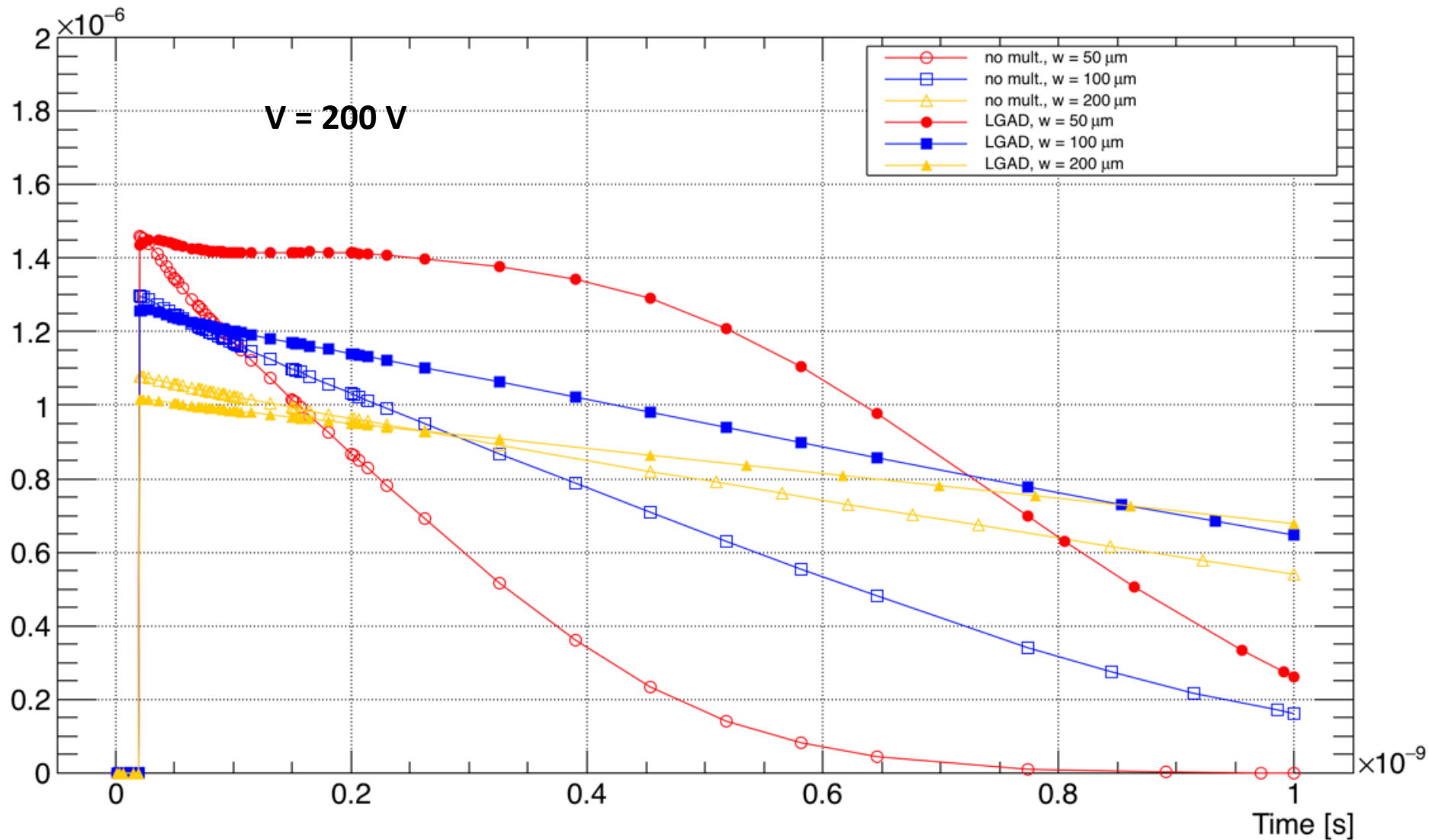
Parameters for fluences within 7×10^{15} n/cm² and 2.2×10^{16} n/cm².

Defect	E (eV)	σ_e (cm ⁻²)	σ_n (cm ⁻²)	η
Acceptor	$E_c - 0.42$	1.00×10^{-15}	1.00×10^{-14}	1.6
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Donor	$E_v + 0.36$	3.23×10^{-13}	3.23×10^{-14}	0.9

Signal vs time, different thicknesses – 200 V

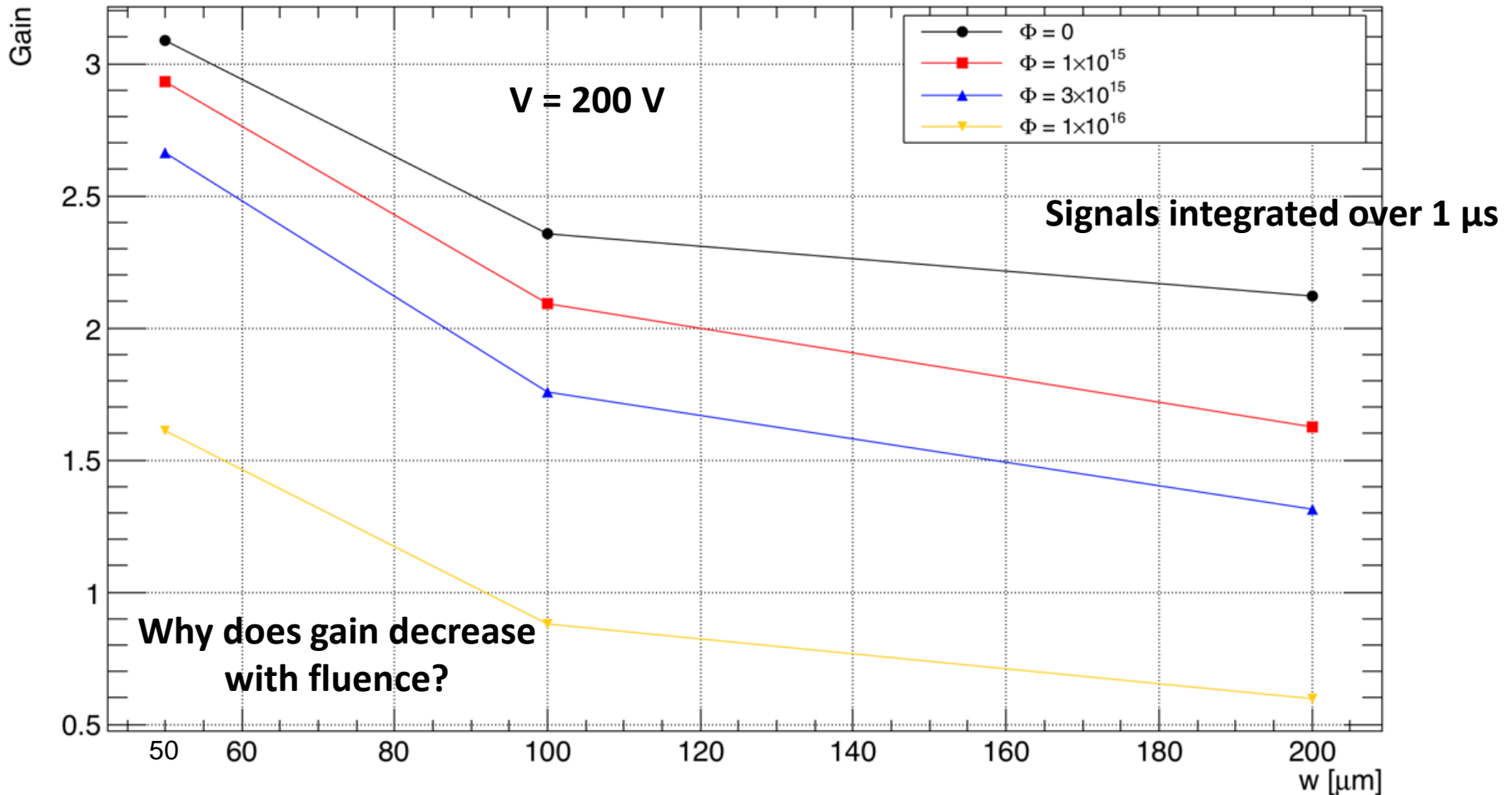


Signal of irr. samples – $\Phi = 1 \times 10^{15}$



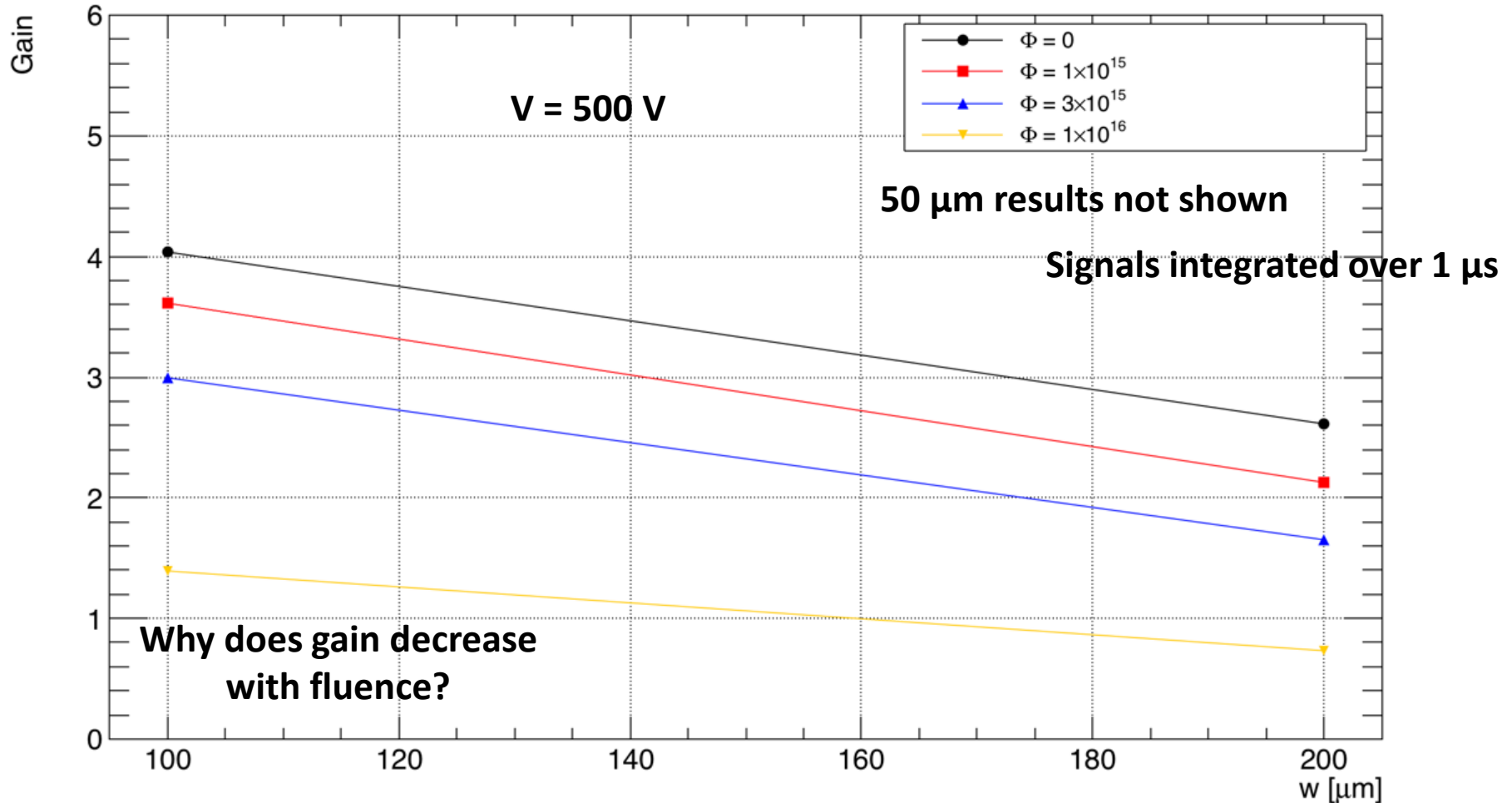
Gain vs different thicknesses – 200 V

Gain = charge normalised to a non-LGAD device at the same fluence and voltage

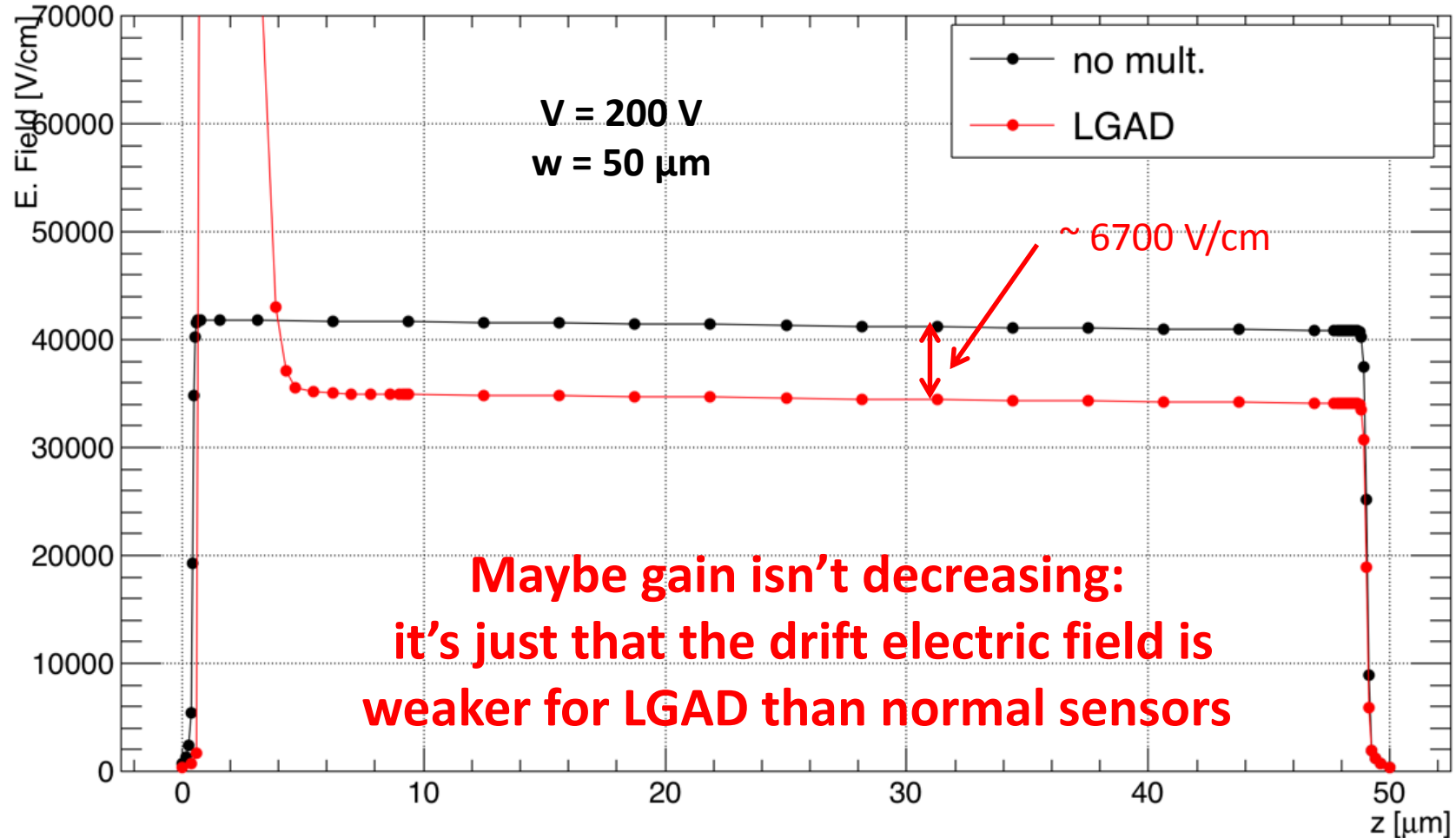


Gain vs different thicknesses – 500 V

Gain = charge normalised to a non-LGAD device at the same fluence and voltage

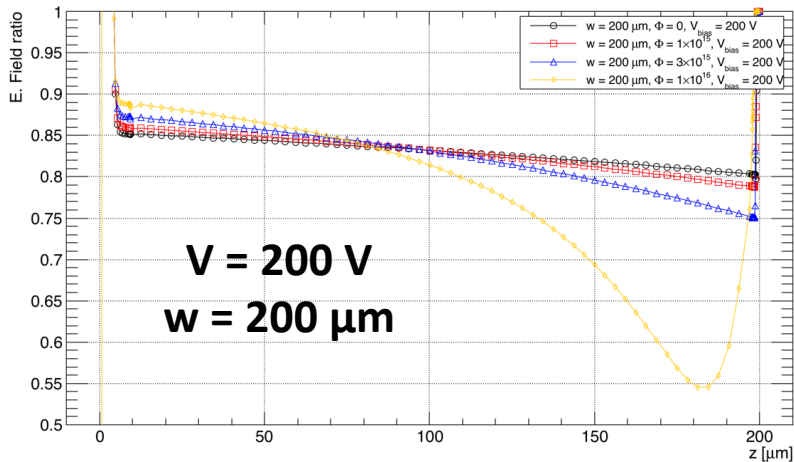
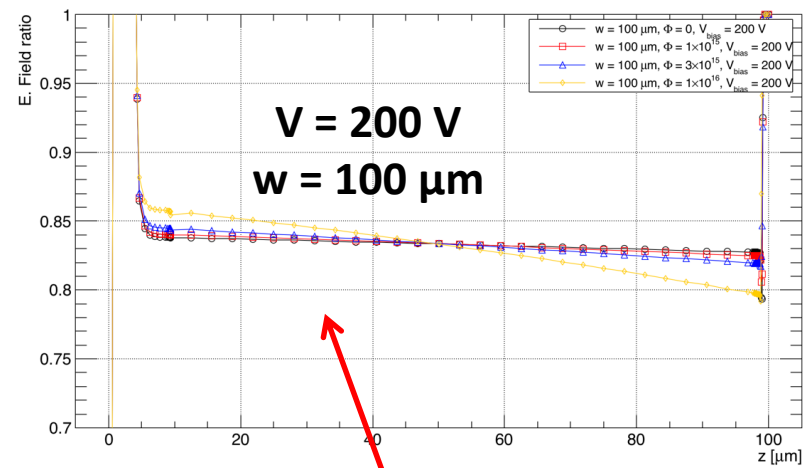
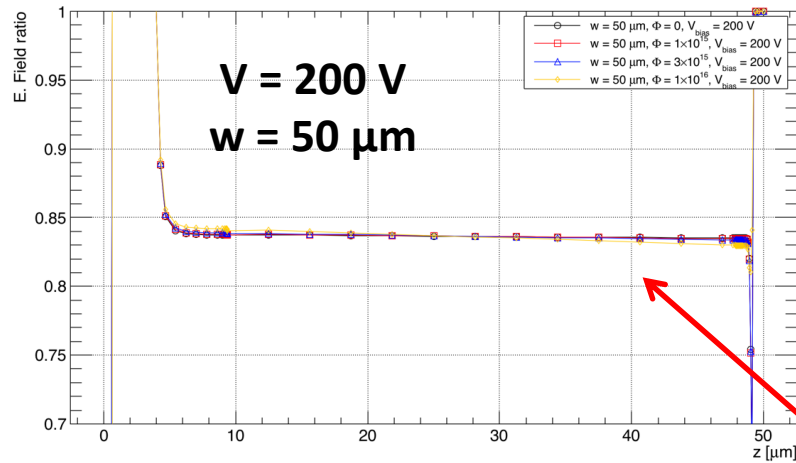


Electric field for $\Phi = 1 \times 10^{15}$



Electric field ratio

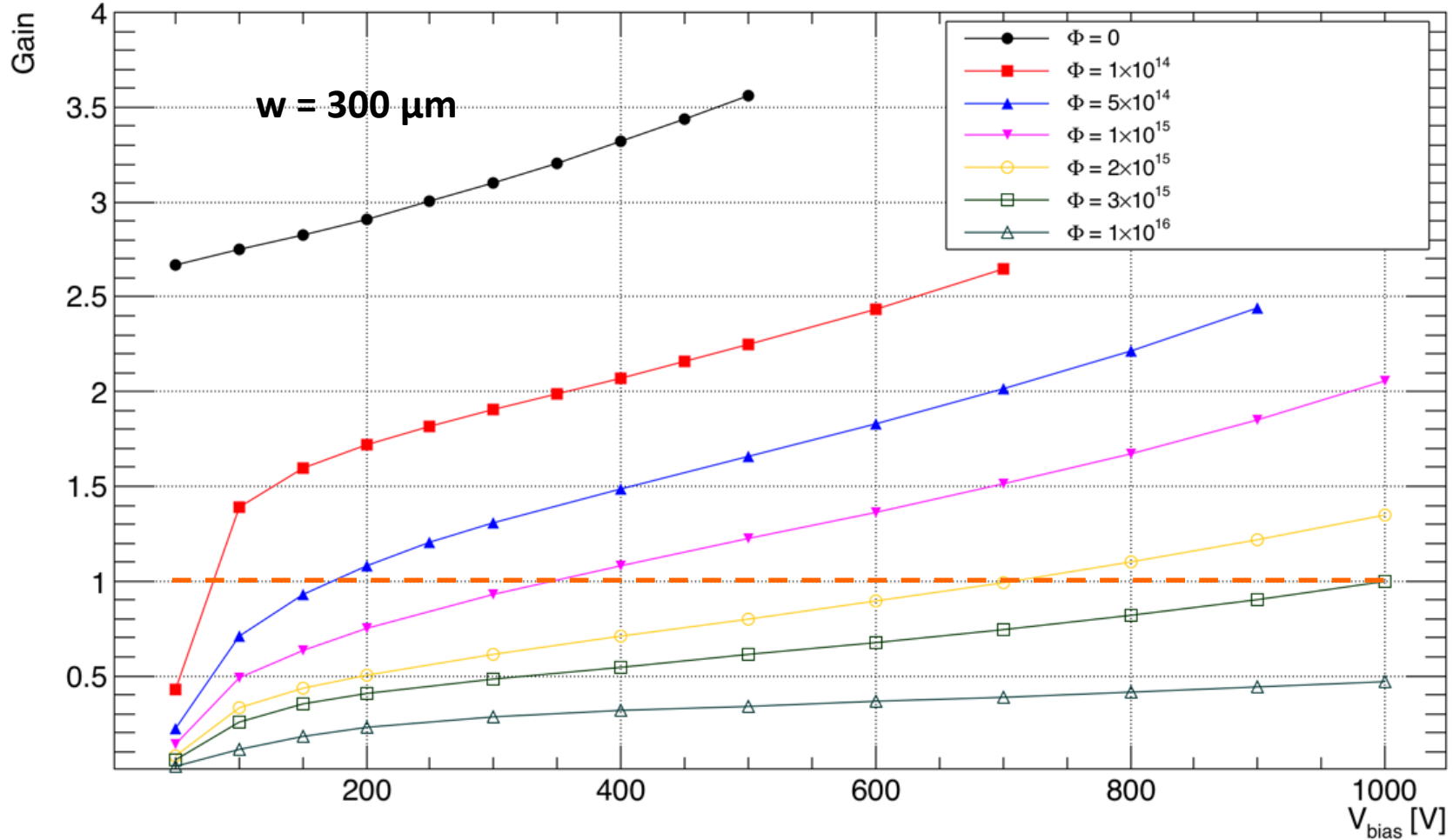
Electric field normalized to the reference detector



Bulk field significantly lower

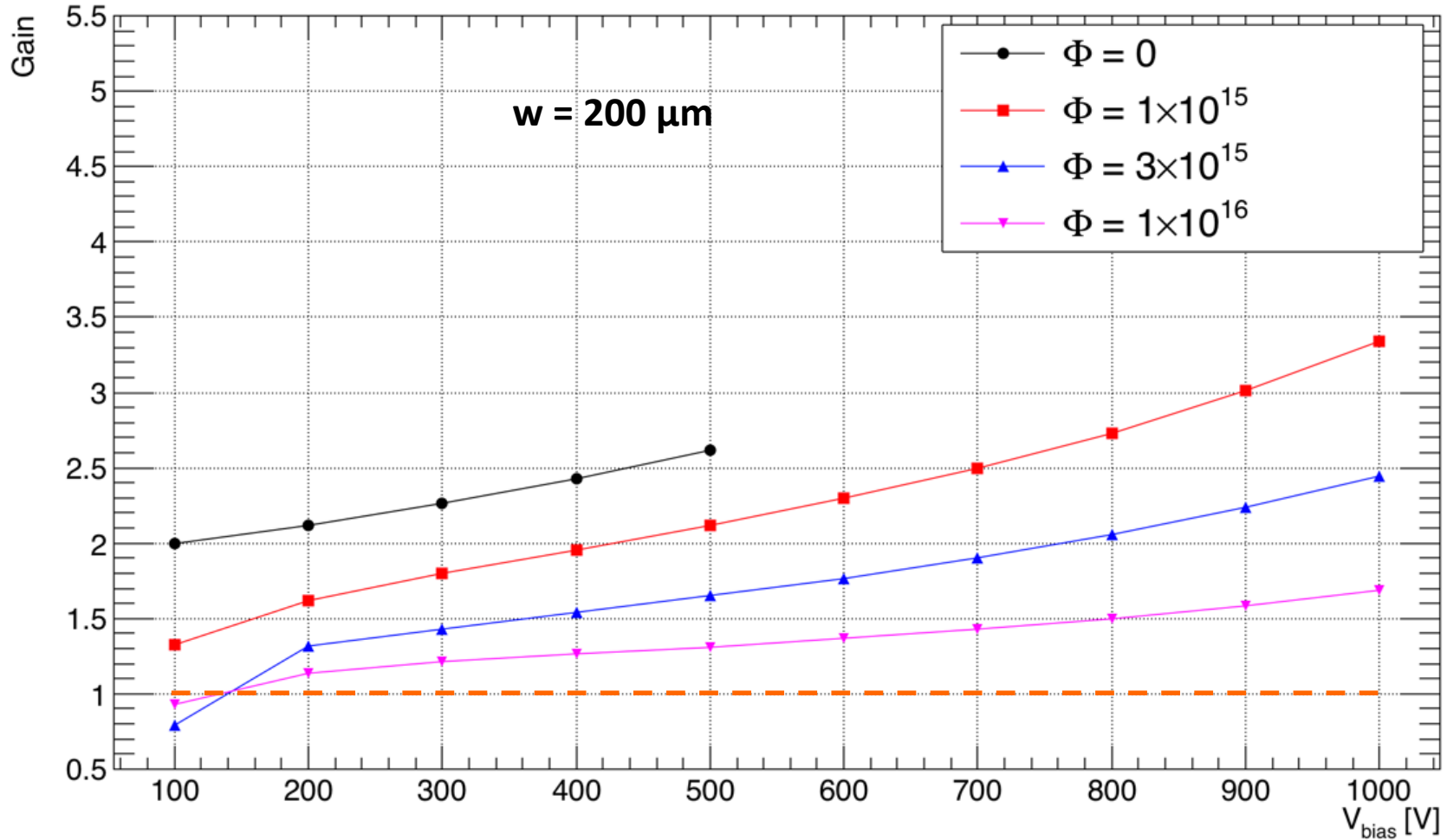
Gain vs bias voltage – $w = 300 \mu\text{m}$

Charge normalized to the reference detector at the zero fluence

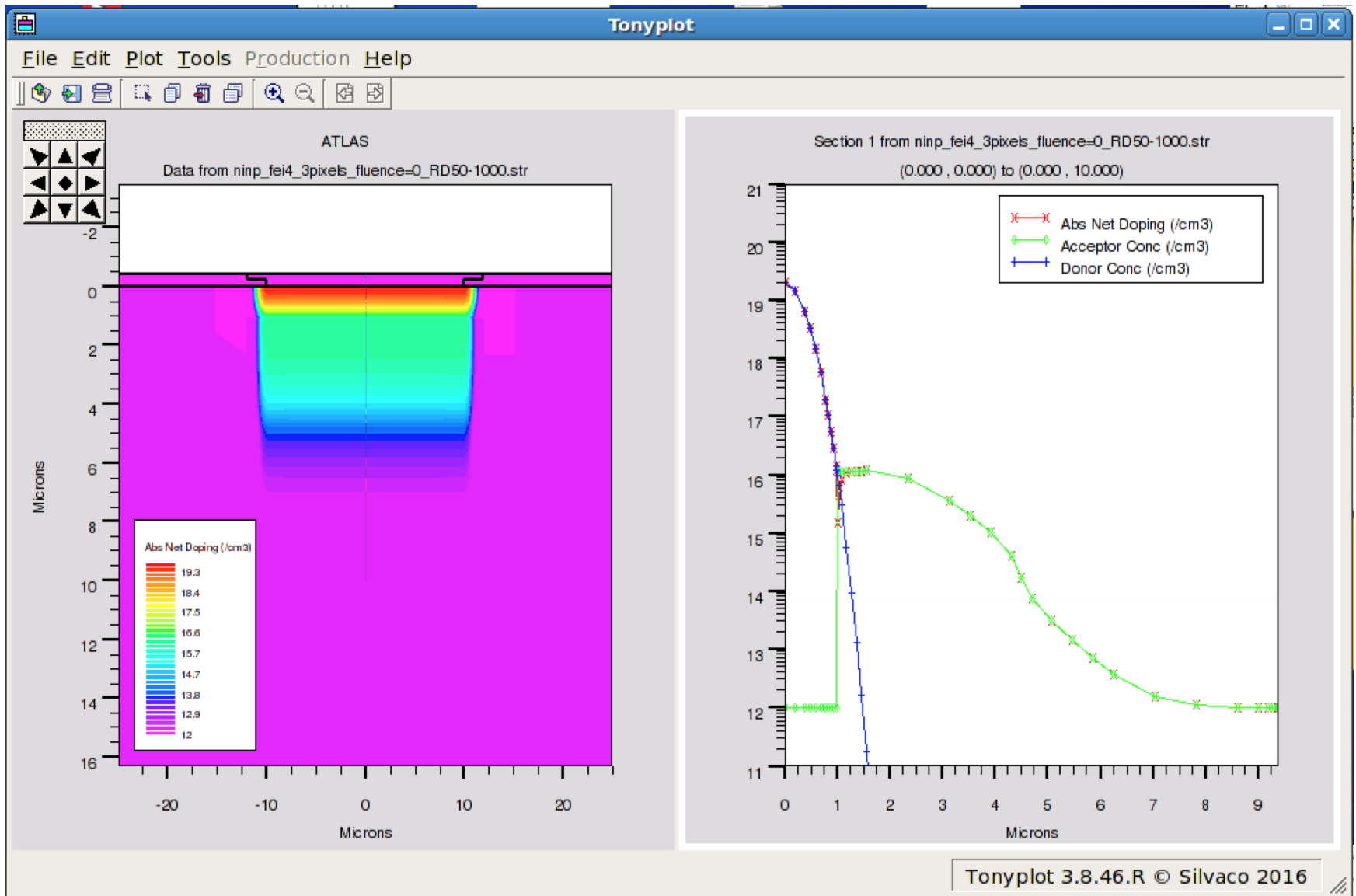


Gain vs bias voltage – $w = 200 \mu\text{m}$

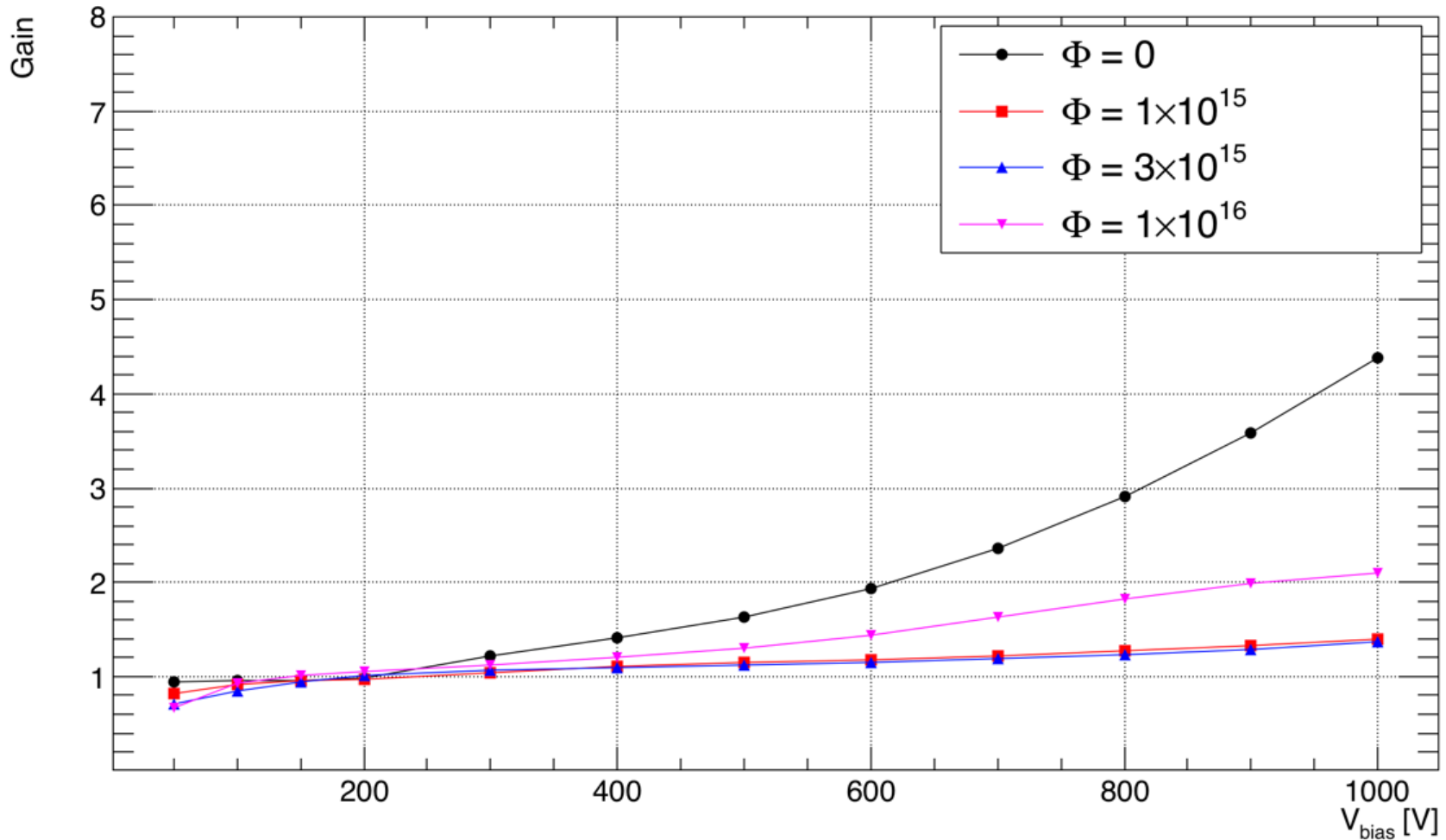
Charge normalized to the reference detector at the same fluence



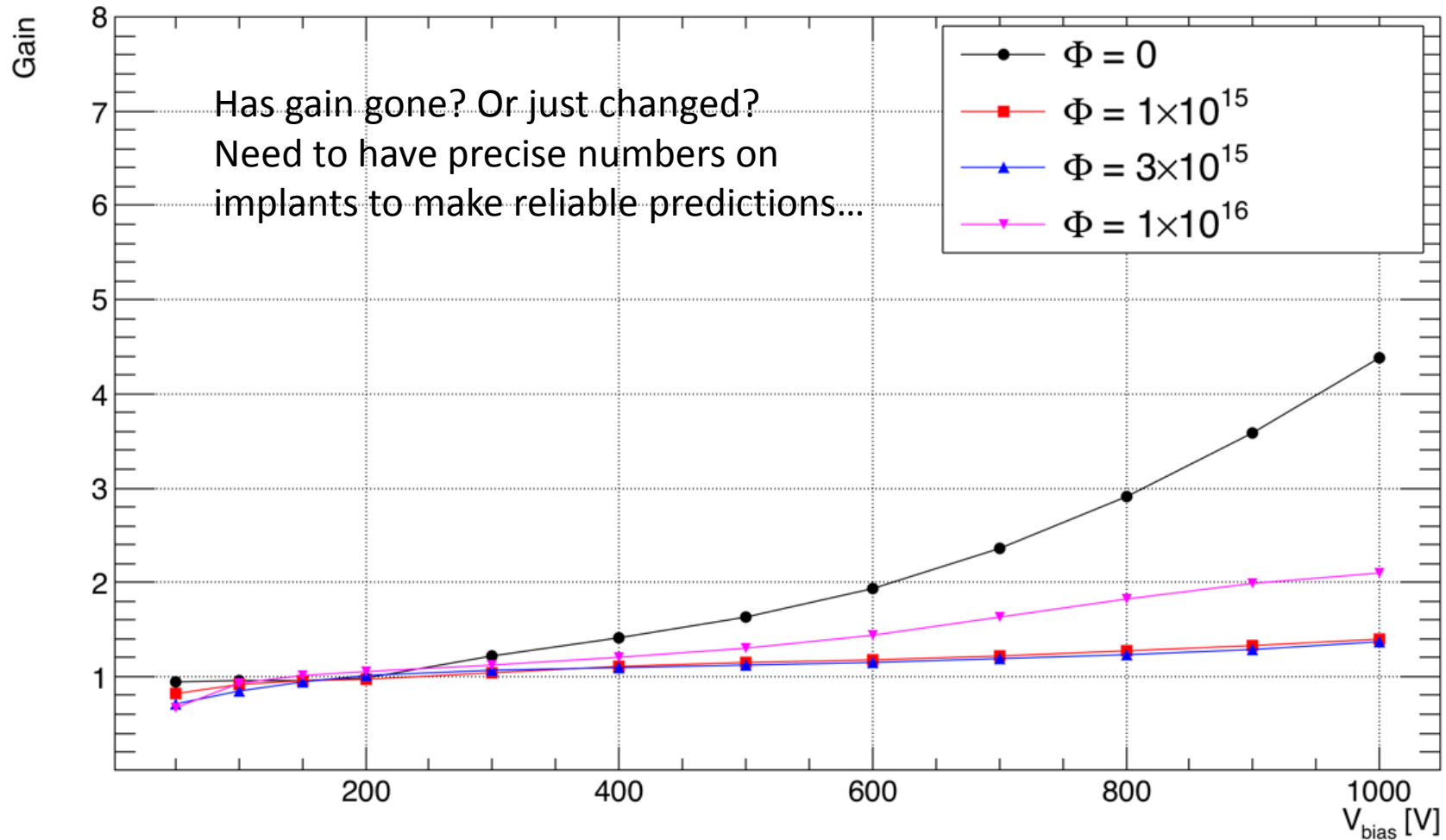
More realistic structure



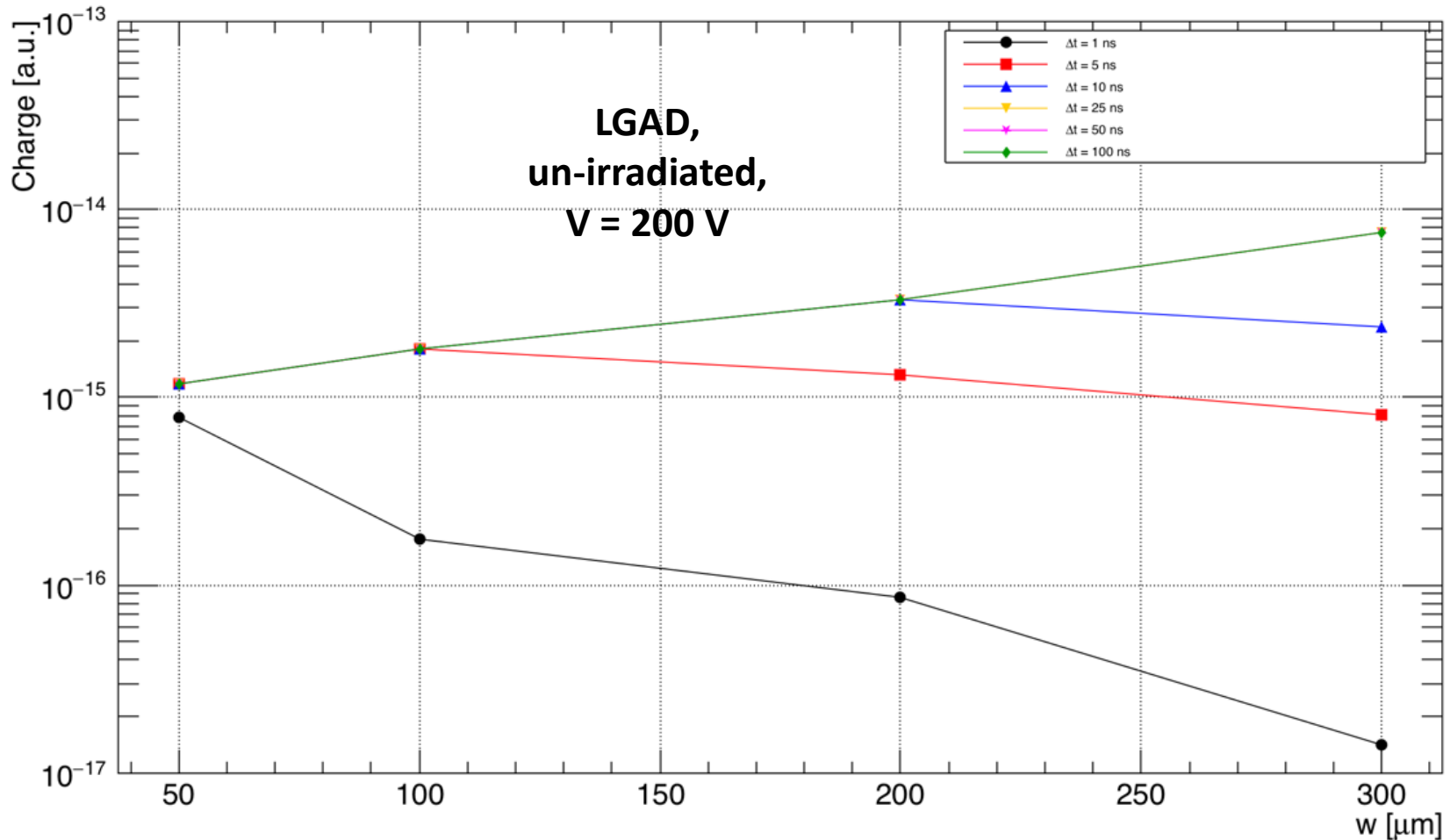
Very preliminary results on the new structure



Very preliminary results on the new structure

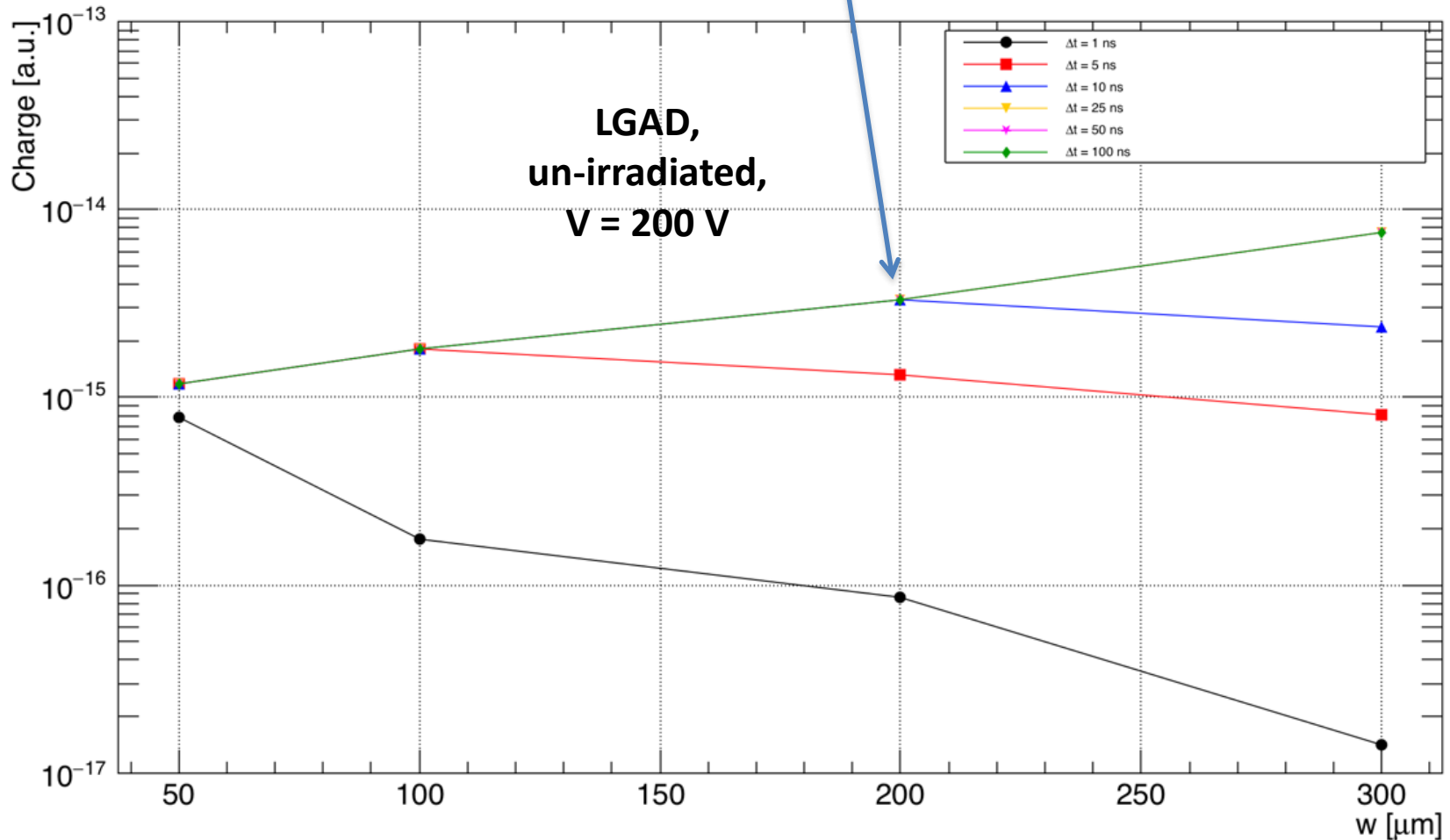


How long do I have to wait for my signal?

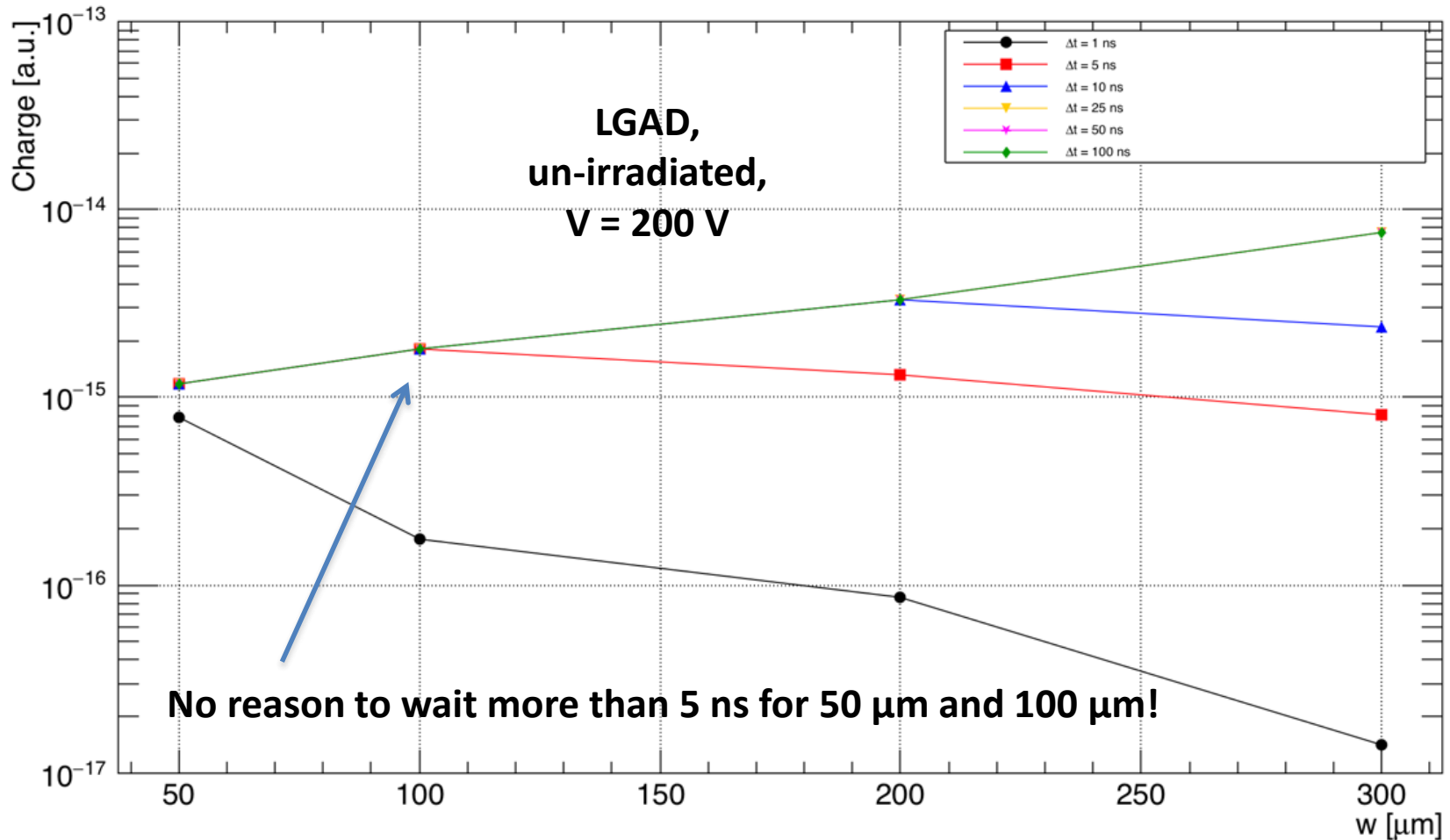


How long do I have to wait for my signal?

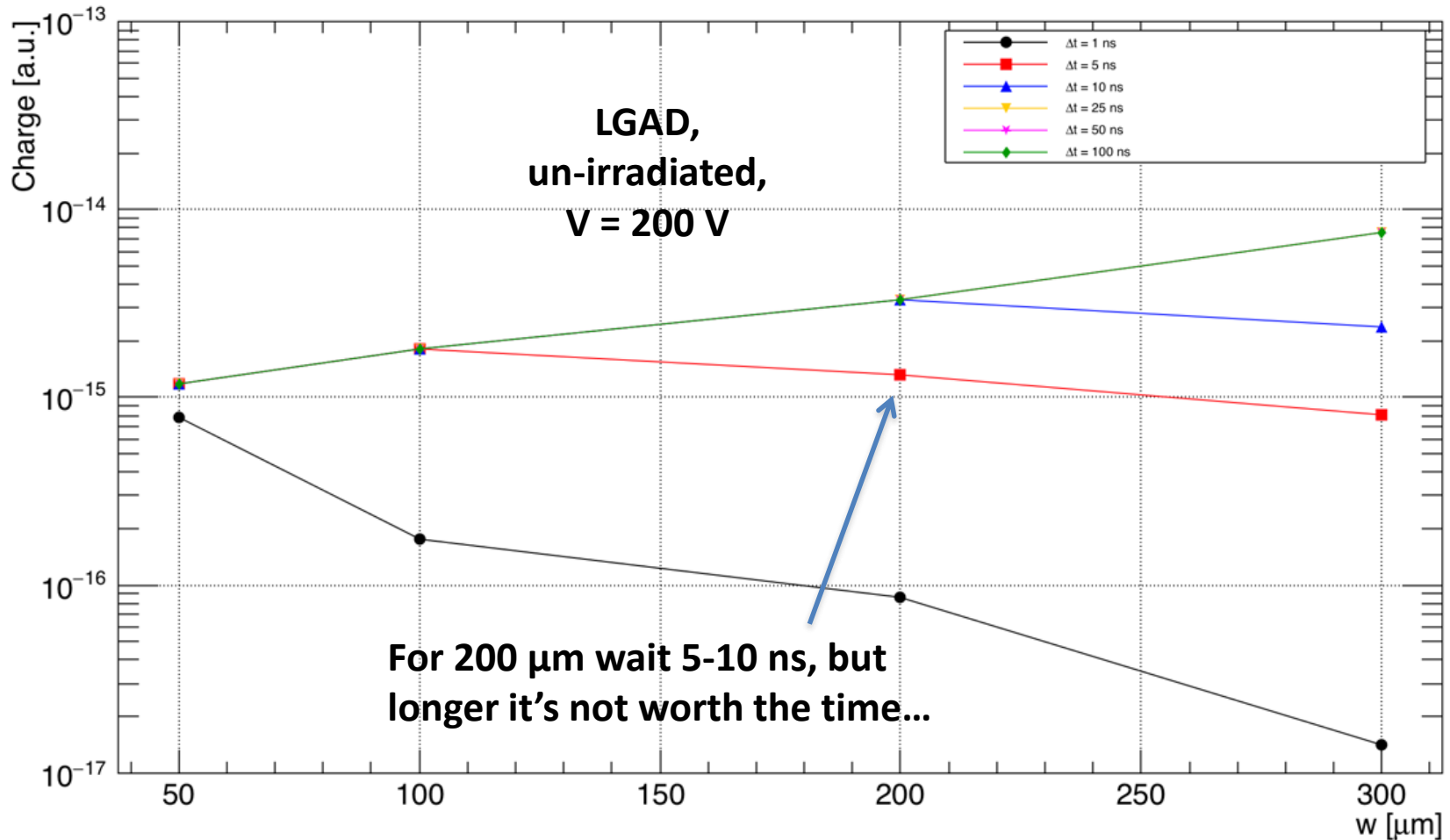
After 10 ns it doesn't make a lot of difference, but...



How long do I have to wait for my signal?



How long do I have to wait for my signal?

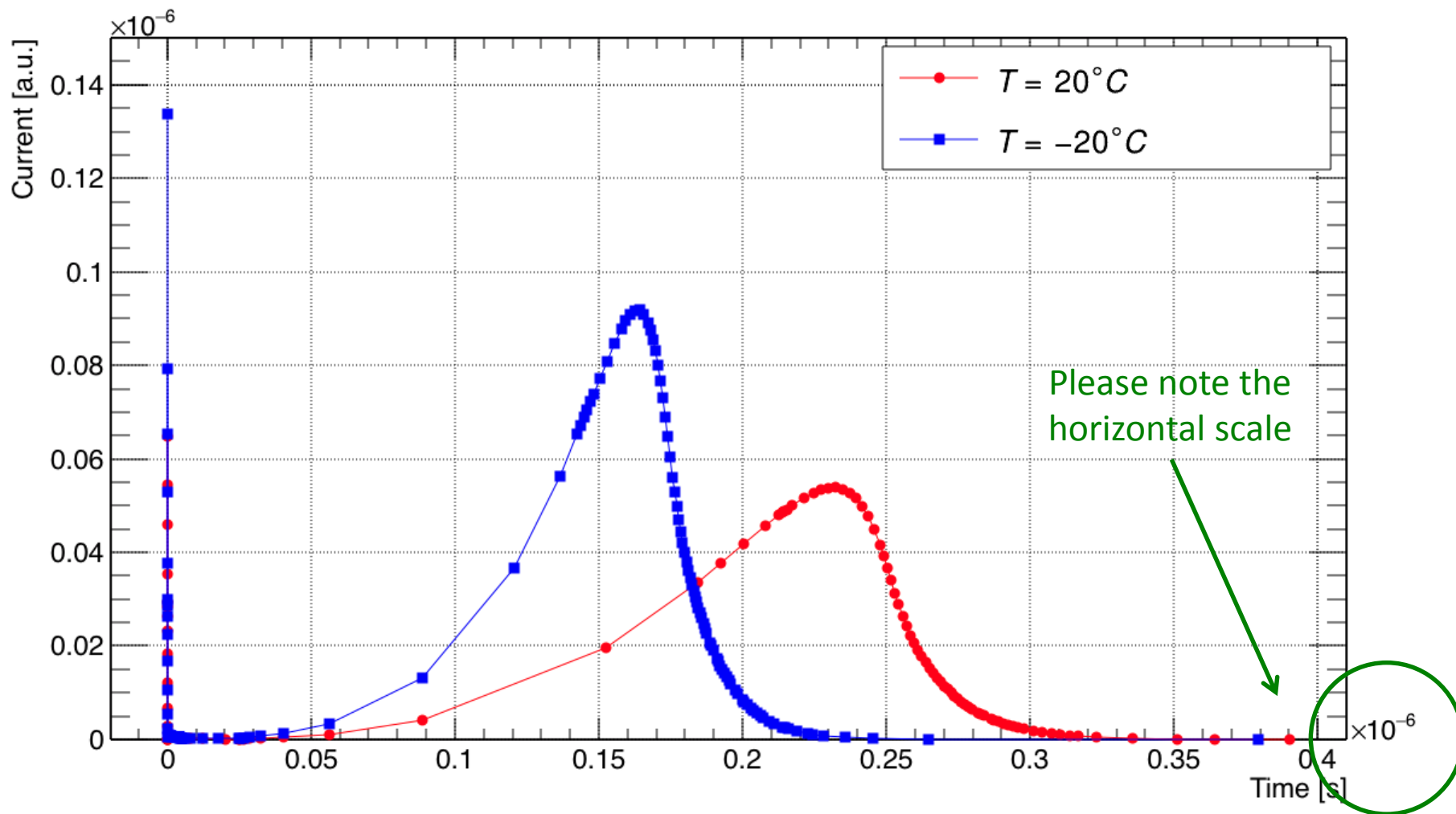


Conclusions & outlook

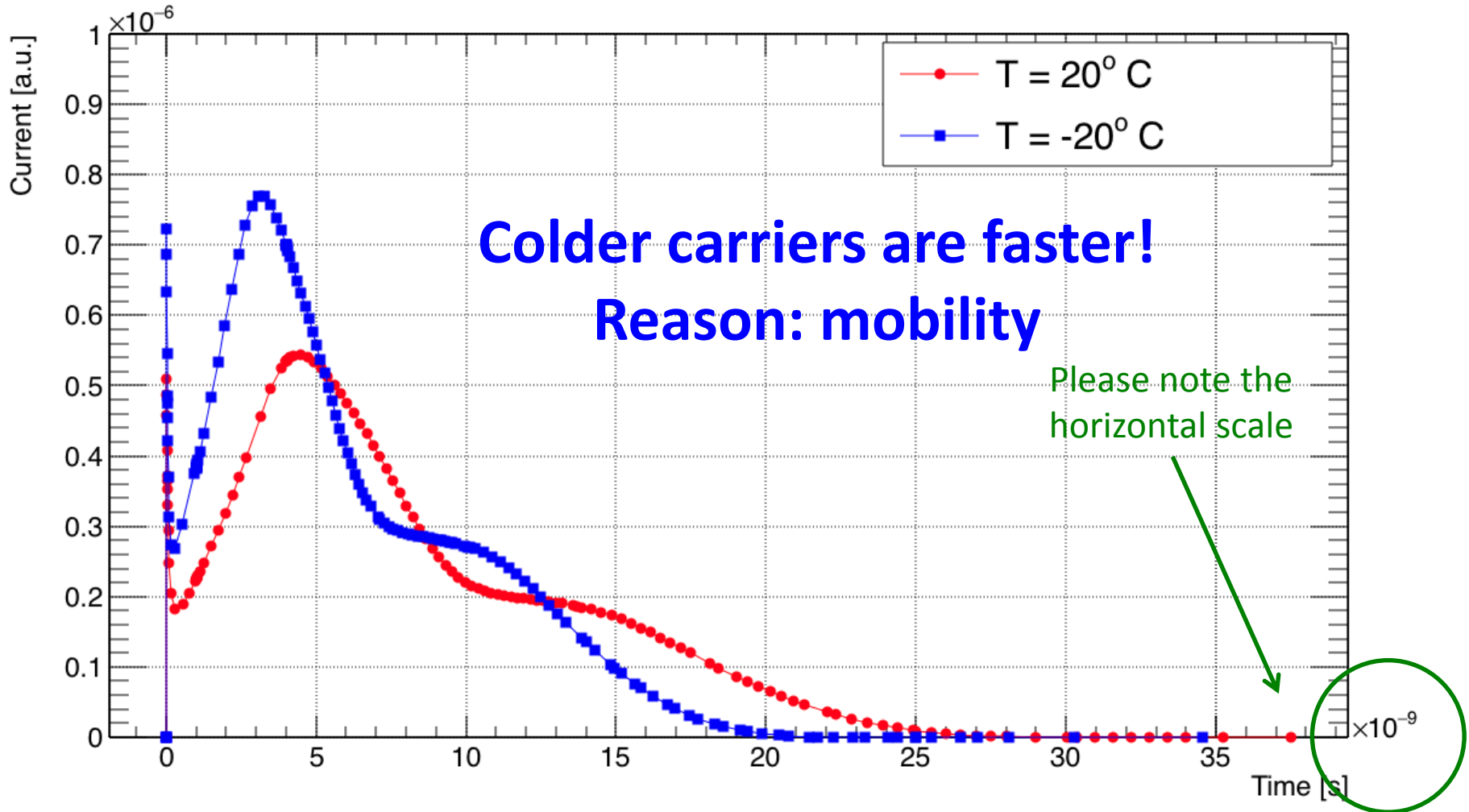
- Signal properties in LGAD have been studied
 - Both alpha from backside and MIPs
- Alpha studies show that the holes are multiplied
- Colder device is faster (expected) and gives rise to more charge
 - Reason: impact ionization is more effective (longer mean free path)
- MIP studies confirms that signal “takes” longer for LGAD
 - But response at $t=0$ is the same as for non-LGAD (expected)
 - Hence: the front-end will make the difference for timing
 - Anyway, interesting timing studies can be carried out
- Lower gain after irradiation could be apparent: an important difference could be linked to the electric field strength
- Gain for $w = 200 \mu\text{m}$ goes from 1 to 1.7 from 0 to 1000V at $\Phi=1 \times 10^{16}$
- Next: *more realistic detectors* (**based on real numbers**), new doping profiles, surface damage effects

Backup

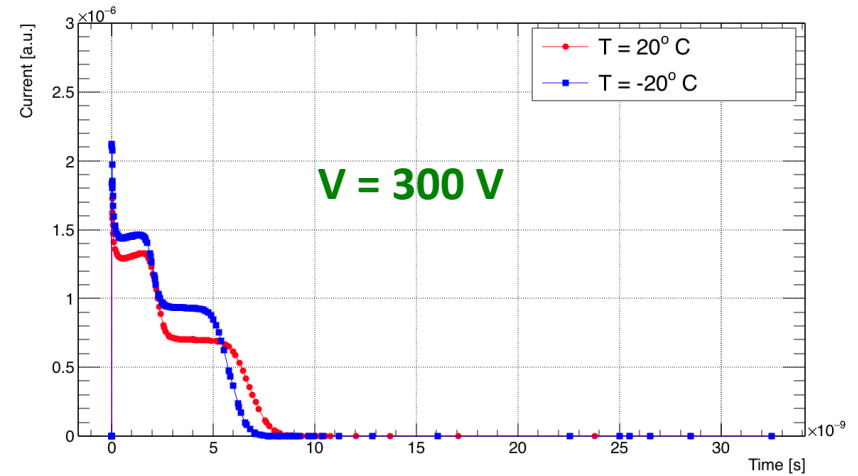
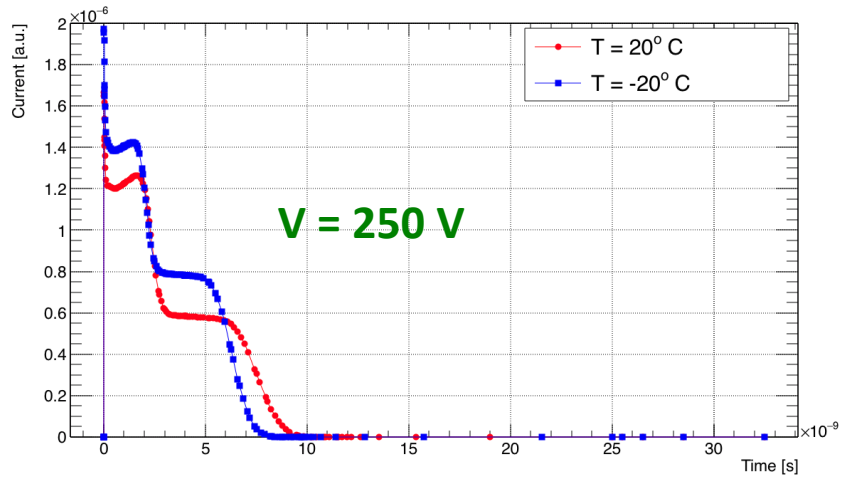
Signal, $V = 50\text{ V}$



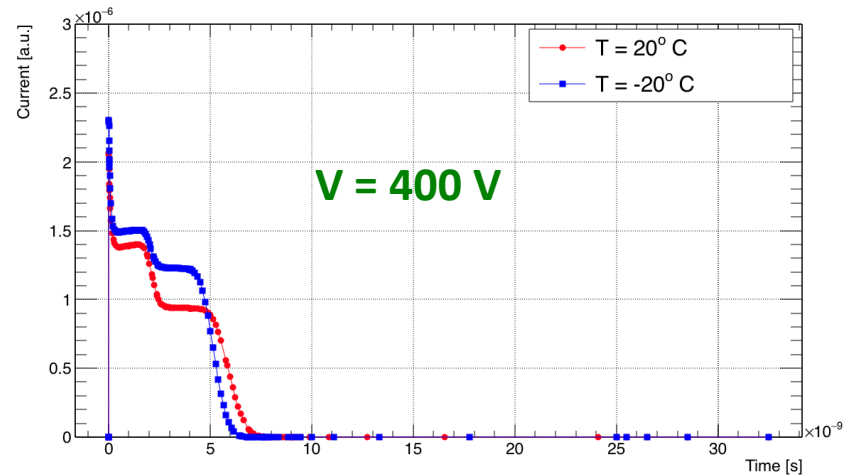
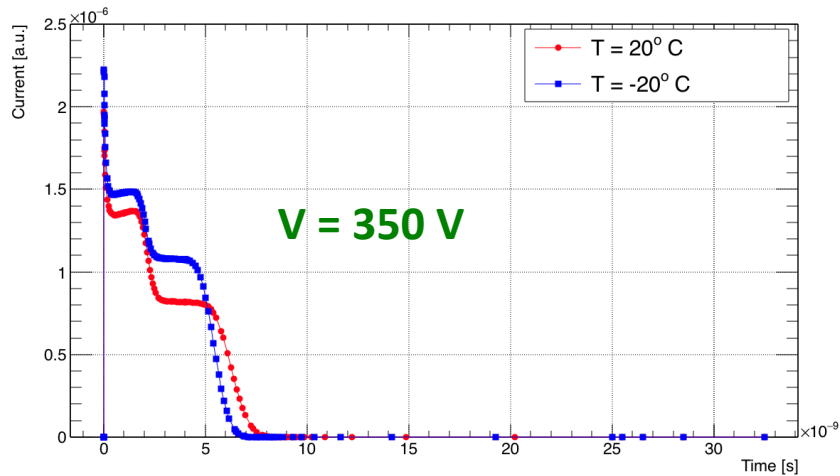
Signal, $V = 100\text{ V}$



More bias points (I)

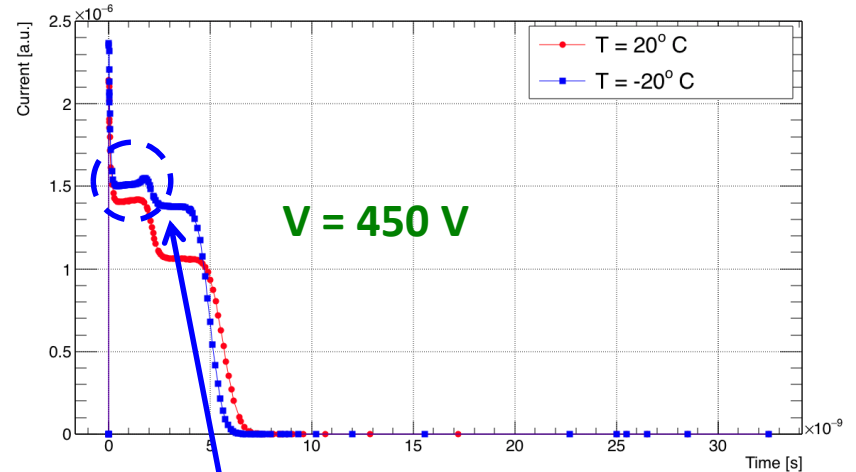


Same horizontal scale for all

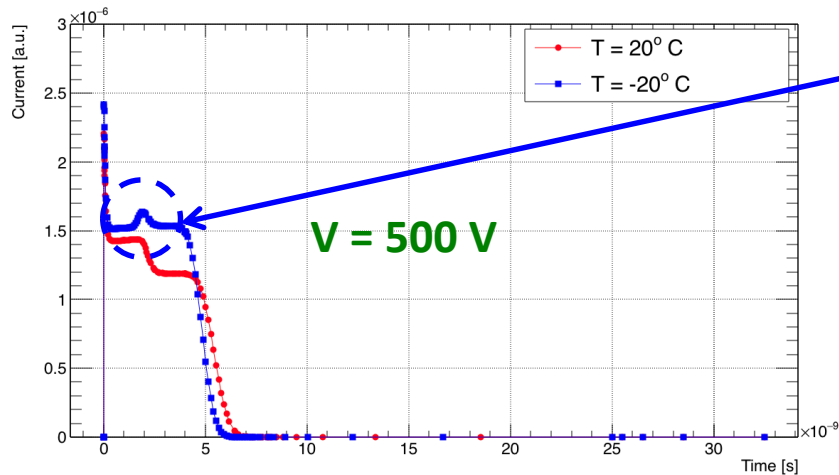


More bias points (II)

As before: colder
means faster...
and more signal too?

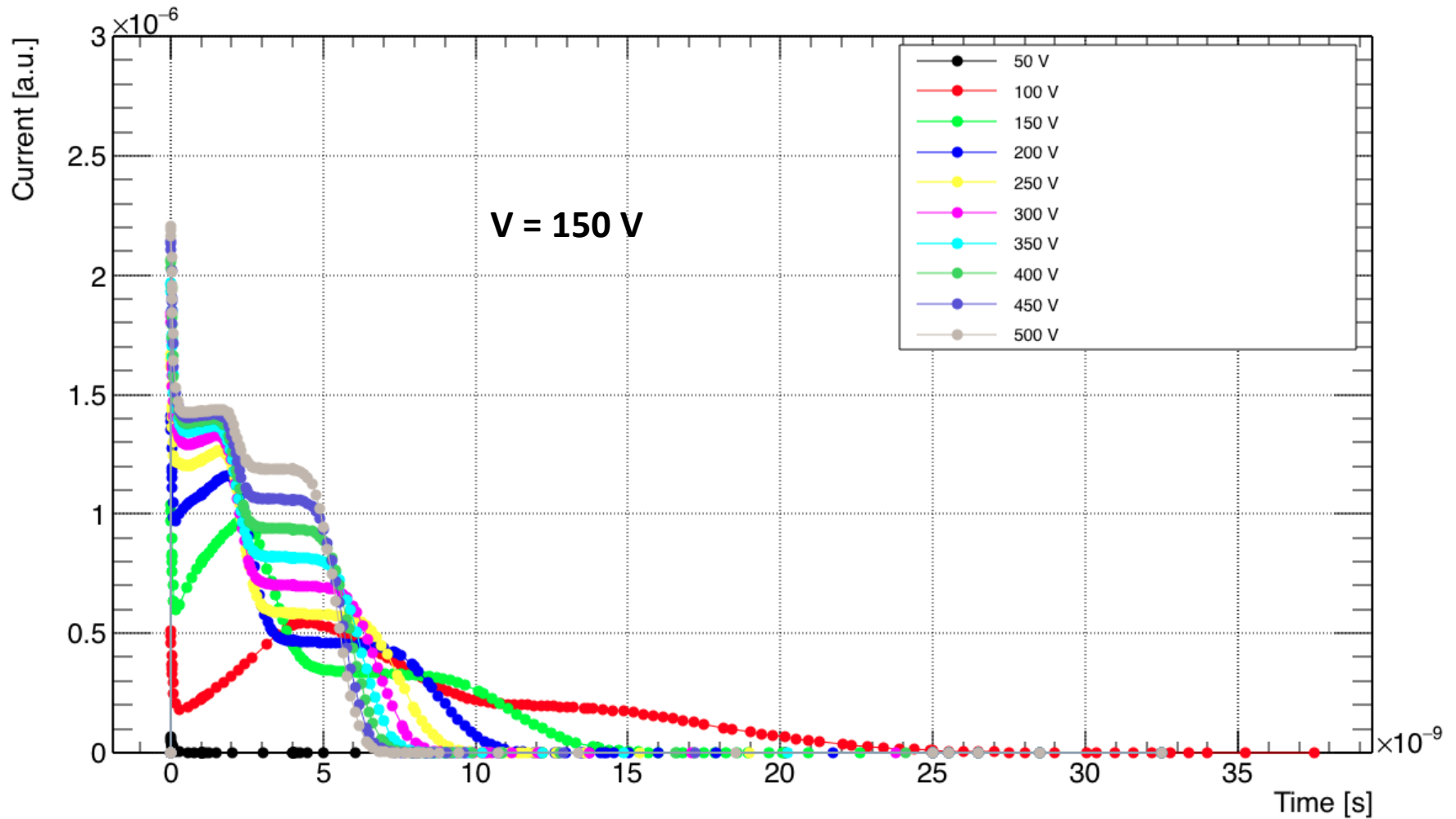


Same horizontal scale for all

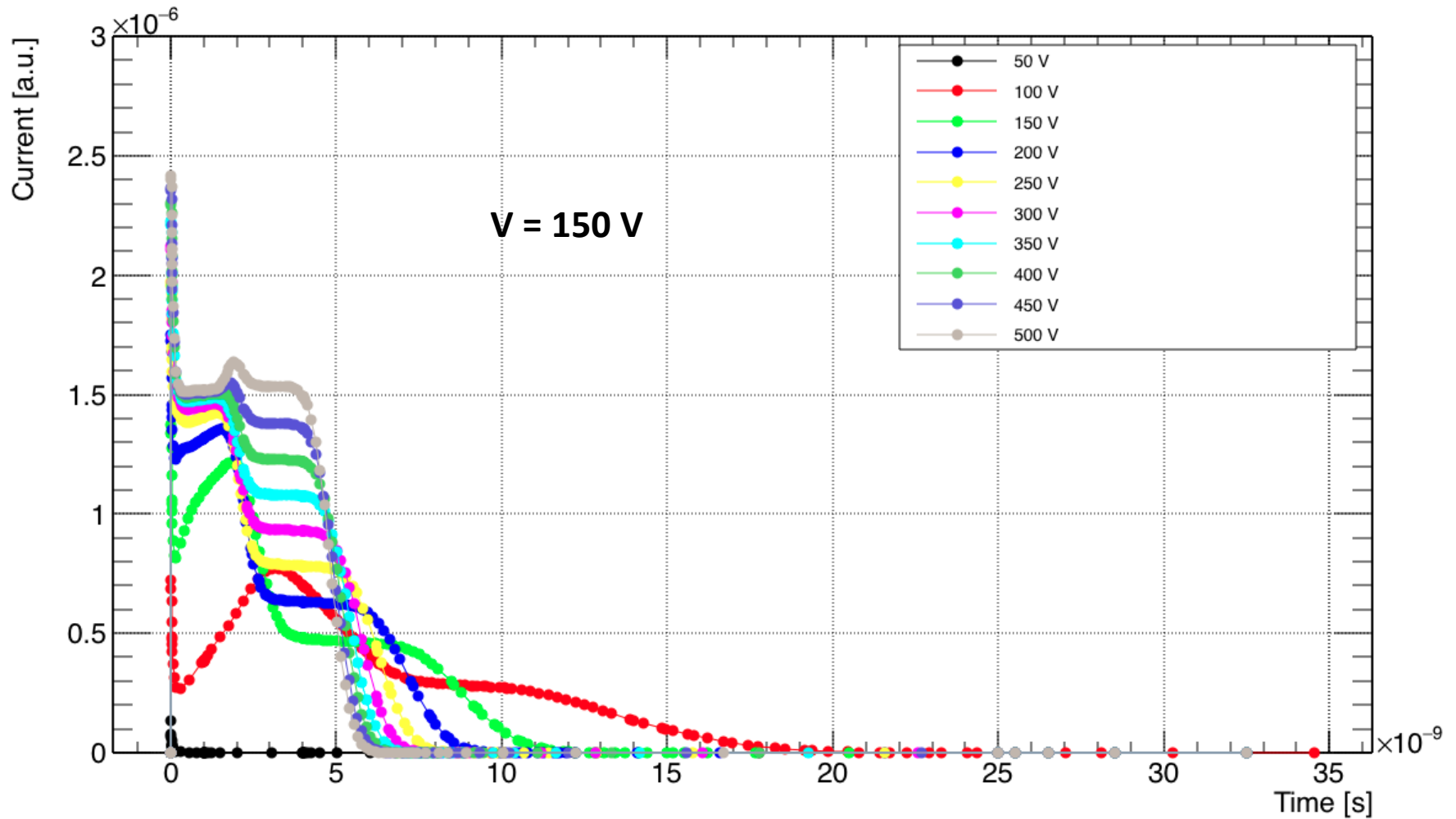


Ridge?

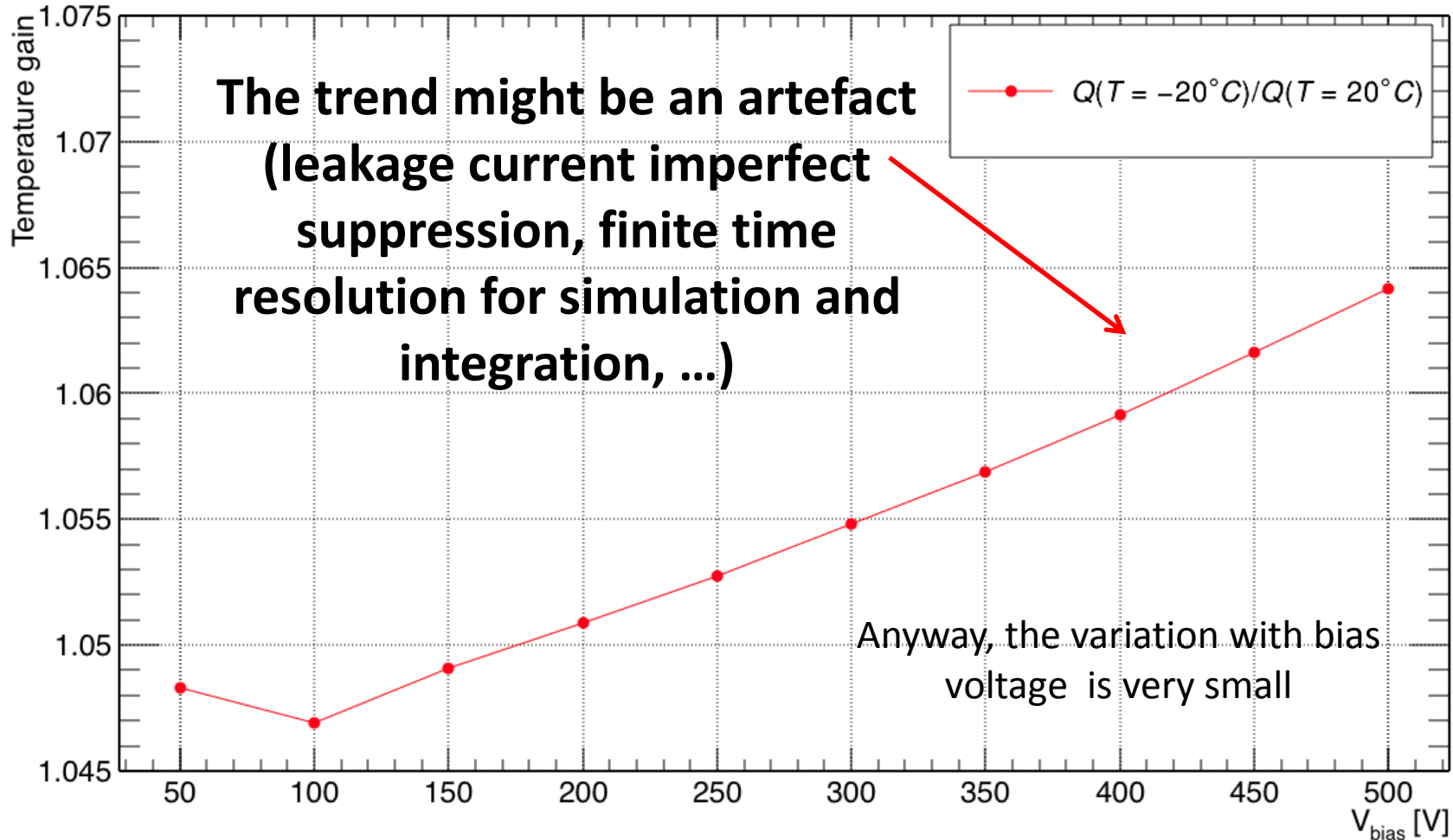
Summary plot for $T = 20^\circ\text{C}$



Summary plot for $T = -20^{\circ}\text{C}$

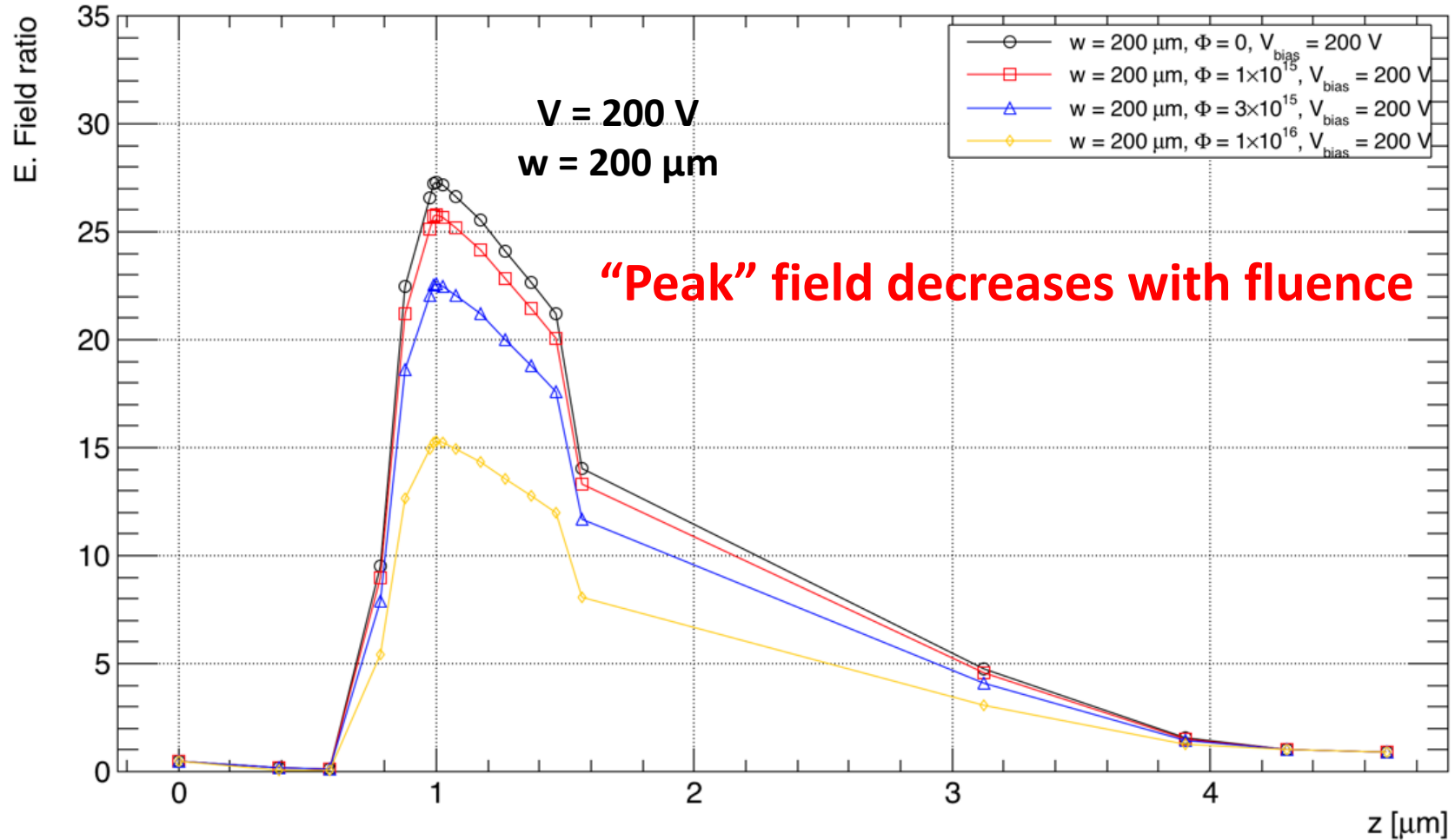


“Temperature” gain

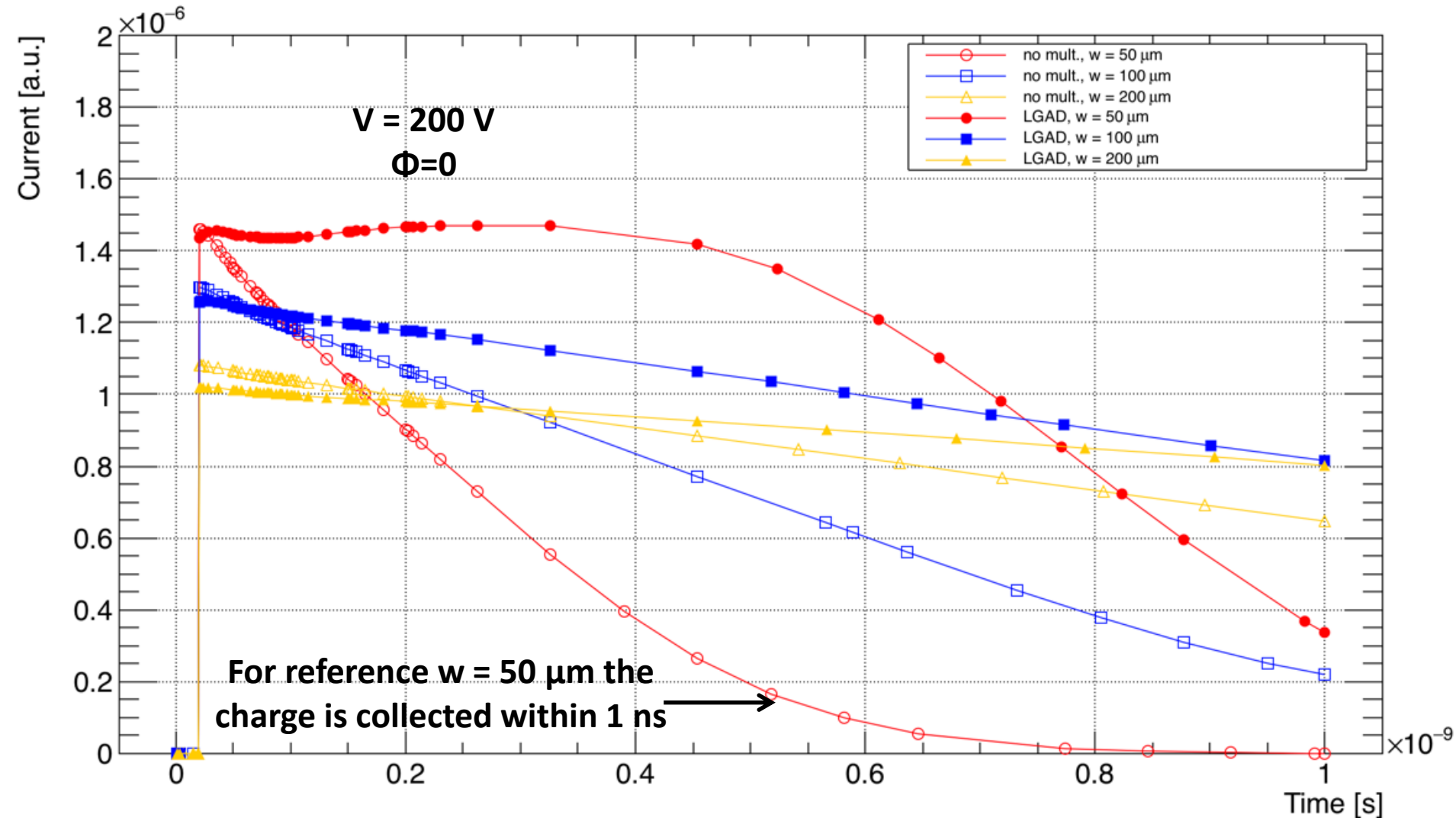


Electric field ratio

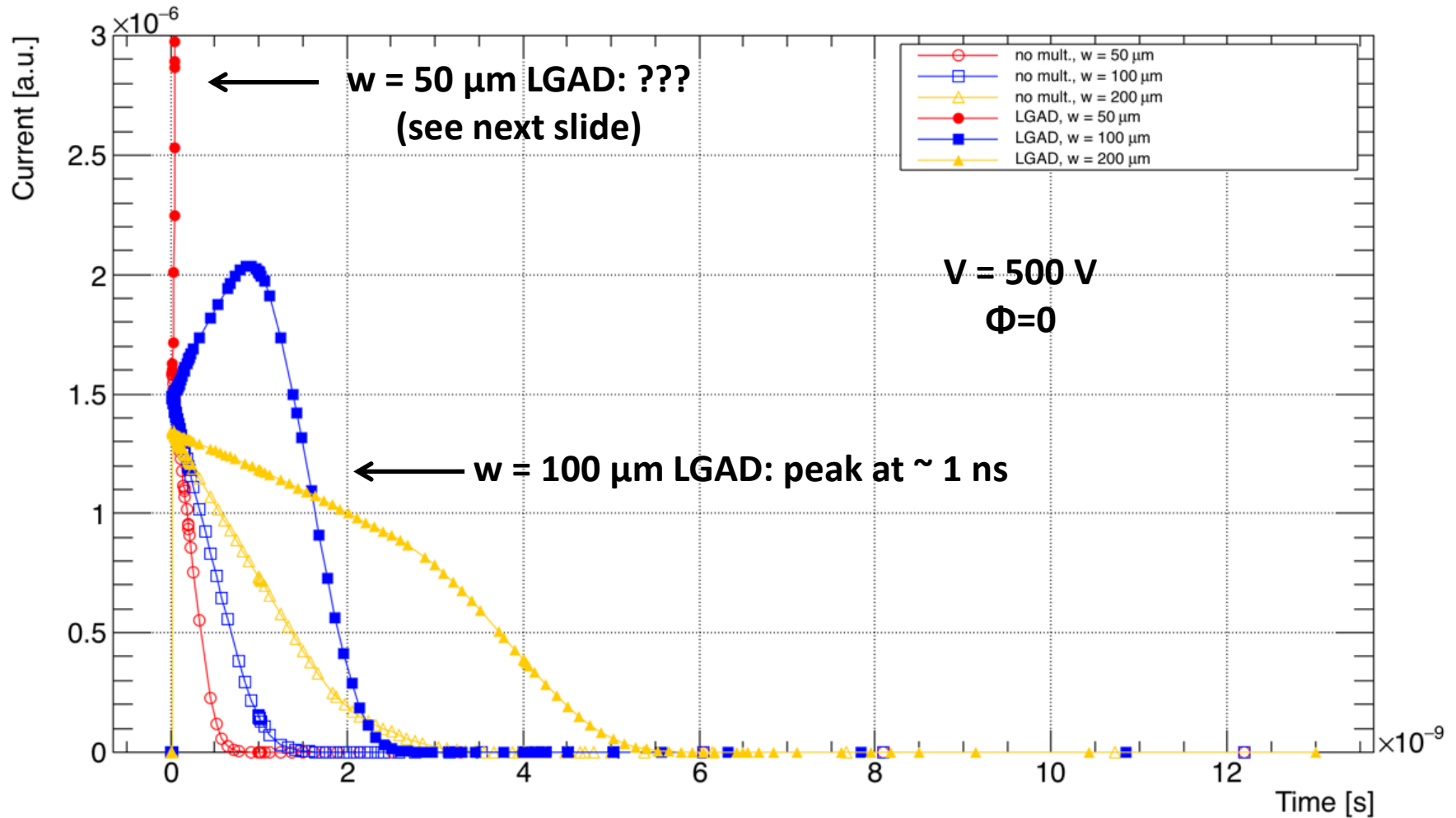
Electric field normalized to the reference detector



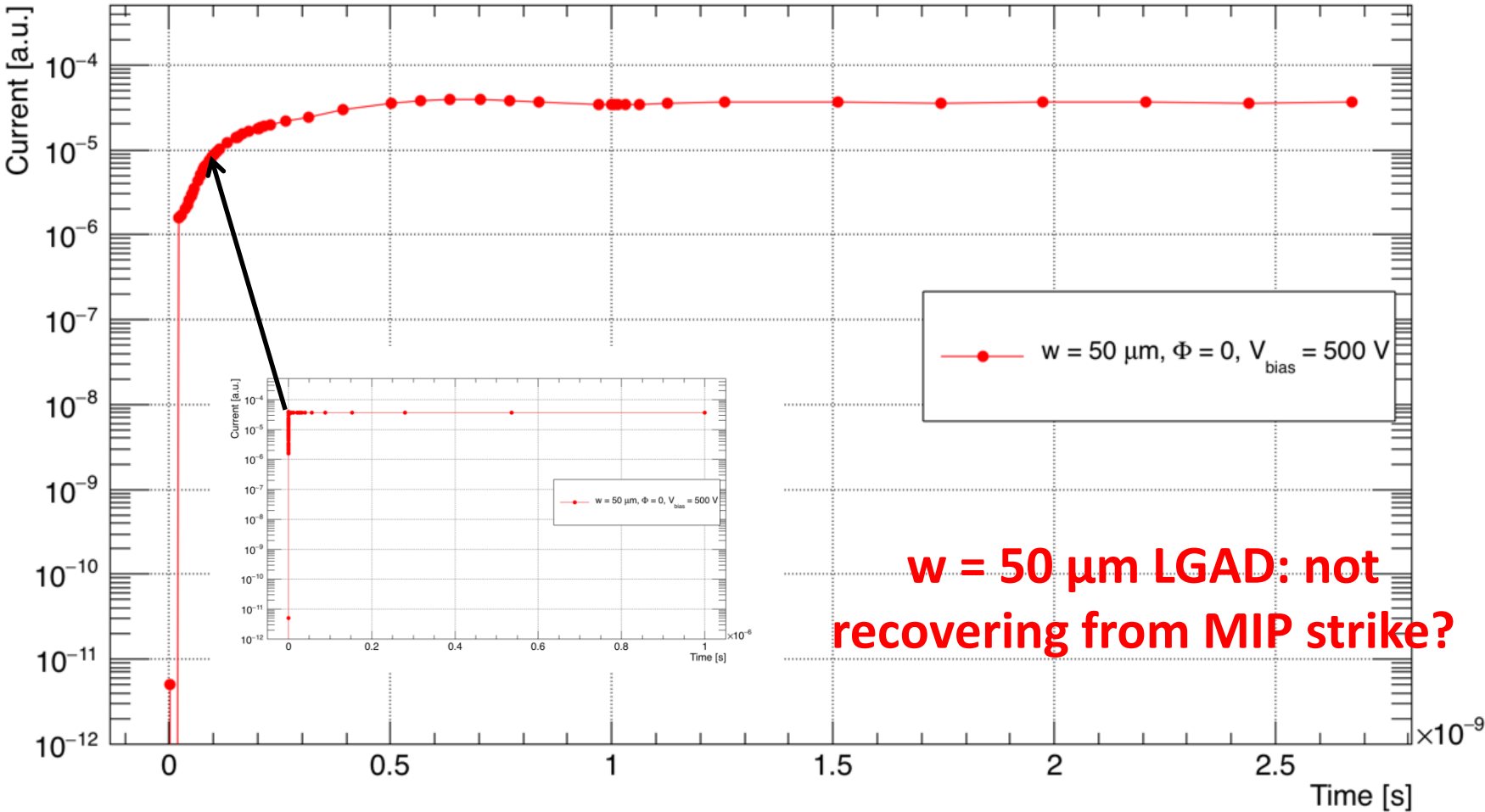
Signal vs time, different thicknesses – 200 V



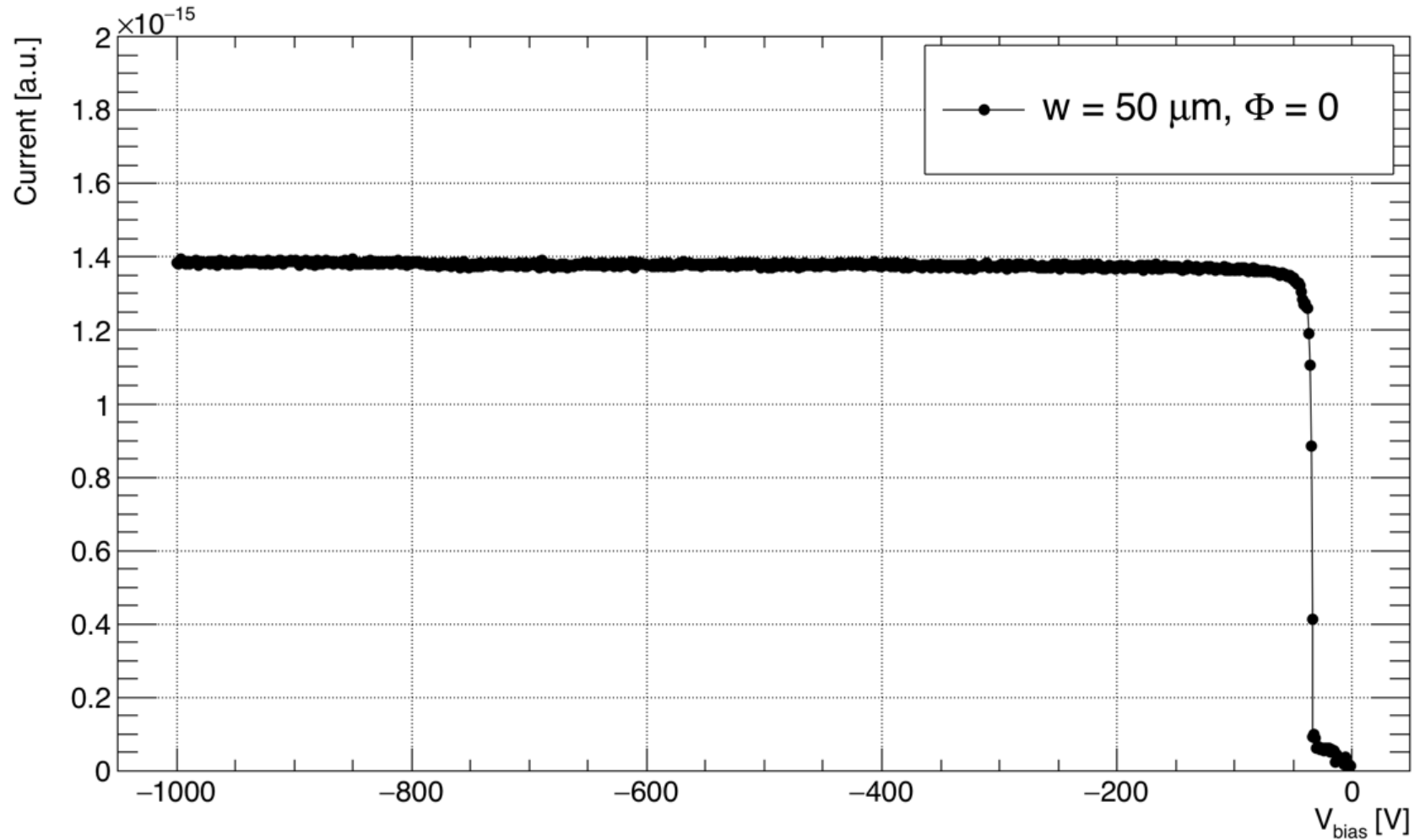
Signal vs time, different thicknesses – 500V



Signal vs time, $w = 50 \mu\text{m}$, un-irr. – 500 V



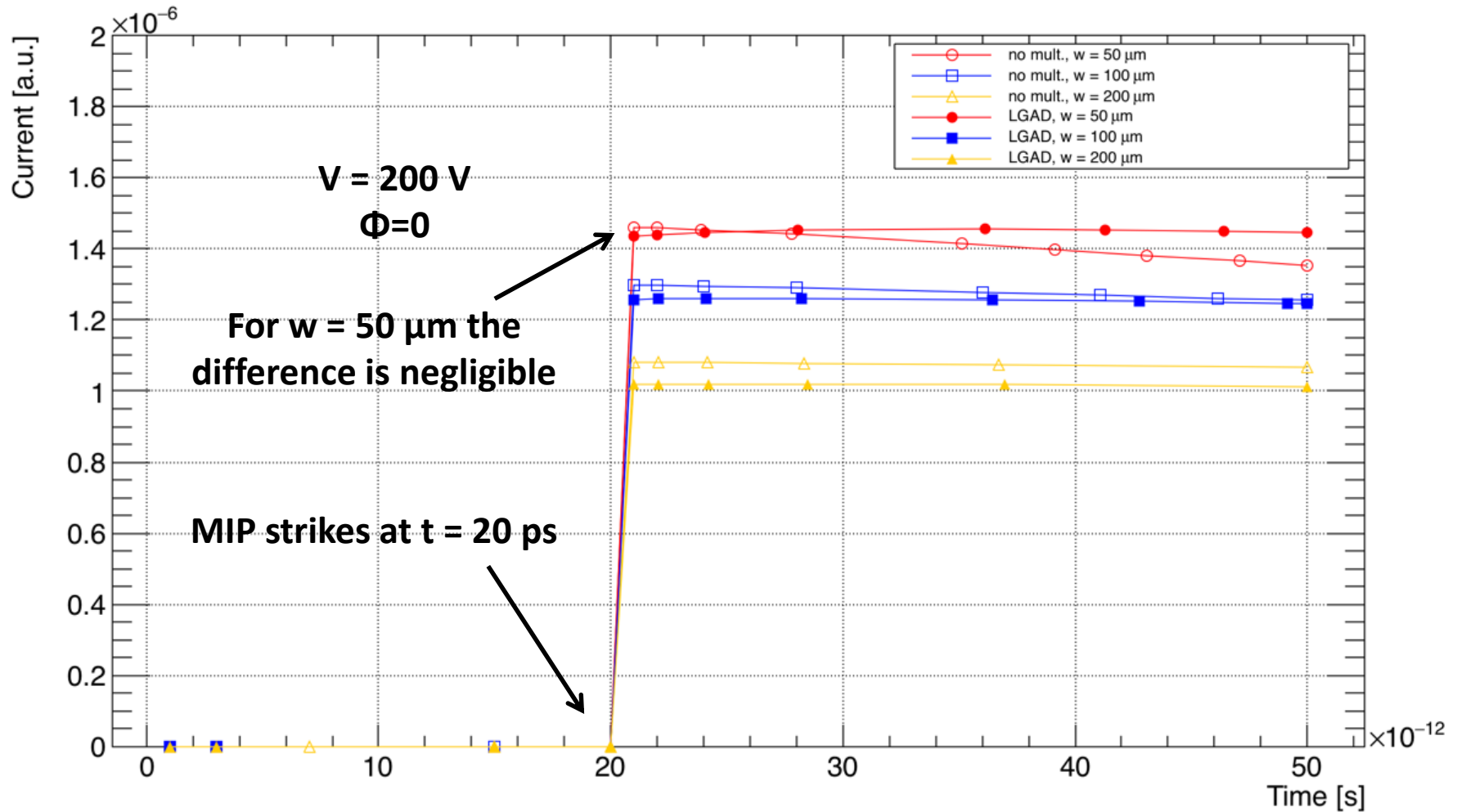
No breakdown in thin un-irr. till 1000 V



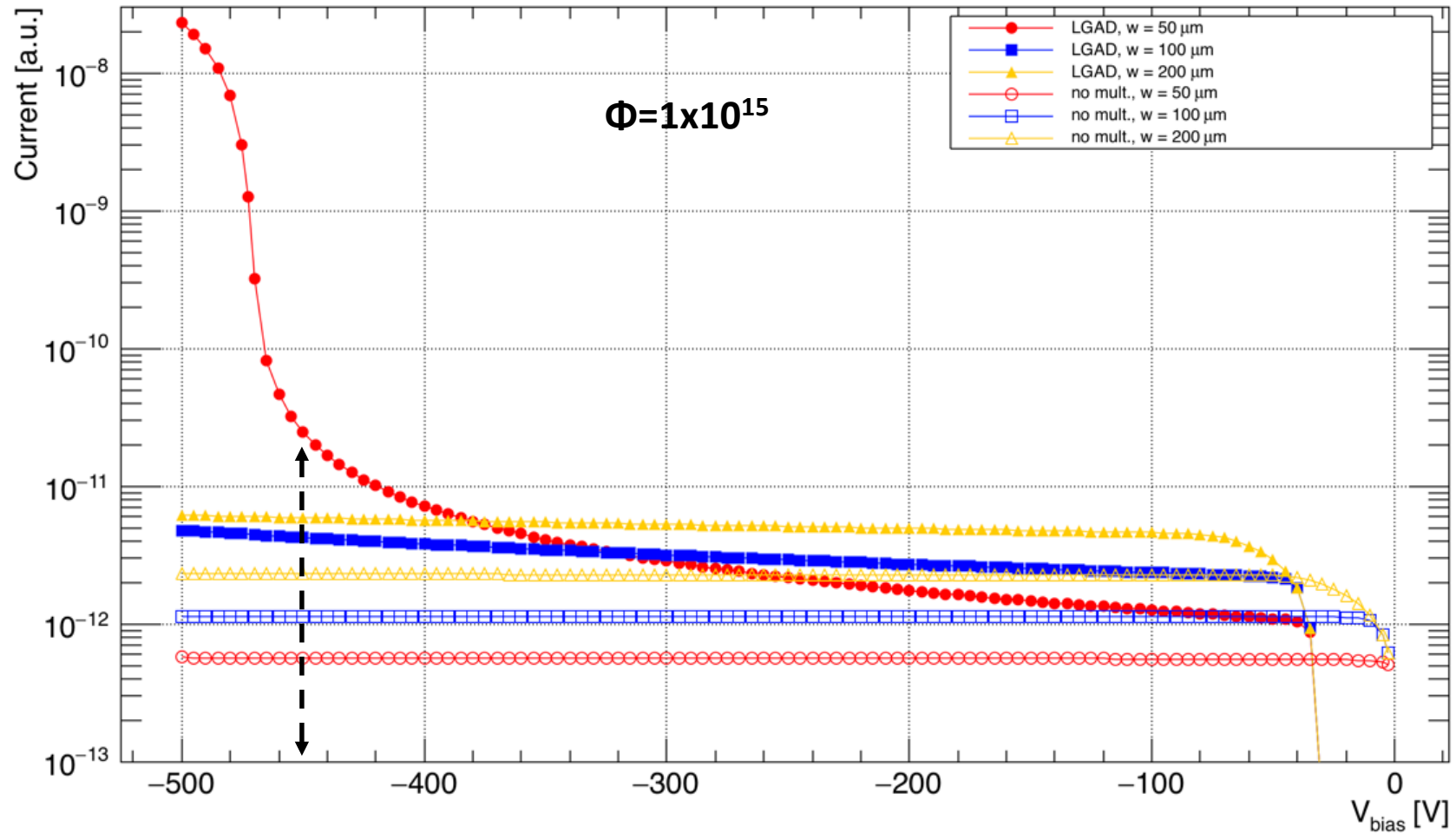
Break down voltage summary for irr. LGAD

Φ [neq/cm ²] w[μ m]	1×10^{15}	3×10^{15}	1×10^{16}
50	450	450	450
100	> 500	900	900
200	> 500	> 1000	> 1000

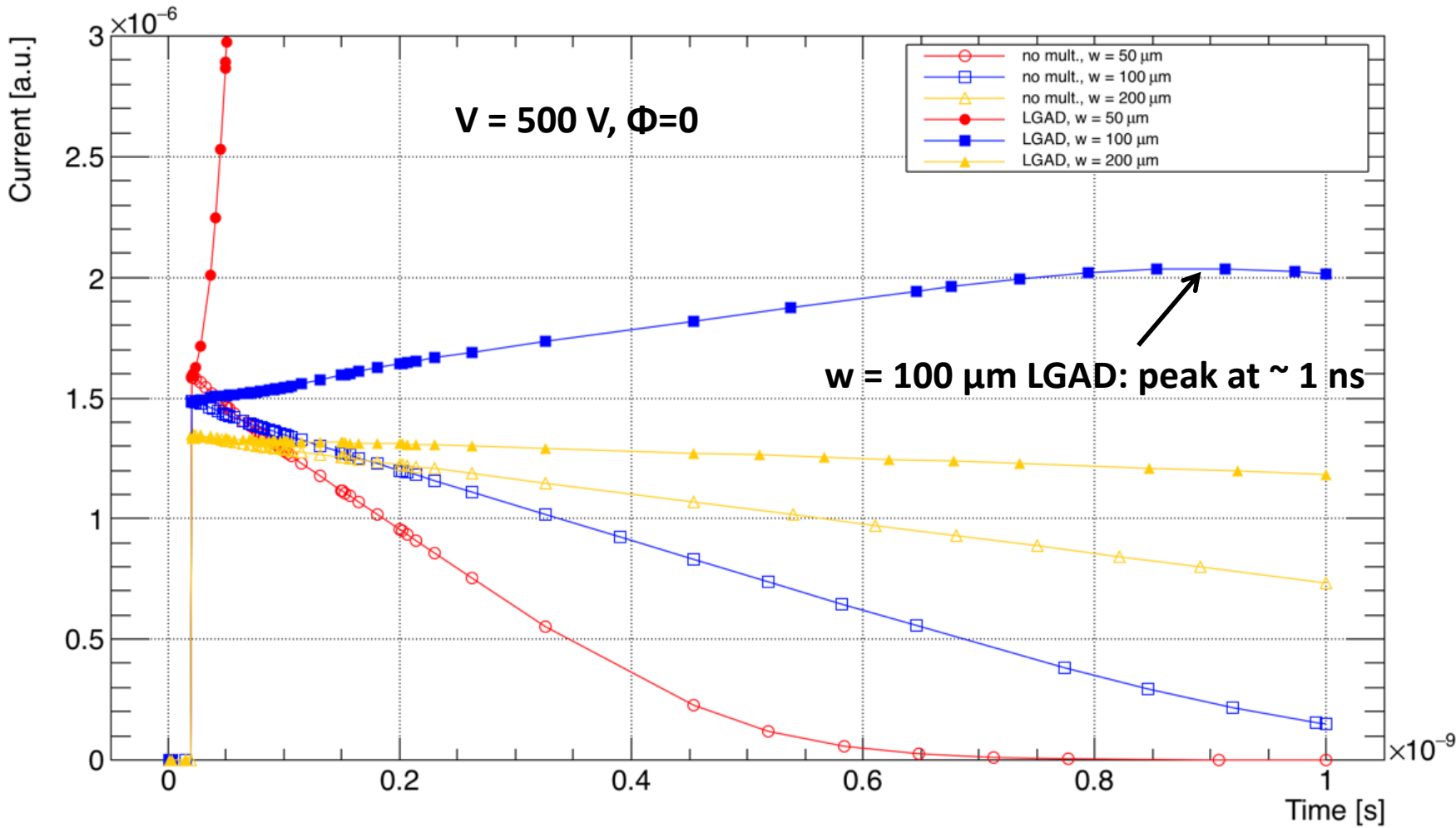
Signal vs time, different thicknesses – 200 V



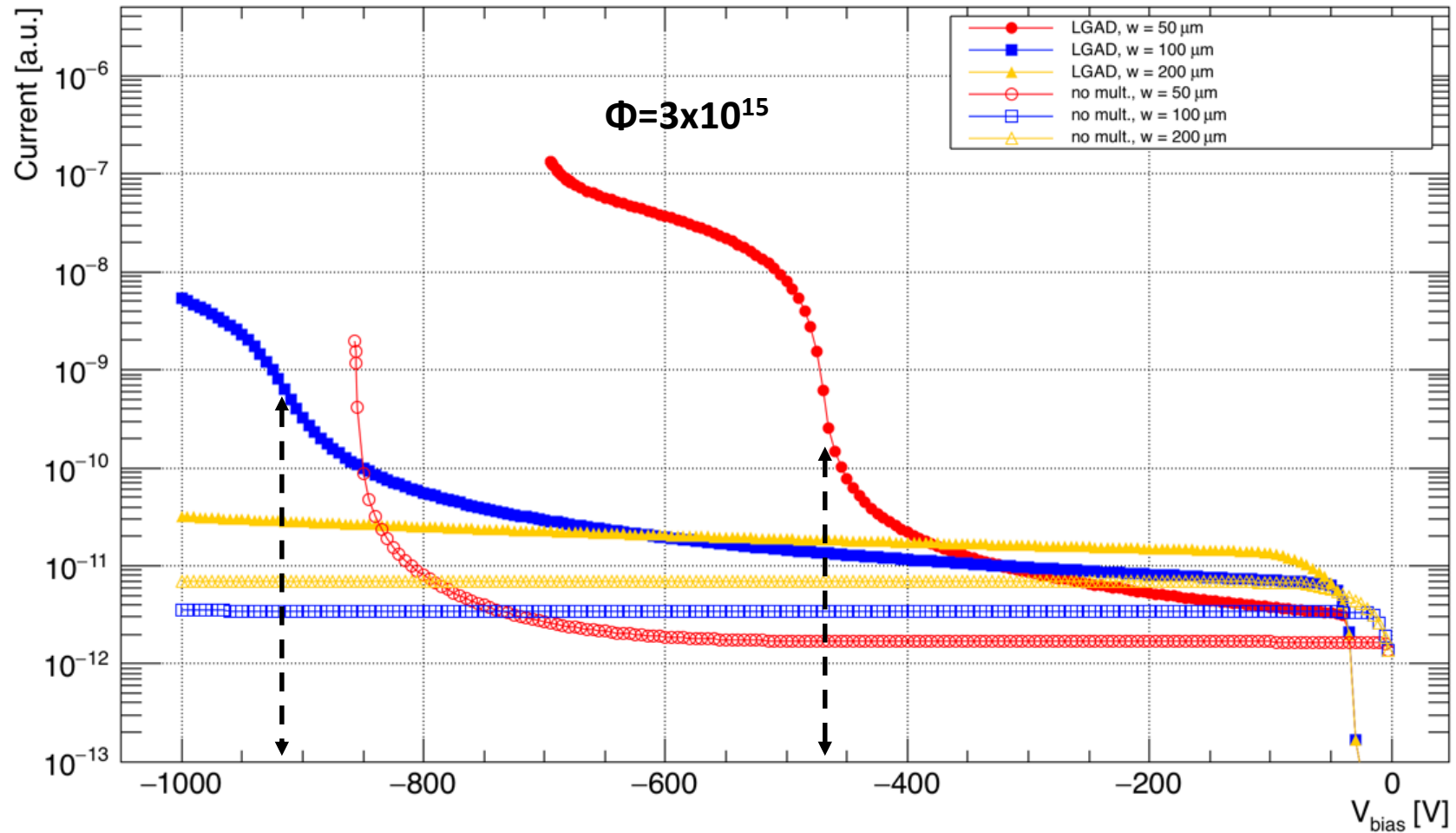
Breakdown in thin irr. LGAD and ref.



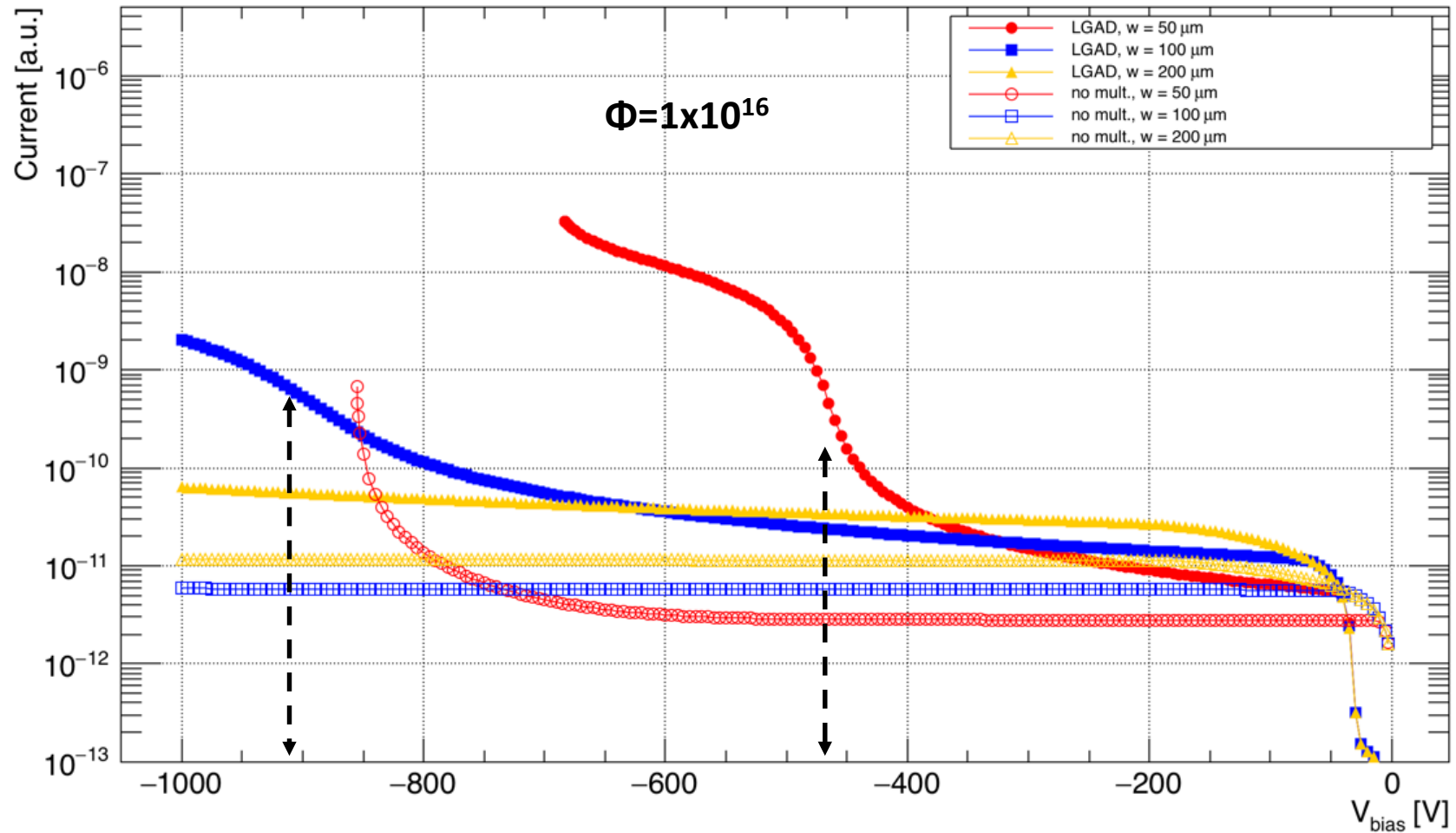
Signal vs time, different thicknesses



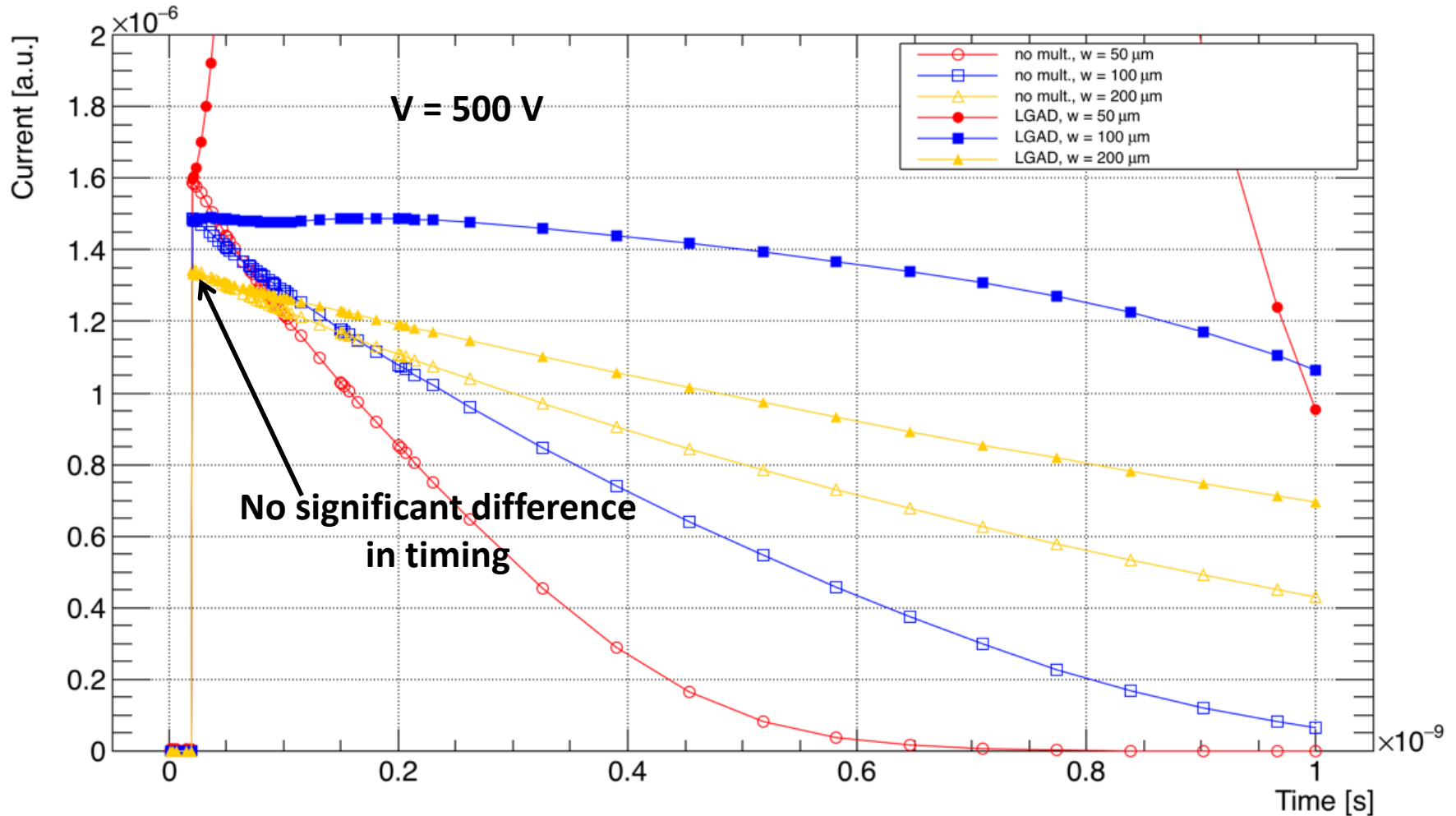
Breakdown in thin irr. LGAD and ref.



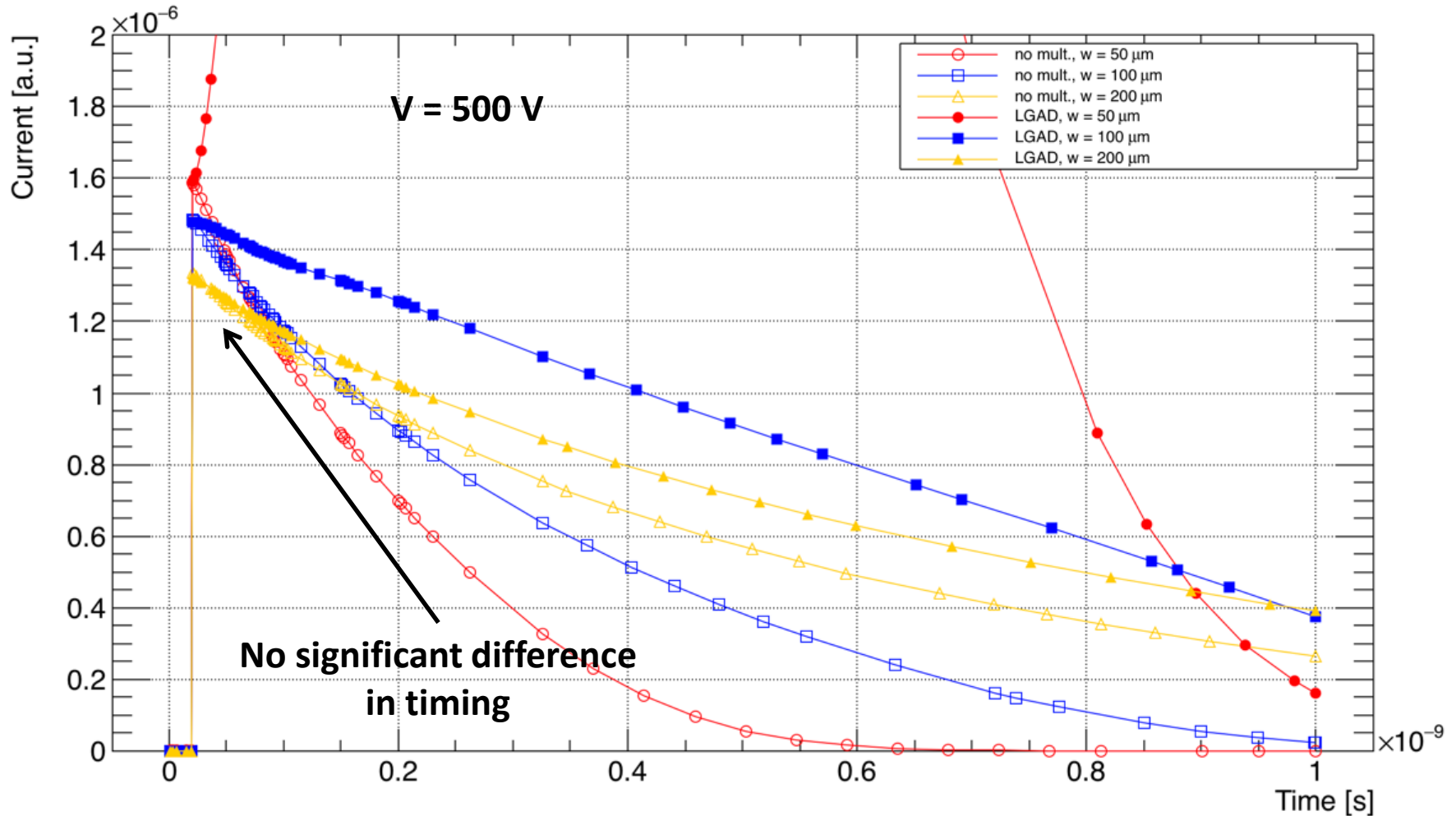
Breakdown in thin irr. LGAD and ref.



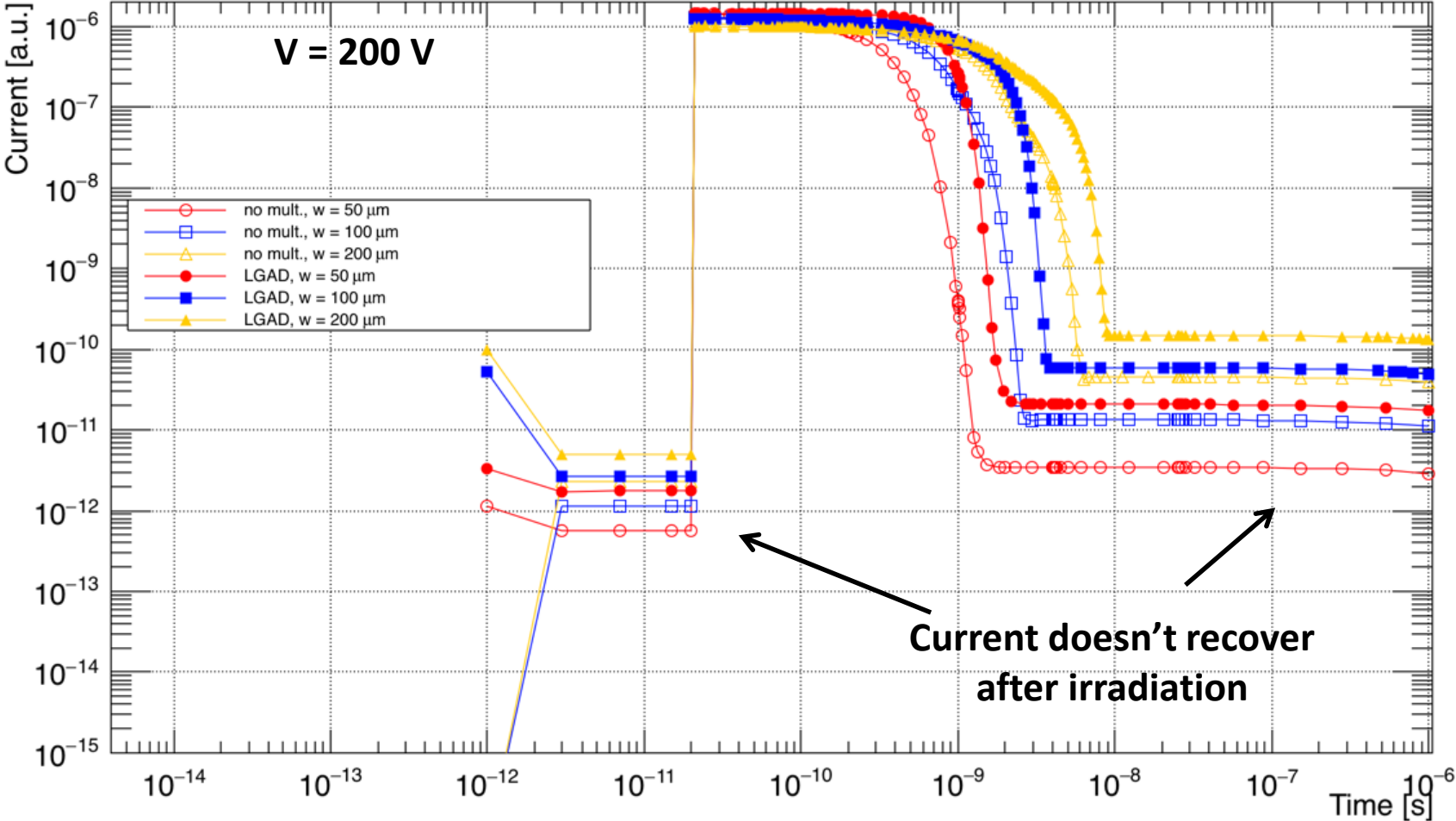
Simulation of irr. samples – $\Phi = 3 \times 10^{15}$



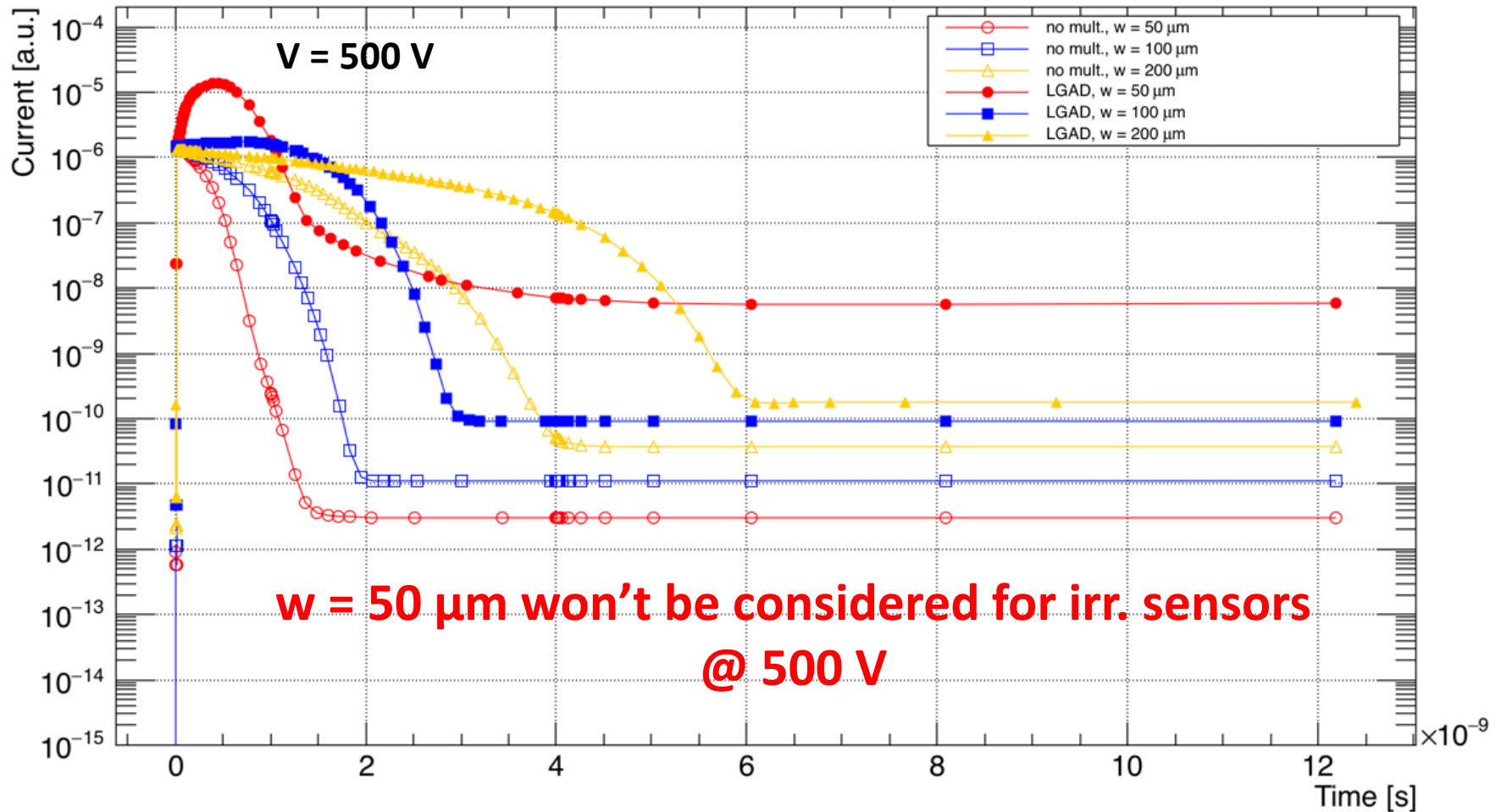
Simulation of irr. samples – $\Phi = 1 \times 10^{16}$



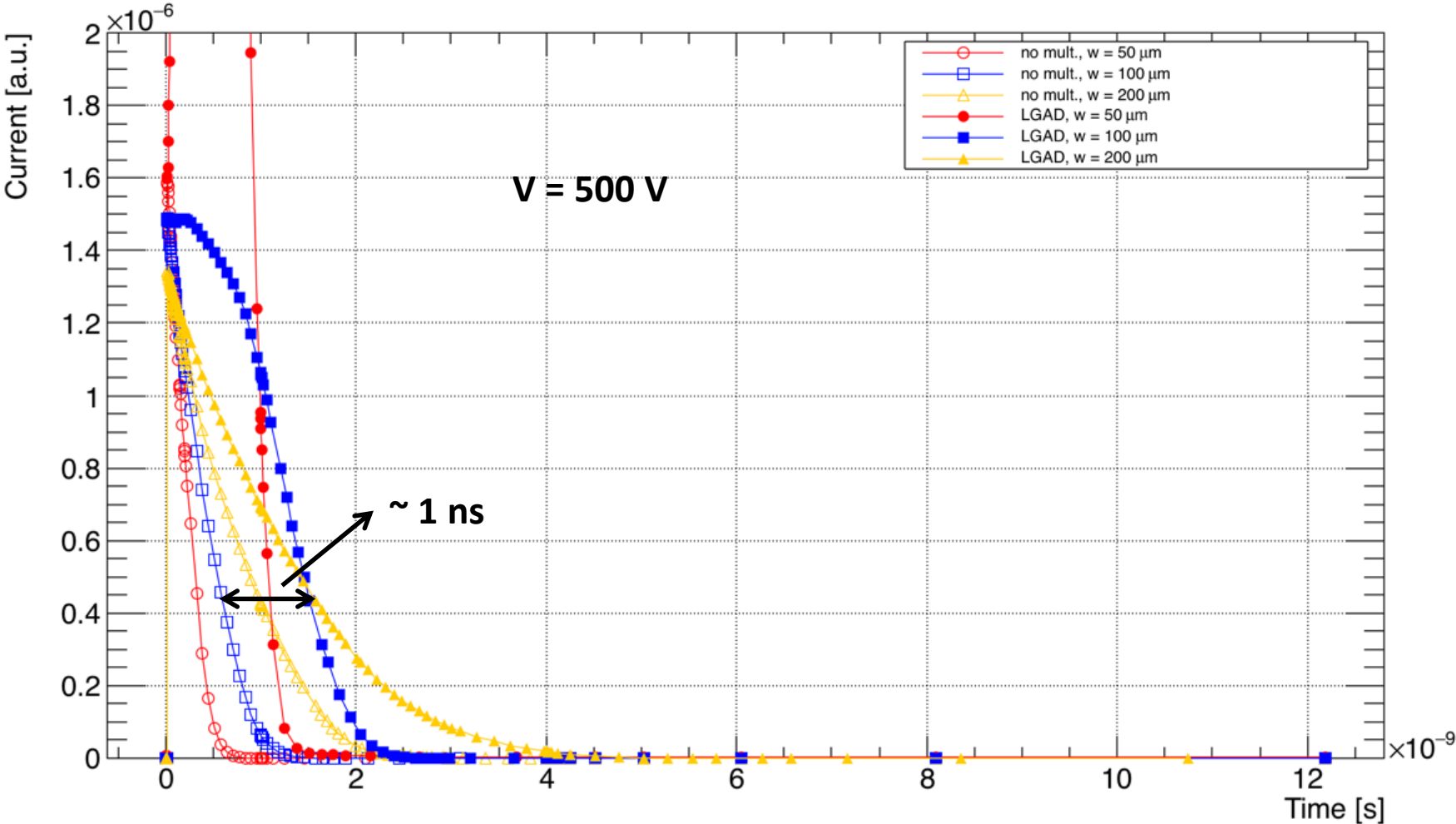
Signal of irr. samples – $\Phi = 1 \times 10^{15}$



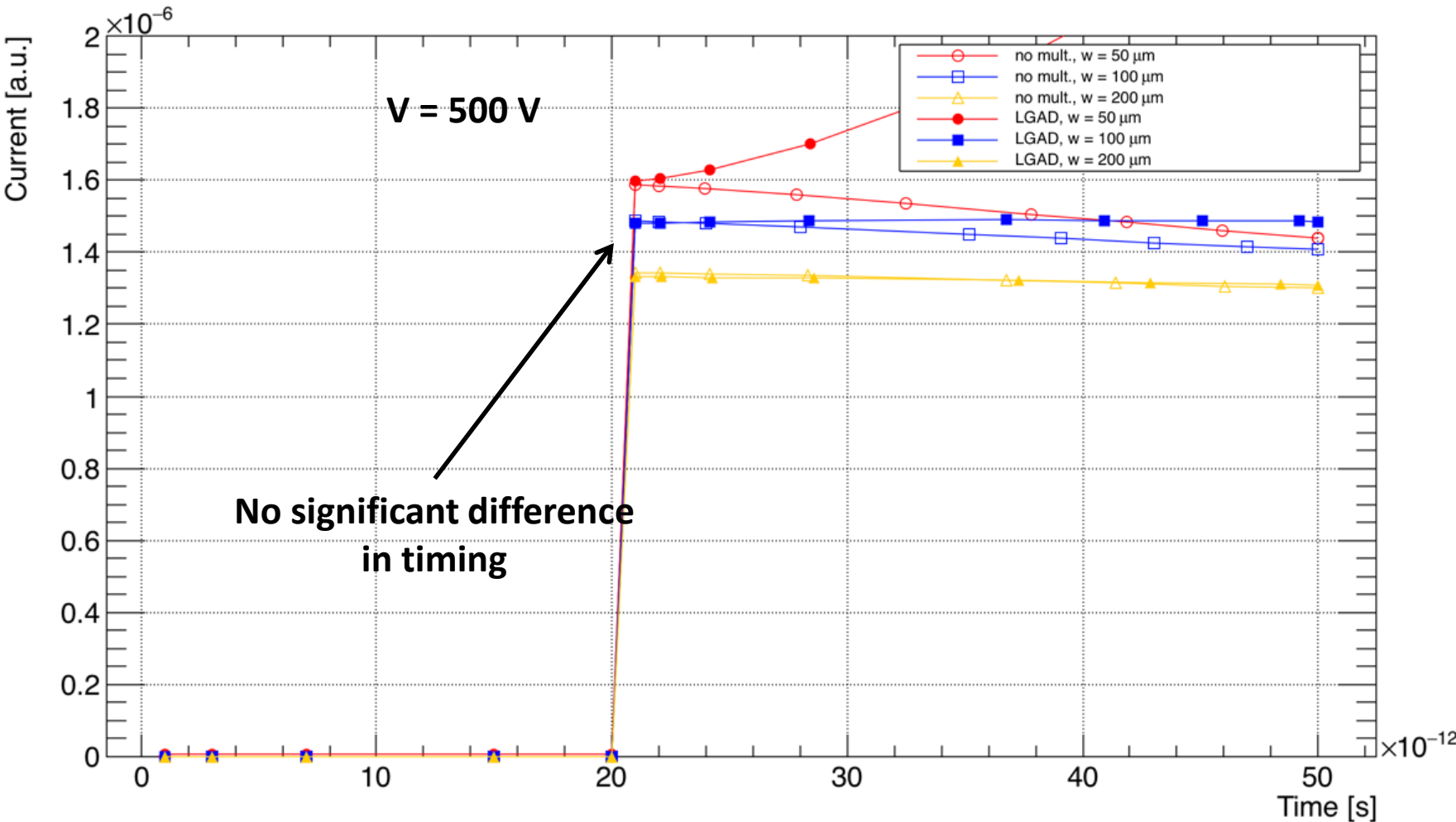
Simulation of irr. samples – $\Phi = 1 \times 10^{15}$



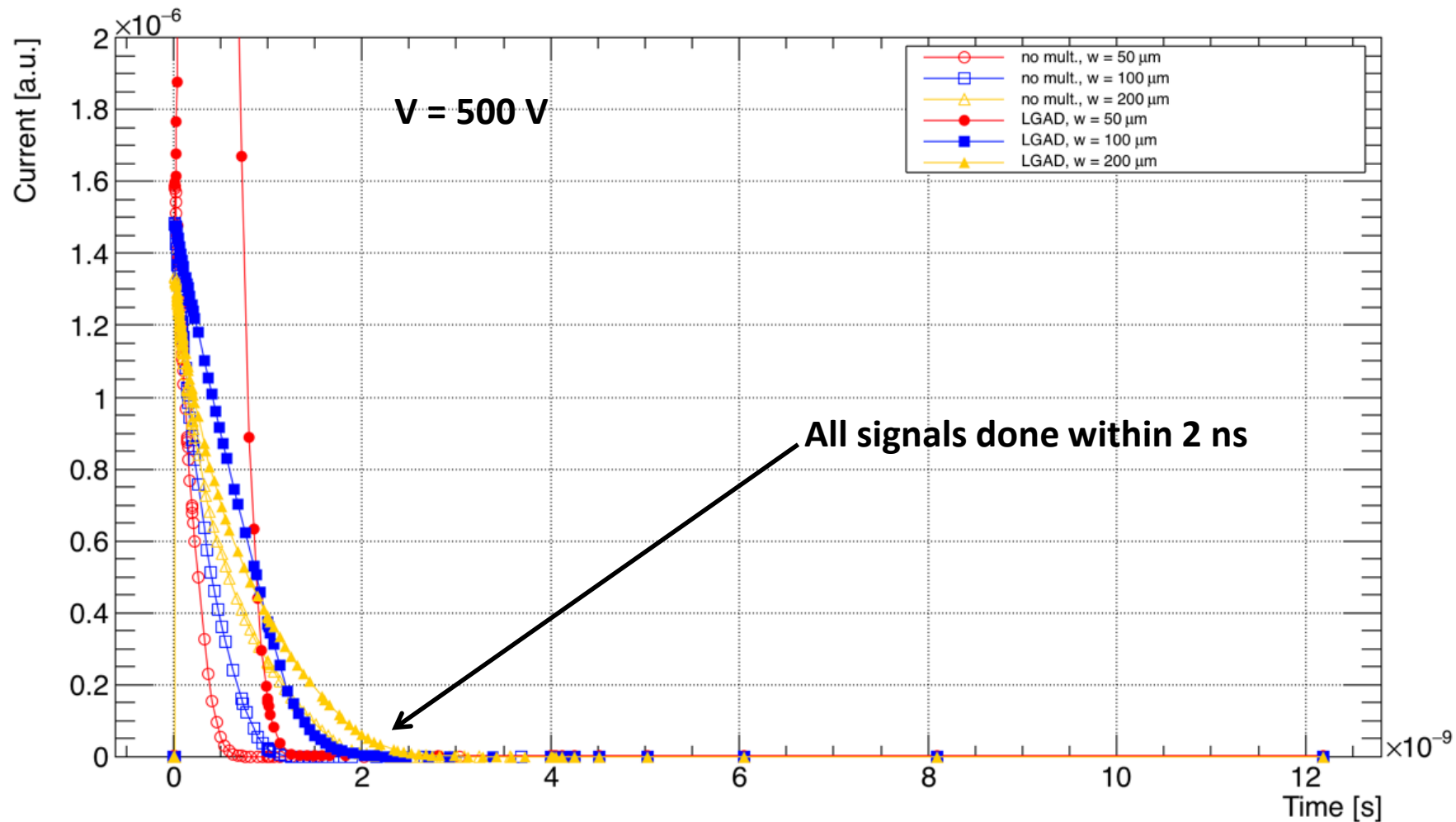
Simulation of irr. samples – $\Phi = 3 \times 10^{15}$



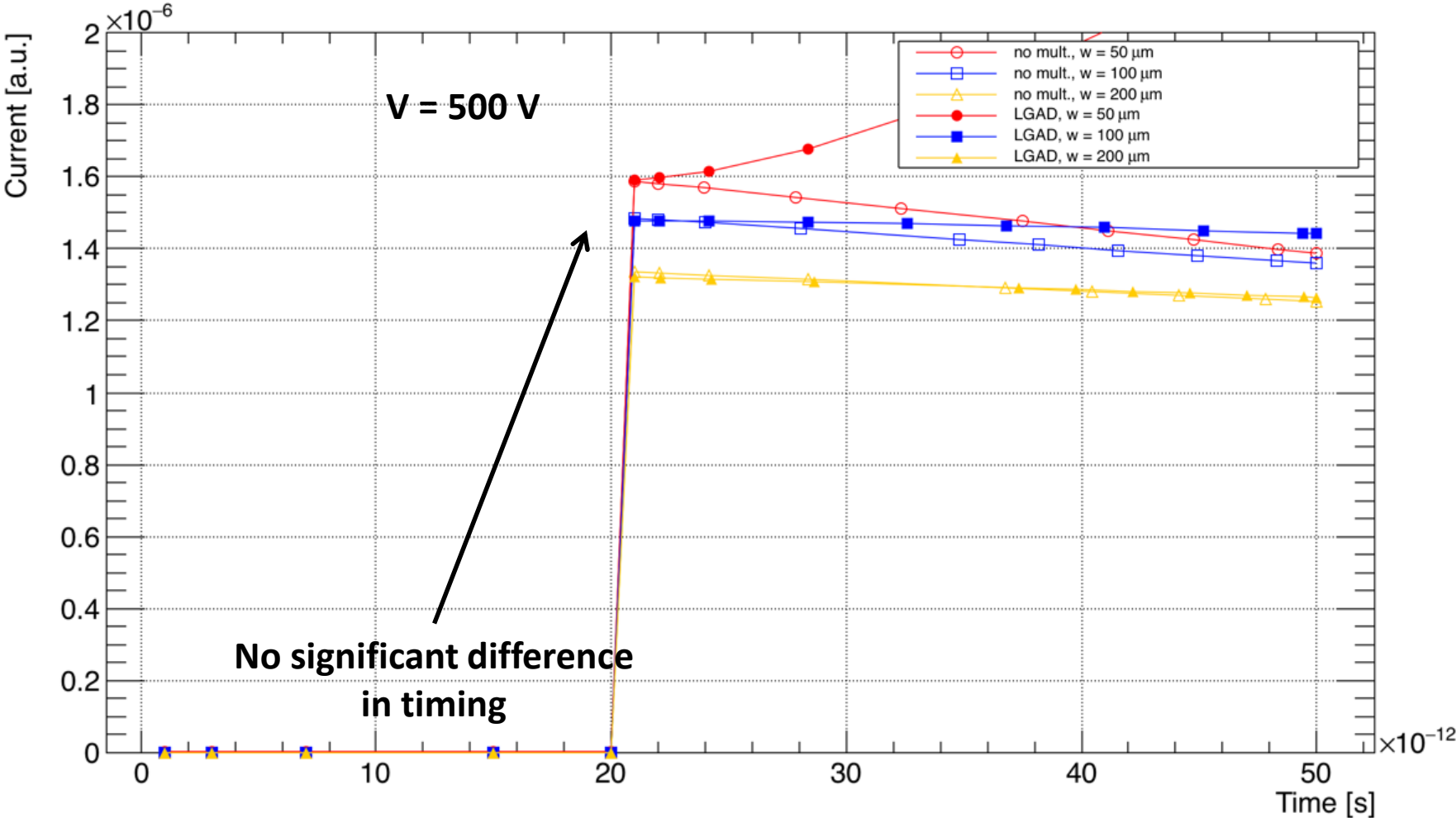
Simulation of irr. samples – $\Phi = 3 \times 10^{15}$



Simulation of irr. samples – $\Phi = 1 \times 10^{16}$

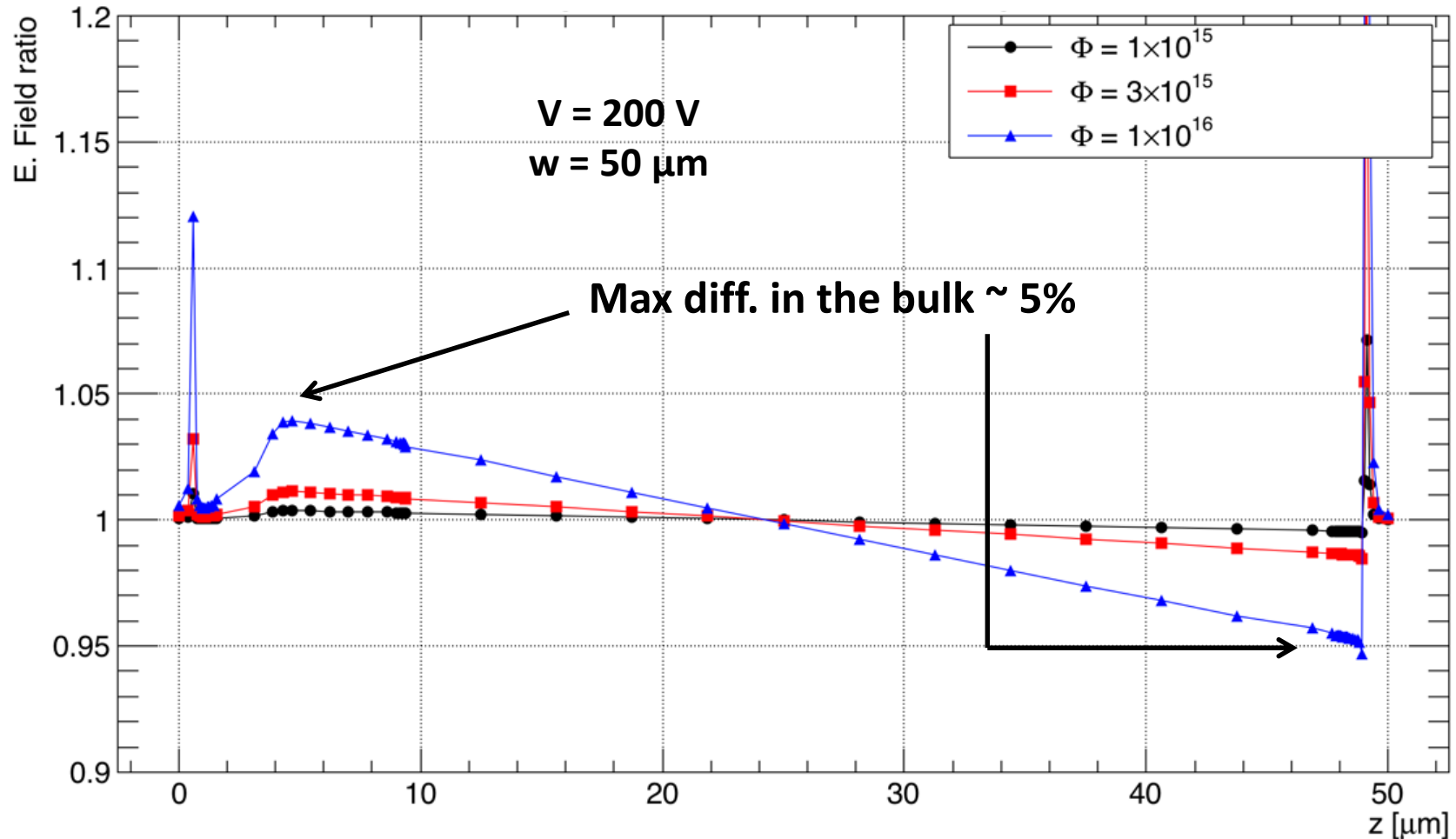


Simulation of irr. samples – $\Phi = 1 \times 10^{16}$



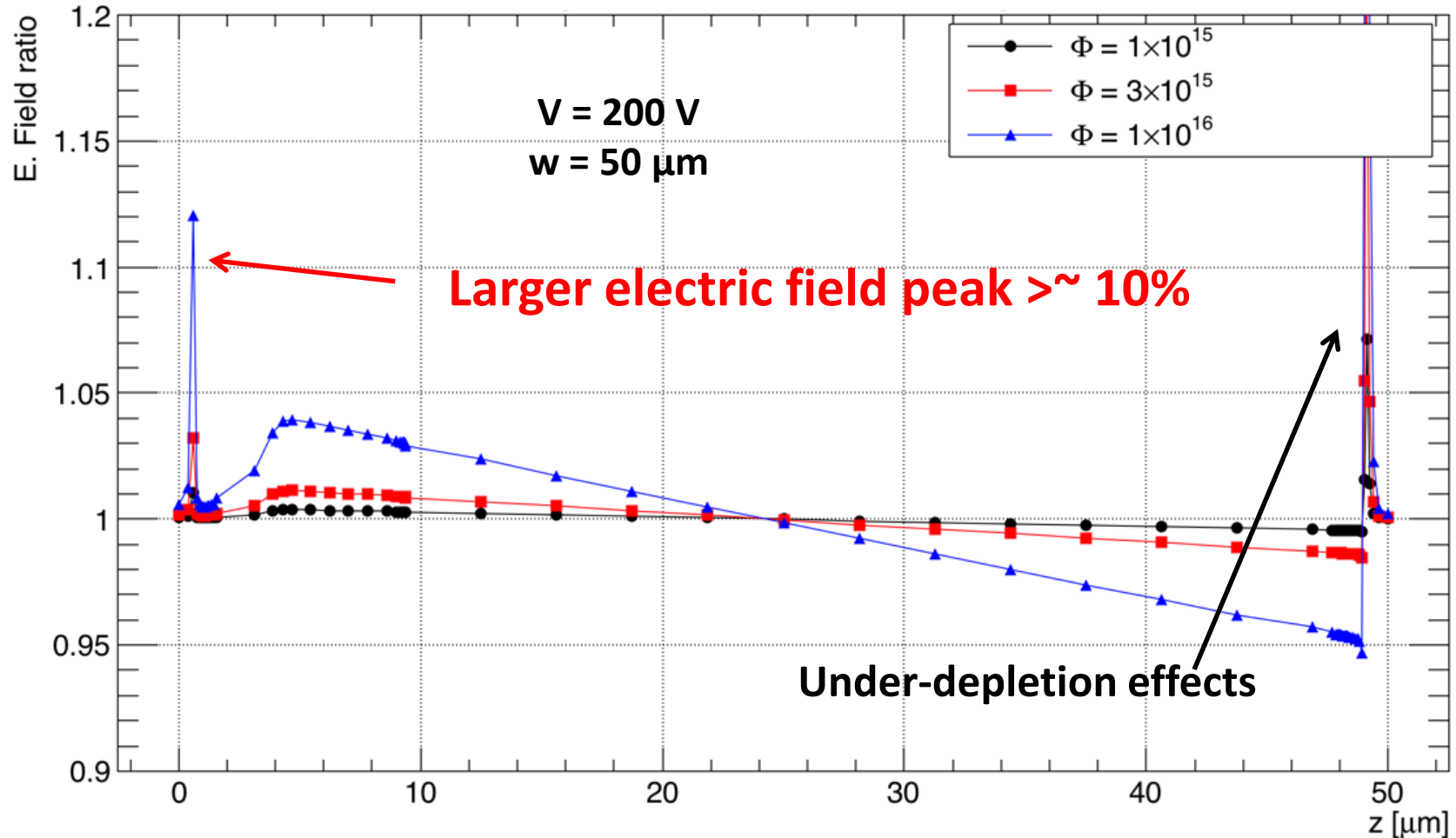
Ratio of electric field – LGAD only

E. Field normalized to E. Field($\Phi = 0$)

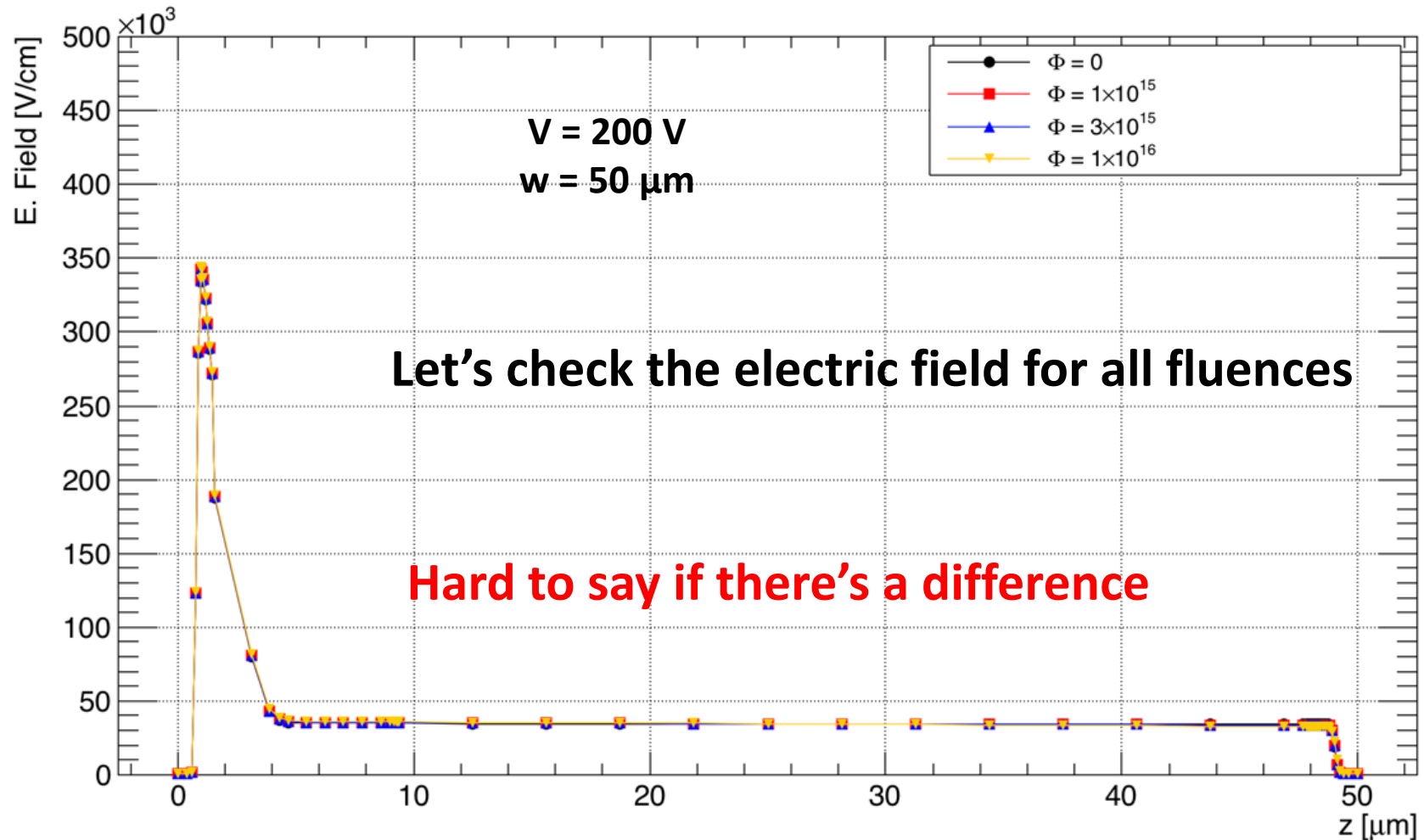


Ratio of electric field – LGAD only

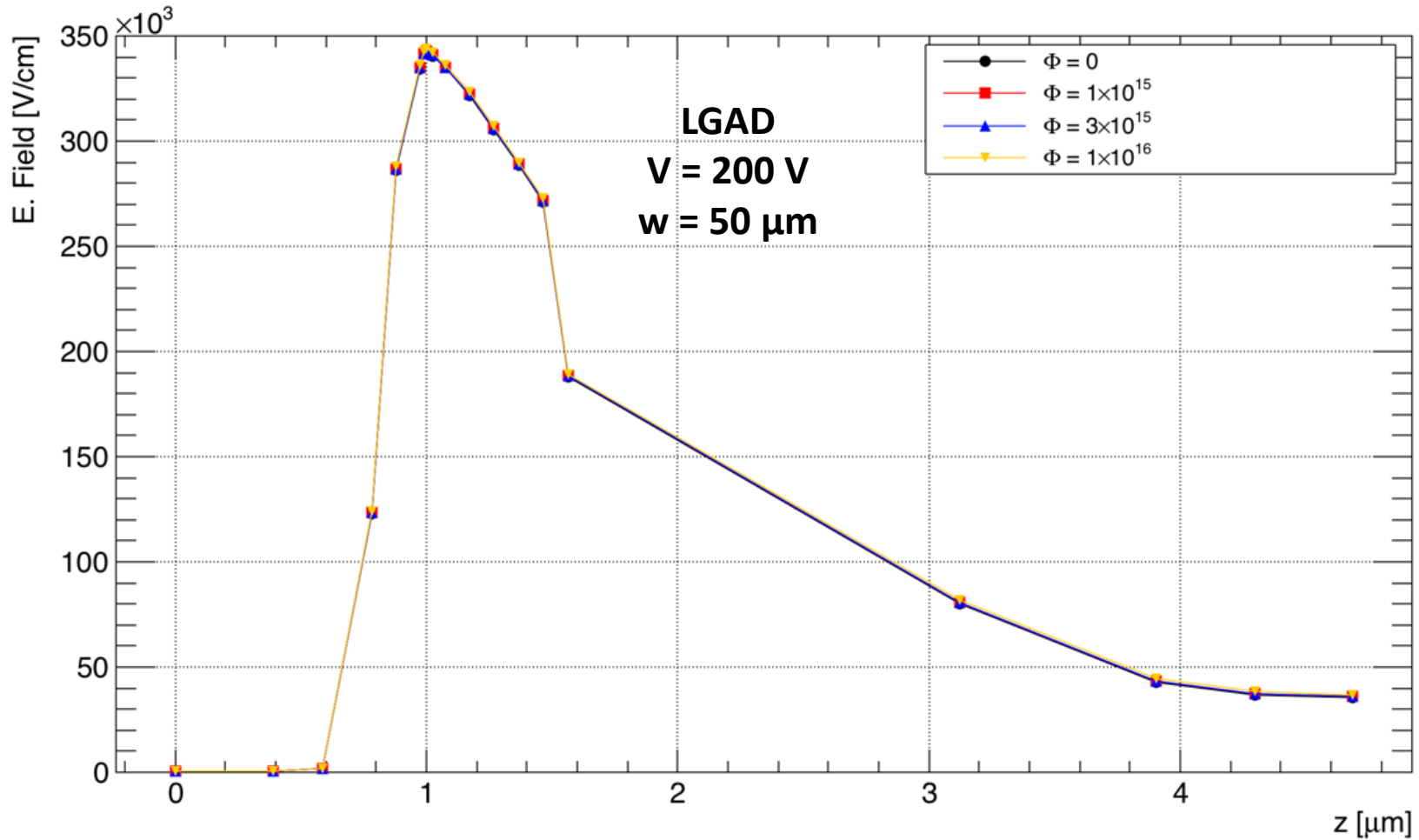
E. Field normalized to E. Field($\Phi = 0$)



Electric field for all fluences

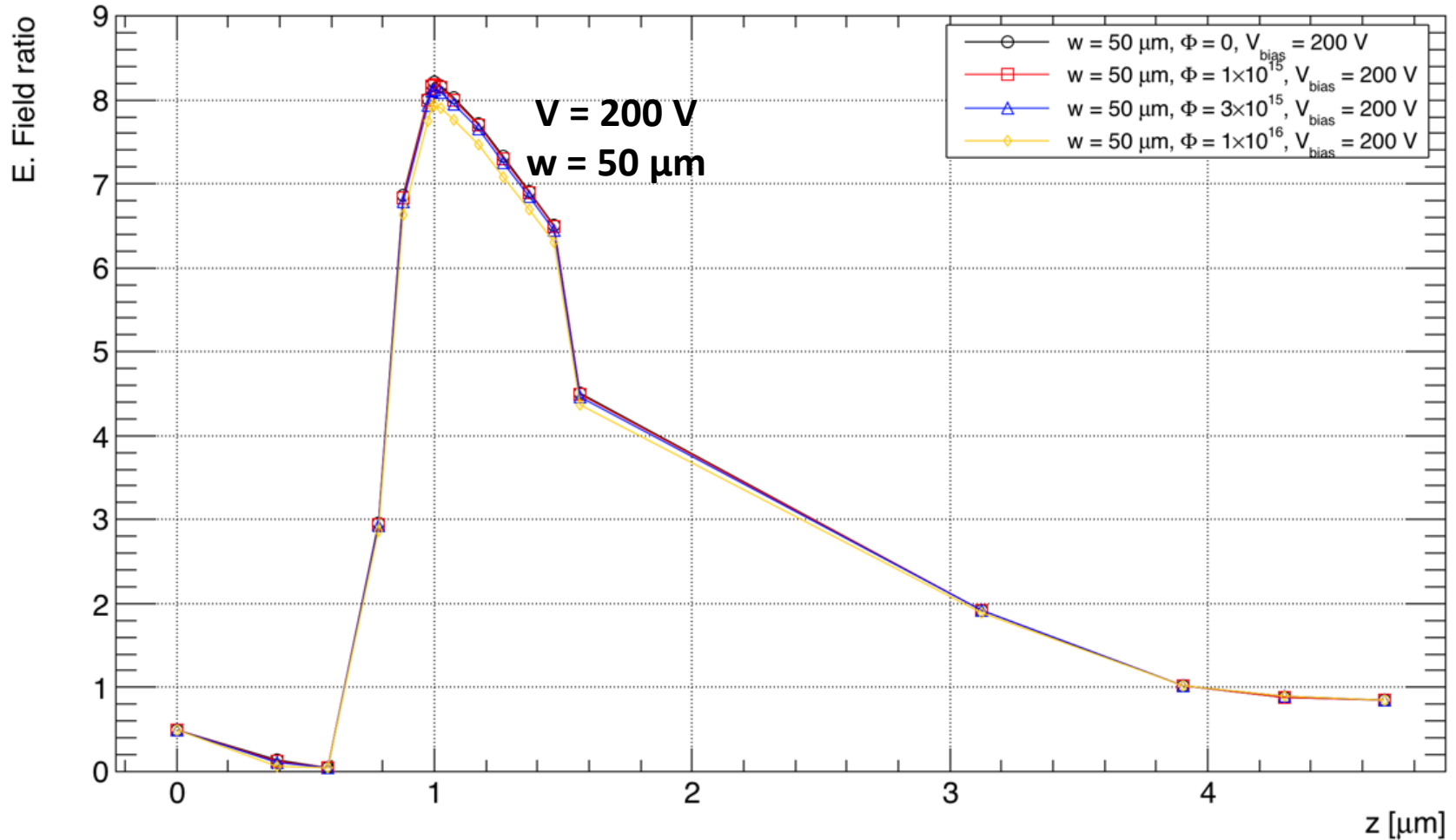


Electric field for all fluences



Electric field ratio

Electric field normalized to the reference detector



Electric field ratio

Electric field normalized to the reference detector

